

Structural Correlation and Magnetic Effects in Ferecrystalline Materials

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"What are the three most important rules of the chemist?" This I knew from Ben. "Label clearly. Measure twice. Eat elsewhere." Patrick Rothfuss, The Name of the Wind

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Abstract

Nanolaminates are an excellent model system to study the correlation of structural and magnetic disorder in magnetic nanomaterials in one dimension because they offer precise control over the structure on a sub-Ångström length scale. Ferecrystals are nanolaminate compounds of the misfit-layer family with the general formula $[(MSe)_{1+\delta}]_m(TX_2)_n$ (M = Pb, Sn, Bi, or rare earth metal; X = S, Se, Te; T = transition metal) where the individual constituents are stacked and rotationally disordered along the *c*-axis. Since *m* and *n* are tunable, they are excellent candidates to systematically investigate surface and finite size-induced structural distortions in nanomaterials.

Detailed knowledge of the atomic structure and the structural correlation of nanomaterials is essential to predict and explain structure-property relations. Reciprocal space maps revealed interlayer correlations in ferecrystals with the structure $[(MSe)_{1+\delta}]_1(TSe_2)_1$ opposed to the typical observed turbostratic disorder. Those results suggest that preferential nucleation and layer alignment during nucleation occur in ferecrystals and show that, at least for some 1:1 ferecrystals, ordered domains are present.

Moreover, a new set of ferecrystalline materials with the general structure $[(Cu_x Cr_y Se_z)_{1+\delta}](NbSe_2)_n$ has been prepared. By varying the annealing temperature of these compounds, it was possible to form four different heterostructures. This is the first set of ferecrystals which gives access to multiple heterostructures by varying the annealing temperature. The different heterostructures have been analyzed by out-of-plane and in-plane diffraction as well as STEM/EDX imaging.

Rietveld refinements have been used with different starting models to gain better understanding of the structure in the $Cu_x Cr_y Se_z$ layer. The $Cu_x Cr_y Se_z$ layer was best described by a symmetric variation of $CuCrSe_2$ structure. Also the effect of the annealing temperature on the atomic layering and site occupancies has also been investigated via Rietveld refinement. By replacing traditional MX rock salt with a $\text{Cu}_x \text{Cr}_y \text{Se}_z$ layer, the first magnetic ferecrystals have been prepared. The $\text{Cu}_x \text{Cr}_y \text{Se}_z$ layer serves as the magnetic constituent and is separated by layers of a nonmagnetic 'spacer' constituent (NbSe₂). Macroscopic magnetization measurements revealed a significant magnetic moment despite the only small magnetic volume. By tuning the number of spacer layers, we can systematically alter the magnetic properties of the ferecrystals and investigate the magnetic interlayer coupling with n.

Kurzzusammenfassung

Nanolaminate sind ein exzellentes Modellsystem, um Korrelationen von struktureller und magnetischer Unordnung in eindimensionalen magnetischen Nanolaminaten zu untersuchen, da sie eine präzise Kontrolle der Struktur auf atomarer Größenordnung ermöglichen. Ferekristalle sind Nanolaminate aus der Familie der Misfit-Verbindungen und haben die allgemeine Strukturformel $[(MX)_{1+\delta}]_m(TX_2)_n$ (M = Pb, Sn, Bi, oder Metall der seltenen Erden; X = S, Se, Te; T = Übergangsmetall). Die einzelnen Bestandteile MX und TX₂ sind entlang der c-Achse übereinander angeordnet, jedoch in der Ebene turbostratisch verdreht. Da *m* und *n* beliebig variiert werden können, sind Ferekristalle ein exzellenter Kandidat für systematische Untersuchungen von Oberflächeneffekten sowie strukturellen Fehlordnungen aufgrund von Effekten der begrenzten Ausdehnung in Nanomaterialien.

Detaillierte Kenntnisse über die atomare Struktur und strukturelle Wechselwirkungen sind ein wichtiger Schritt, um strukturell bedingte Eigenschaften zu erklären und vorherzusagen. Reziproke Gitterkarten zeigen für $[(MSe)_{1+\delta}]_1(TSe_2)_1$ strukturelle Wechselwirkungen zwischen den Schichten, was im Gegensatz zu der normalerweise beobachteten turbostratischen Verdrehung steht. Diese Ergebnisse deuten an, dass eine bevorzugte Nukleation und eine Ausrichtung der Schichten während der Nukleation stattfinden und zeigen, dass zumindest in manchen 1:1 Ferekristallen geordnete Domänen vorhanden sind.

Ein neues Set ferekristalliner Materialen mit der allgemeinen Strukturformel $[(Cu_xCr_ySe_z)_{1+\delta}]_1(NbSe_2)_n$ wurde erfolgreich hergestellt. Durch Variation der Glühtemperatur ist es möglich, vier verschiedenen Heterostrukturen zu bilden. Dies sind die ersten Ferekristalle, die durch Variation der Glühtemperatur verschiedenen Heterostrukturen bilden. Die verschiedenen Heterostrukturen wurden mittels Röntgendiffraktion in und außerhalb der Ebene sowie durch STEM/EDX Abbildungen untersucht.

Verschiedene Startmodelle wurden genutzt, um mittels Rietveld-Methode ein besseres Verständnis über die Struktur in der $Cu_x Cr_y Se_z$ -Schicht zu erhalten. $Cu_x Cr_y Se_z$ lässt sich am besten durch eine symmetrische Variation der CuCrSe₂ Struktur beschreiben. Der Einfluss der Glühtemperatur auf die atomare Struktur und Besetzung wurde ebenfalls mittels Rietveld-Methode untersucht.

Durch Ersetzen der Kochsalzverbindung MX mit einer $Cu_x Cr_y Se_z$ -Schicht konnten die ersten magnetischen Ferekristalle hergestellt werden. Hierbei dient die $Cu_x Cr_y Se_z$ -

Schicht als magnetische Komponente und wird durch eine nichtmagnetische Trennschicht (NbSe₂) separiert. Makroskopische Magnetisierungsmessungen zeigen ein signifikantes magnetisches Moment, obwohl die Proben ein sehr kleines magnetisches Volumen besitzen. Durch Variation der Trennschicht Wiederholungseinheit n konnte eine systematische Variation der magnetischen Eigenschaften erzielt werden. Der Zusammenhang von magnetischen Wechselwirkungen zwischen den Schichten und nwurde untersucht.

Contents

Ab	Abstract			
Κι	Irzzu	sammenfassung	v	
1. Introduction				
2.	Scie	ntific aims	4	
3.	Theory			
	3.1.	Ferecrystals	6	
	3.2.	MER method	7	
	3.3.	Crystal structure of $CuCr_2Se_4$	9	
	3.4.	Structure of transition metal dichalcogenides	11	
	3.5.	X-ray and neutron reflectometry	13	
		3.5.1. Polarized neutron reflectometry	18	
4.	Interlayer correlations in 1:1 ferecrystals			
	4.1.	Introduction and aims	20	
	4.2.	Evidence of interlayer correlation	20	
	4.3.	Higher order reflections	25	
	4.4.	Reciprocal space maps along MSe and TSe_2 reflection series $\ldots \ldots$	26	
	4.5.	Potential candidates for interlayer correlations	29	
	4.6.	Summary	34	
5.	$[(Cu_xCr_ySe_z)_{1+\delta}]_1(NbSe_2)_3$ ferecrystals			
	5.1.	Introduction and aims	36	
	5.2.	Sample calibration and preparation	36	
	5.3.	Annealing study	39	
	5.4.	Heterostructure formation in a broader set of samples	42	
	5.5.	Structural investigation of the in-plane structure	46	
	5.6.	Scanning transmission electron microscopy	48	
	5.7.	Summary	53	
6.	Stru	ctural investigation of the $Cu_x Cr_y Se_z$ constituent	56	
	6.1.	Introduction and aim	56	
	6.2.	Comparison of different models for the $Cu_x Cr_y Se_z$ layer	56	

	6.3.	Struct	ural differences in heterostructure A and B	63		
	6.4.	Prepar	cation of $[(Cu_x Cr_y Se_z)_{0.5}]_{1+\delta}(NbSe_2)_3$	65		
	6.5.	Struct	ure of $[(\mathrm{Cu}_x \mathrm{Cr}_y \mathrm{Se}_z)_{0.5}]_{1+\delta}(\mathrm{NbSe}_2)_3 \ldots \ldots$	66		
	6.6.	Summ	ary	68		
7.	[(Cu	ı _x Cr _y Se	$[e_z)_{1+\delta}]_1$ [NbSe ₂] $_n$ ferecrystals	70		
	7.1.	Introd	uction and aims	70		
	7.2.	Sample	e preparation \ldots	70		
	7.3.	Struct	ural investigation of set 3 with $n = 1 - 5 \dots \dots \dots \dots$	70		
	7.4.	Magne	etic Properties of $CuCr_2Se_4$, $CuCrSe_2$, and $CrSe_2$	73		
	7.5.	Macros	scopic magnetization	75		
	7.6.	Polariz	zed neutron reflectometry	81		
	7.7.	Summ	ary	83		
8.	Con	clusion	and summary	86		
9.	Exp	perimental section				
	9.1.	Sample	e preparation	88		
	9.2.	Instru	ments	88		
		9.2.1.	Bruker AXS D8	88		
		9.2.2.	ID03	89		
		9.2.3.	ВМ-33-С	89		
		9.2.4.	Electron probe microanalyzer	90		
		9.2.5.	XRF	90		
		9.2.6.	MARIA	90		
		9.2.7.	STEM	91		
		9.2.8.	STEM and EDX at PNNL	91		
		9.2.9.	STEM and EDX at ER-C	91		
		9.2.10.	SQUID	92		
	9.3.	Progra	ums	93		
		9.3.1.	Layer thickness	93		
		9.3.2.	aps slicereduce	93		
		9.3.3.	Le Bail fits and Rietveld refinements	93		
		9.3.4.	Fits	93		
		9.3.5.	Refinement of X-ray reflectivity data	94		
		9.3.6.	Diamond	94		

Ap	Appendix 96		
Α.	Interlayer correlations in 1:1 ferecrystals	96	
	A.1. Le Bail and Rietveld refinement	96	
	A.2. Reciprocal space maps and Gaussian fits	102	
	A.3. X-ray diffraction patterns of ferecrystals with m, n $\neq 1$ \hdots	104	
В.	$[(Cu_xCr_ySe_z)_{1+\delta}]_1(NbSe_2)_3$ ferecrystals	106	
	B.1. Total thickness and c-lattice parameter of the 1:3 samples \ldots .	106	
	B.2. Le Bail fit of $hk0$ data \ldots	107	
	B.3. XRF data of 1:3 data	109	
С.	Structural investigation of the $Cu_x Cr_y Se_z$ constituent	110	
	C.1. Rietveld refinement of 1:2 sample of set 3 annealed at 350 $^{\circ}\mathrm{C}$	110	
	C.2. Le Bail fit and Rietveld refinement of $00l$ data of 1:3 samples of set 3 $$.	113	
	C.3. Le Bail fit and Rietveld refinement of $00l$ data of sample 6 $\ldots \ldots$	114	
	C.4. Le Bail fit of $hk0$ data of $6 \dots $	116	
D.	$[(Cu_xCr_ySe_z)_{1+\delta}]_1[NbSe_2]_n$ ferecrystals	118	
	D.1. <i>c</i> -lattice parameters	118	
	D.2. Le Bail fit of $hk0$ data \ldots	119	
	D.3. XRF data of $1:n$ data	125	
Ε.	Rebinning algorithm of aps slicereduce	126	
F.	Abbreviations	140	
Re	References 14		
Eid	desstattliche Erklärung	158	

1. Introduction

Thin films with nanosclae thickness have already been used in ancient Egypt for decorative coatings. They prepared leaf gold with 100 - 300 nm thickness to coat, for example, wood, papyrus, and metal objects.^[1] In 1903, Emil Broch handed in a patent for a transparent mirror using a thin metal film.^[2] Nowadays thin metal films are used to give materials a metal like appearance. Besides decorative coatings, thin films are usually used to modify surfaces and improve the properties of a substrate.^[3] Mechanical properties like the hardness can be improved with coatings of diamond like layers.^[4] Whereas thin film with a high hydrophilicity has an anti-fogging effect on the substrate.^[5]

In optical lenses, multiple alterations of the properties like low reflectance, physical durability, and high transmission are desired. These are achieved by stacking multiple thin films into a multilayer system.^[6] Multilayered nano films made of two or more materials are also called nanolaminates. Nanolaminates offer a large structural diversity and with that many properties that are not accessible with the corresponding bulk materials.^[7] Their improved or new chemical and physical properties make them potential materials for optical and electrical devices like X-ray optics,^[8,9] memory storage (thin film magnetic recording media),^[10–12] energy storage,^[13,14] gas,^[15,16] and moister^[17] diffusion barrier.

The individual layer thickness ranges between few Å and several tens of nm.^[7] To control and modify the properties of nanolaminates, a precise control of layer thickness, composition, and crystal structure is necessary. The thickness of the films influences properties like catalytic activity, gas absorption, and diffusion. In optoelectronic thin films, a high crystallinity is essential for optimal performance of the devices.^[18]

Magnetic nanomaterials are intensely investigated with fundamental as well as technological aspects due to their potential applications in catalysis, information technology, and medical applications.^[19–22] Their unique physical properties, including enhanced magnetic anisotropies and superparamagnetism, are closely related to finite size effects induced by the material surface.^[20] The nanoparticle magnetization is related to structural disorder leading to spin disorder, not only at the surface but also in the core of magnetic nanoparticles.^[23]

The modulated elemental reactants method (MER),^[24–26] established by Johnson *et al.*, enables the preparation of atomic scale precise films. The composition of prepared precursors is close to the desired product reducing the diffusion length and enabling the production of products that are kinetically stabilized.^[27] This enables the pro-

duction of heterostructures that are not accessible by usual inorganic synthesis.^[28] Ceder *et al.* proved, via the data-mined ionic substitution algorithm,^[29] that besides the observed polymorphs there are more than 10 potential polymorphs in rock salt compounds.^[30] The low diffusion ranges and annealing temperatures in the MER method have the potential to access various local free-energy minima. Therefore, ferecrystalline materials prepared by the MER method are ideal systems to prepare new heterostructures.

This work aims to investigate various multilayered materials prepared by the MER method and to prepare the first magnetic ferecrystals. The effect of correlation, stacking, composition, and annealing condition on the crystal structure and magnetic properties is the main object of this thesis.

2. Scientific aims

The present work is structured in four chapters. In the first part, the interlayer correlations in 1:1 ferecrystals are studied by reciprocal space mapping. Samples with $m \neq n \neq 1$ are analysed to find the origin of the interlayer registrations. Ferecrystals are generally rotationally disordered in plane.^[31,32] In contrast to that, recently studied m = n = 1 ferecrystals indicate directionally dependent interlayer registration.^[33] A detailed analysis of the structure by in-plane and out of-plane diffraction is provided.

The second part of this work focuses on $[(Cu_xCr_ySe_z)_{1+\delta}]_1(NbSe_2)_3$ ferecrystals. Johnson *et al.* showed that CuCr_2Se_4 thin films can be prepared by the MER method. New ferecrystalline materials were prepared by replacing the rock salt MX with CuCr_2Se_4 and inserting NbSe_2 as paramagnetic spacer. Here, a number of precursors were prepared with $n = 3 [(Cu_xCr_ySe_z)_{1+\delta}]_1(NbSe_2)_3$ to probe the potential formation of different heterostructures. Samples with different elemental composition of the $Cu_xCr_ySe_z$ layer were prepared. The elemental compositions of the different heterostructures are investigated by XRF. The effect of annealing time and temperature on the formation of different heterostructures is studied by in-plane and out of plane diffraction as well as STEM-EDX.

The objective of the third part is to solve the atomic layering in the $Cu_x Cr_y Se_z$ layer. Rietveld refinements using three potential atomic arrangements as starting models were performed. Which model is appropriate to describe the data, will be discussed. In a second step, the derived model is used to determine the change in structure by decreasing the annealing temperature from 400 to 350 °C.

the effect of the magnetic In the fourth part, layer separation in $[(\operatorname{Cu}_x \operatorname{Cr}_y \operatorname{Se}_z)_{1+\delta}]_1(\operatorname{NbSe}_2)_n$ with n = 1 - 5 is studied. The systematic variation of n provides the opportunity to study the impact of n on the structure and magnetic interlayer interactions. First, a detailed analysis of the systematic change in structure with n by out of-plane and in-plane diffraction is provided. The effect of n on the magnetic properties of $Cu_x Cr_y Se_z$ has been analyzed by temperature dependent magnetic susceptibility measurements, field dependent magnetization, and polarized neutron reflectometry.

3. Theory

3.1. Ferecrystals

Misfit layer compounds (MLC) are thermodynamically stable nano laminates of rock salt materials and dichalcogenides with the general structure $[(MSe)_{1+\delta}]_m (TSe_2)_n$ with M = Pb, Sn, Bi, or rare earth metal; X = S, Se, Te; T = transition metal, δ the misfit parameter (Figure 3.1, left).^[34] They are usually prepared in high temperature synthesis, making only energetically favourable products (m, n = 1 - 3) accessible. The c-axis of the multilayered material is normal to the constituent layers. The layers are aligned along the b-axis and do not have a commensurate a-axis, yielding a strained material with a complex superlattice structure. The incommensurate inplane structure leads to a difference in in-plane packing density, which is given by the misfit parameters δ . Due to the termination of the 3D rock salt structure, a puckering along (00*l*) is observed.^[35]

The stability of MLC is not yet understood as usually an alloy material would be expected to be more stable. There are three different theories explaining the stability of MLCs. The charge transfer between the constituent layers might result in ionic interaction.^[36–38] Another possibility is that interlayer covalent bonds are the source of the high stability.^[39–41] Ab initio electronic structure calculations showed that nonstoichiometric substitution of Ta into the PbS layer have a stabilizing effect.^[42]





Ferecrystals are MLC which are rotational disordered in-plane but like normal MLC

stacked along the c-axis (Figure 3.1).^[28,43] Due to the rotational disorder, the materials lack a 3D crystallinity and therefore are called ferecrystals (named after '*fere*' lat. for '*almost*'). Ferecrystals are prepared by the modulated elemental reactant (MER) method (chapter 3.2) and make a vast variation of m and n accessible.^[20,28,44] The binary layers are structurally non-interacting (*i.e.*, epitaxial strain-free) and thus can be regarded as individual nanostructures,^[45] whereas their coherent stacking enables application of electron microscopy and diffraction techniques towards investigation of their structural profile. Due to the preferred orientation along the c-axis, X-ray diffraction perpendicular to the film gives exclusively (00*l*) reflections and allows the determination of the *c*-lattice parameter. In-plane diffraction of ferecrystals give exclusive (*hk*0) reflections of the two constituent phases because of the turbostratic disorder.

3.2. MER method

Ferecrystalline materials are prepared by a physical vapour deposition (PVD) named modulated elemental reactant (MER) method^[26,44] using a custom-built physical vapour deposition chamber by *Thermionic*.^[25] A schematic sketch of the used chamber can be seen in Figure 3.2.



Figure 3.2: Schematic representation of the deposition chamber used. Se effusion cell (1), electron guns (2), crystal monitor (3), sample carousel (4), motor (5) and sample (6). (Modified from M. Anderson, University of Oregon, 2011.)^[46]

The chamber is operated with a pressure of $7 \cdot 10^{-5}$ to $7 \cdot 10^{-6}$ Pa which is achieved by a cryogenic pump. The selenium source material is evaporated with an effusion cell, chromium, niobium, and copper are evaporated with electron guns (1 and 2 in Figure 3.2). For chromium a bending magnet raster is used to expand the lifetime of the source material as chromium does not melt but sublimates. Therefore the electron

beam creates a hole in the source material. The choice of the source form has a large impact on the reproducibility of the chromium samples. A good source material requires a smooth surface and has to be slightly convex in shape. (100) silicon can be used as substrate and is placed in a motorized carousel which can be rotated above the sources (4 and 6 in Figure 3.2). Pneumatic shutters are used as a physical barrier between source and substrate, (Figure 3.3). With the aid of quartz micro balances (crystal monitor) (3 in Figure 3.2) the deposition rate is determined. Thickness values which are monitored by the crystal monitor are not accurate A values and therefore are referred to as Fåkestroms (Få). The rates are usually in the range of 0.2 - 0.5 Få. The crystal monitor (3 in Figure 3.2) and the substrate (6 in Figure 3.2) can not have the same orientation to the source (1 and 2 in Figure 3.2). These geometry variations result in different amounts of atoms hitting the substrate than the crystal monitor and are represented by the tooling factor. By keeping a constant deposition rate and controlling the opening times of the shutters, the amount of deposited material can be controlled. A custom-made LabVIEW program controls the deposition rates of the electron guns by the supplied energy, the movement of carousel, the opening times of shutters, and the deposited sequence. After deposition, the system is flushed with nitrogen until the chamber has atmospheric pressure. After sample exchange and optionally source replacement the chamber is pumped to vacuum for the deposition of the next set of samples.



Figure 3.3: Schematic representation of the shutter system.

The nucleation is the rate determining step in the MER method.^[24,31,47] The layering of the deposited elements has to mimic the desired product. As the precursors layering and atomic composition is close to the product only low energies are needed to form the desired product. If the precursor has a high deviation in atomic layering and composition then more energy would be necessary to form the compound. On this way it is possible to form metastable compounds if the energy for the nucleation is below the energy which is needed for a rearrangement and the formation of a thermodynamic stable compound.^[24] A precise precursor calibration allows the MER method the formation of compounds that are not accessible by a classic synthesis,^[48] *i. e.*, a kinetic control of solid state synthesis.^[49]

The deposition order for $[(MX)_{1+\delta}]_m(TX_2)_n$ would be X-M-X-T, with M = Pb, Sn, Bi, or rare earth metal; X = S, Se, Te; T = transition metal. If TX₂ is more oxidation sensitive than MX the order can be reversed. The layers need to contain roughly the right amount of atoms per subunit. For preparation of such sample, slight selenium excess is usually used as typical annealing temperatures are above the evaporation temperature of selenium.^[43] The modulated precursors have atomically thin layers with a low degree of crystallinity already in the as deposited material.^[47] The order has to be repeated until the desired total thickness is achieved. To change *m* or *n* only the number of layer in deposition order has to be changed without further calibration.^[44] Different arrangements of *m* and *n* give theoretically access to over 20.000 different compounds with *m* and $n \leq 10$.^[28]

Johnson *et al.* prepared $[(M1Se)_{1+\delta}]_m[(T1Se_2)_{1+y}]_n[(M2Se]_{1+\delta}]_m(T2Se_2)_n$ samples with three different constituent layers $(M1 \neq M2 \text{ or } T1 \neq T2)$ increasing the amount of possible compounds to 130 million.^[27,50,51] Doping the T-Se or M-Se layer with another T or M allows the alteration of electrical properties.^[52-55] Therefore the MER method allows the preparation of theoretical designed highly complex structures that have enhanced properties.

3.3. Crystal structure of CuCr₂Se₄

CuCr₂Se₄ crystallizes in a normal cubic spinel structure $(Fd\bar{3}m)$ with an *a*-lattice parameter of 10.337(6) Å.^[56] The tetrahedral sites are occupied by copper and ¹/₈ filled (Figure 3.4, left). Chromium occupies the octahedral sites (¹/₂ filled, Figure 3.4, right).

Previous work showed that CuCr_2Se_4 has a preferred orientation in thin films (Figure 3.5, left), with the [111] direction perpendicular to the substrate.^[46,57–59] The cleavage surface of CuCr_2Se_4 is also the $(111)^{[60]}$ plane, indicating a low surface energy for (111). Twins tend to nucleate off the (111) plane^[61] of CuCr_2Se_4 . The growth parallel to a twin plane is energetically favourable.^[62]

For analysis of (hk0) data, we transformed the cubic structure into the hexagonal subgroup $R\bar{3}m$ (Figure 3.5, right). Due to the transformation, the *c*-lattice changes to $\sqrt{3}c = 17.84$ Å. The atomic positions and lattice parameters for the cubic space group and hexagonal transformation are given in Table 3.1.

Diffusions of niobium through the selenium layer is slow, preventing the formation of



Figure 3.4: Spinel structure of $CuCr_2Se_4$ Cu sits within the tetrahedral sites (left) and Cr within the octahedral sites (right). For clearness not all octahedral sites are drawn.^[56]



Figure 3.5: Spinel structure of $CuCr_2Se_4$ along the [111] (left) with filled coordination sphere and marked (blue) are for hexagonal transformation (middle). Hexagonal projection of $CuCr_2Se_4$ view along b-axis (right).

higher order product.^[63] Gupta *et al.* found that, at low reaction temperatures below $300 \,^{\circ}$ C, the formation of CuCrSe₂ is favoured as opposed to CuCr₂Se₄.^[64]

As copper diffusion is a known issue,^[65,66] especially in thin films,^[67–69] controlling the copper content in the CuCr₂Se₄ layer is challenging and the copper content in the crystalline CuCr₂Se₄ layer might be lower than in the precursor. The phase diagram of CuCr₂Se₄ and CuCrSe₂ (Figure 3.6) shows that with increasing copper content the formation of CuCrSe₂ is more likely.

	$Fd\bar{3}m$	Wyckoff	$R\bar{3}m$	Wyckoff
c [Å]	10.377(6)		17.84	
a [Å]	= c		7.31	
Cu1	$1/8 \ 1/8 \ 1/8$	8a	$0 \ 0 \ ^{1}/8$	6c
Cr1	$1/2 \ 1/2 \ 1/2$	16d	$0 \ 0 \ ^{1/2}$	3b
Se1	$1/4 \ 1/4 \ 1/4$	32e	$0 \ 0 \ ^{1/4}$	6c
Cr2	-		$1/2 \ 0 \ 0$	9e
Se2	-		$1/2 \ 1/2 \ 1/2$	18h

 Table 3.1: Cell, atomic parameters and Wyckoff positions for the cubic spinel and the hexagonal transformation.



Figure 3.6: Binary section of the ternary phase diagram for Cu-Cr-Se. ASM Alloy Database.^[70]

3.4. Structure of transition metal dichalcogenides

Transition metal dichalcogenides (TMDs) TX₂ of group IV, V, VI and VII transition metals have a layered structure.^[71] The individual layers are stacked along the c-axis and bond by weak van der Waals interactions. These weak van der Waals bonds allow the exafolation of TMDs down to single layers.^[72] In-plane, the TMDs are connected by strong covalent bonds.^[73] The layers are hexagonally packed and have a thickness of 6 - 7 Å. The two dichalcogenides layers of the TMD can stack aligned AbA, giving a trigonal prismatic coordination (D_{3h}) of the metal atom. The trigonal prismatic coordination is referred to as 2H (1H in a single layer). The layering of the two polytypes along the c and b-axis is shown in Figure 3.7. Alternatively, one of the layers can be shifted giving an AbC layering. Due to the shifted layer, the metal is octahedrally coordinated (D_{3d}), referred to as 1T polytype.^[73-76] The two





coordination and the corresponding layering can be seen in Figure 3.8. The 1T and 2H polytypes can be stacked in various sequences. Eleven different polytypes can be found in TMDs which can be transformed into each other by external parameters.^[77]



Figure 3.8: Stacking of the individual TMD layers along c-axis for the 2H (left) and 1T polytype (right).

Group IV elements form the 1T polytype and group V elements mostly form the 1T polytype. Group VI elements mostly crystallize in the 2H polytype, and group VII elements form a distorted 1T polytype.^[73] The properties and symmetry of the TMDs depend on the filling of the d orbitals.^[75] d^0 systems are more stable in octahedral coordination than in trigonal prismatic.^[73] Filling the d orbital the trigonal prismatic

is energetically more stable than the octahedral structure, which is again reversed for system with even higher *d*-electron counts (group VII elements).^[73] By intercalation into the van der Waals gap, the filling of the *d* orbital can be engineered and a transformation of the coordination can be induced.^[74]

If the bulk TX₂ forms only one polytype, the corresponding ferecrystalline material will also consist of only this polytype, otherwise the individual TMD layers will be turbostratically disordered.^[78] Johnson *et al.* discovered that the dichalcogenides tend to crystallize in ferecrystals in their thermodynamically stable polymorph.^[31] By increasing n in $[(MSe)_{1+\delta}]_m (TSe_2)_n$, a huge variation of higher order polytypes is accessible in ferecrystals and even polytypes that have not been reported in the bulk material can be formed.^[79]

3.5. X-ray and neutron reflectometry

X-ray reflectometry (XRR) and neutron reflectometry are surface sensitive scattering techniques that can be used to analyze the layer and film thickness, material density, roughness of surface and interface, and determine the layer structure.^[80]



Figure 3.9: Schematic representation of the reflection at an interface showing incident ray $\vec{k_i}$ and reflected ray $\vec{k_r}$ at angle θ and the scattering vector $\vec{Q_z}$.

If the incident angle of an incoming beam is below the critical angle θ_c , total reflection occurs. For incident angles larger than θ_c ($\theta > \theta_c$) a part of the beam penetrates the sample and is transmitted and another part is reflected on the surface (Figure 3.9). The difference between the reflected ray $\vec{k_r}$ and the incident ray $\vec{k_i}$ gives the scattering vector $\vec{Q_z}$ (equation 3.1).^[81]

$$\vec{Q_z} = \vec{k_r} - \vec{k_i} \tag{3.1}$$

As the moduli of $\vec{k_r}$ and $\vec{k_i}$ are equal in elastic scattering,

$$\left|\vec{k_r}\right| = \left|\vec{k_i}\right| = k_0 = \frac{2\pi}{\lambda} \tag{3.2}$$

the scattering vector can be written as:

$$Q := |Q_z| = \sqrt{k_0^2 + k_0^2 - 2k_0 \cos(2\theta_i)} = \frac{4\pi \sin(\theta_i)}{\lambda}$$
(3.3)

X-ray and neutron reflectometry are related to the refractive index n:

$$n = 1 - \delta + i\beta \tag{3.4}$$

Where δ is the anomalous dispersion correction

$$\delta = \frac{r_e \rho_e \lambda^2}{2\pi} \tag{3.5}$$

and β related to the absorption length μ

$$\beta = \frac{\lambda \mu_x}{4\pi} \tag{3.6}$$

 r_e is the electron radius (2.818 \cdot 10⁻¹⁵ m) and ρ_e is the electron density.^[82]

For neutron reflectometry δ and β are generally in the same order of magnitude as for X-rays. As the scattering length b is different for neutrons δ and β for neutron reflectometry are as follows:^[81]

$$\delta = \frac{b\rho_n \lambda^2}{2\pi} \tag{3.7}$$

$$\beta = \frac{\lambda \mu_n}{4\pi} \tag{3.8}$$

The scattering length density (SLD) of a material depends on its density, the intrinsic scattering power and has the units $Å^{-2}$. The intrinsic scattering power depends on the electrons density and nuclear scattering lengths for X-ray and neutron scattering, respectively.^[82] The neutron SLD is:

$$SLD = \frac{\sum_{i=1}^{N} b_i}{V_m}$$
(3.9)

Where b_i is the scattering length of the N atoms within the material and V_m is the material volume. The SLD can be calculated for X-rays as:

$$SLD = r_e N_A \frac{\sum_{i=1}^{N} \rho_m Z_i}{M}$$
(3.10)

Here, N_A is the Avogadro constant, and ρ_m is the mass density of the material and M is the molecular weight. Z is the Thomson scattering factor describing the elastic scattering of a wave on z electrons of an isolated atom.

Multiple layers with varying SLDs give a scattering length density profile normal to the interface which determines the reflectivity.



Figure 3.10: Schematic representation of reflection at a layer on a substrate showing incident ray $\vec{k_i}$ and reflected ray $\vec{k_r}$ at angle θ and the scattering vector $\vec{Q_z}$.

In a layered material like in Figure 3.10 the beam can be reflected at the layer/air interface or at the layer/substrate interface and both can interfere. The resulting periodic oscillations are called Kiessig Fringes. The period of the Kiessig Fringes is determined by the film thickness d.^[83] From the separation of the Kiessig Fringe maxima ΔQ the total film thickness can be calculated as:

$$\Delta Q = \frac{2\pi}{d} \tag{3.11}$$

The total layer thickness in a ferecrystal d was calculated from the Kiessig Fringes in the XRR data.^[84] The modified Braggs law (Eq. 3.12) gives the angular position θ_i of the Kiessig Fringes.^[85] Where m_i is the diffraction order of the *i*-th maxima, λ the X-ray wavelength and θ_c angular position of critical angle.

$$m_i \lambda = 2d\sqrt{\sin^2\theta_i - \sin^2\theta_c} \tag{3.12}$$

Absolute film thickness is determined by rearranging the equation-plotting the square of the sine of the maxima of the oscillations θ_i versus the square of the wavelength over two times the order m_i squared and extracting the thickness d from the slope, as given by the equation below.

The equation was rearranged to equation 3.13 and the $\sin^2\theta_i$ as plotted a function of λ^2 over two times the order m^2 . Then the film thickness can be extracted from the slope of the plot.

$$\sin^2\theta_i = \left(\frac{\lambda}{2}\right)^2 \frac{m^2}{d^2} + \sin^2\theta_c \tag{3.13}$$

The path of the beam in Figure 3.10 can be described by Snell's law (equation 3.14).

$$n_0 \sin(\theta) = n_1 \sin(\theta_2) \tag{3.14}$$

Air has a refractive index of 1 (n_0) and for the critical angle where $\theta_2 = 0$ (3.13) can be derived as:

$$\theta_c = \arccos(n_1) \tag{3.15}$$

In order to model the reflectivity data out of the SLD profile, Paratt's formalism is used in this work. Parrat's formalism (equation 3.16) gives a precise expression for all regions since absorption is considered and no approximations are made.^[86] The reflectivity r for N+1 layers is described as:

$$r_{N+1} = \frac{r'_{N,N+1} + r_N e^{id_N k_N}}{1 + r'_{N,N+1} r_N e^{id_N k_N}}$$
(3.16)

Here d_N is the material thickness. The Fresnel reflection coefficient^[87] between the layers N and N+1 $\theta > \theta_c$ is:

$$r'_{N,N+1} = \frac{k_{N+1} - k_N}{k_N + k_{N+1}} \tag{3.17}$$

As the layer and surface roughness σ generate a diffuse scattering, Névot and Croce deduced a modified Fresnel coefficient which considers the roughness:^[80,88]

$$r'_{N,N+1} = \frac{k_{N+1} - k_N}{k_N + k_{N+1}} e^{-2k_N k_{N+1} \sigma_{N,N+1}^2}$$
(3.18)

$$k_N = \sqrt{\omega^2 - 2\delta_N i 2\beta_N} \tag{3.19}$$

Here ω is the diffracted-beam direction with respect to the crystal surface.^[89]

The effect of the film thickness, density, roughness on the SLD profile, and the reflectivity curve are represented in Figures 3.11 - 3.13. A multilayer of Mo|Nb|Mo on silicon was simulated. The molybdenum density and thickness thereby were kept constant. By increasing the niobium film thickness, the distance between the Kiessig Fringes is reduced (Figure 3.11). The lower intensity in the SLD profile corresponds to niobium (64.259 Å⁻²). When the niobium layer thickness is increased the distance between the molybdenum parts in the SLD profile increases as well.

The difference in density of the layers and the substrate affects the amplitude of Kiessig Fringes. A large density difference gives a higher amplitude for the Kiessig



Figure 3.11: Effect of niobium layer thickness in Mo|Nb|Mo films on a silicon substrate on the Kiessig Fringes (top) for visualization is the data plotted with an offset. SLD profiles of the films for visualization are the SLD plotted with an offset (bottom).



Figure 3.12: Effect of niobium layer density in Mo|Nb|Mo films on a silicon substrate on the Kiessig Fringes (top) and on the SLD profile (bottom).

Fringes. The niobium part in the SLD profile is effected by the change in density (Figure 3.12).

In most cases a surface or interface is not perfectly smooth but shows a certain roughness. The decrease in intensity of the Kiessig Fringes is related to the roughness of the surface and the different interfaces.^[87] The roughness was changed for niobium, molybdenum and the substrate by the same degree. Figure 3.13 demonstrates the effect of different surface roughnesses on the reflectivity curve and SLD profile.



Figure 3.13: Effect of niobium layer roughness in Mo|Nb|Mo films on a silicon substrate on the Kiessig Fringes (top) and on the SLD profile (bottom).

3.5.1. Polarized neutron reflectometry

Polarized neutron reflectometry (PNR) allows the determination of the vector magnetization of the material. The magnetic moment of the neutron can be used to analyze the vector magnetization depth profile normal to the surface.^[90,91] Therefore it is possible to analyze strength and range of magnetic interactions in a multilayered material.

The neutrons of the incident beam are conventionally polarized to a fixed direction. The investigated material may then change the polarization of the neutrons.^[92] The reflectivity pattern of the material is analyzed according to the sign of the neutron polarization before and after the reflection R^{++} , R^{--} , R^{+-} and R^{-+} .^[90]

4. Interlayer correlations in 1:1 ferecrystals

4.1. Introduction and aims

Understanding and controlling nucleation and growth is an important step in improving the crystallinity of thin films and thus crucial for the materials performance.^[18,93] Ferecrystals $[(MSe)_{1+\delta}]_m (TSe_2)_n$ with m = n = 1 (here referred to as 1:1) are typical parent systems for higher order ferecrystals as they are generally more easily accessed.^[94-97] Ferecrystals with m = n > 1 become more unstable with increasing m, n and decompose into the 1:1 compound with increasing annealing temperature.^[98] Moreover, a comparison with the corresponding misfit material is not possible for the very large range of potential higher order (m, n) ferecrystals^[28,99] as most misfit compounds have the composition $[(MSe)_{1+\delta}]_1(TSe_2)_1$.^[34,100]

Previous X-ray or electron diffraction experiments on 1:1 samples had a rather low resolution and showed only broad (hkl) reflections.^[31,32,94,97]

Recent high resolution studies on $[(SnSe)_{1+\delta}]_1(VSe_2)_1$ ferecrystals indicate directionally dependent interlayer registration, as opposed to the typically observed rotational disorder.^[31,101] STEM images of $[(SnSe)_{1+\delta}]_1(TSe_2)_1$ revealed regions with long range order in the stacking direction $c.^{[102]}$ Those results show that at least for some 1:1 ferecrystals ordered domains are present.

A systematic study of such potential interlayer structural correlations in five different 1:1 ferecrystals was carried out and is presented in this chapter.

4.2. Evidence of interlayer correlation

In order to identify interlayer correlations in 1:1 ferecrystals, reciprocal space maps were performed along the l direction (Q_z) of the first in-plane reflections, where the rock salt and dichalcogenide reflections overlap. X-ray diffraction scans in inplane (hk0) and out-of-plane (00l) geometry were performed to determine the lattice parameters and exclude a deviation from the usual ferecrystalline structure in these directions.

Figure 4.1 gives the out-of-plane diffraction patterns of the 1:1 materials. The different 1:1 ferecrystals are abbreviated to MT as all investigated ferecrystals are based on selenium and only the M and T metals are varied. For instance $[(SnSe)_{1+\delta}]_1(VSe_2)_1$ is abbreviated to SnV.



Figure 4.1: X-ray diffraction patterns of selected m = n = 1 ferecrystals in out-of-plane (00*l*) geometry.

All observed reflections in the X-ray diffraction patterns of out-of-plane geometry are indexed according to (00l) reflections of the ferecrystal superstructure, indicating that the individual layers of samples are stacked along the c-axis. The refined *c*lattice parameters are given in Table 4.1. *c*-lattice parameters, determined by a Le Bail fit, and atomic distances, determined by Rietveld refinement, are consistent with previously published data of these materials.^[31,43,94,95,102–104] Detailed results of the Le Bail fit and Rietveld refinement can be found in appendix chapter A.1.

 Table 4.1: c-lattice parameters obtained from Rietveld refinement of X-ray diffraction patterns in out-of-plane geometry.

	c [Å]
SnTi	12.083(2)
PbV	12.282(6)
BiNb	12.091(3)
SnV	12.070(2)
BiTi	11.818(6)

Figure 4.2 shows X-ray diffraction patterns in in-plane geometry for the five 1:1 ferecrystals. All observed reflections are indexed according to (hk0) reflections of the binary compounds as expected for ferecrystalline materials.^[43,99] The in-plane lattice parameters of the binary compounds, obtained by the Le Bail method, are given in Table 4.2. Detailed results of the Le Bail fit are given in the appendix chapter A.1. The obtained lattice parameters are consistent with previously published data of these materials.^[31,43,94,95,102–104] Some of the in-plane lattice parameters have a slight variation to the bulk values which is a known phenomenon for ferecrystals.^[99] In the X-ray diffraction patterns in in-plane (Figure 4.2) and out-of-plane (Figure 4.1) geometry all reflections could be indexed as (00l) reflections of the superstructure or (hk0) reflections of the binary compounds. Therefore they give no evidence for a (hkl) superstructure.



Figure 4.2: X-ray diffraction patterns of selected m = n = 1 ferecrystals in in-plane (hk0) geometry.

Table 4.2: Lattice parameters obtained from Le Bail fits of X-ray diffraction patterns inin-plane geometry.

	a MSe [Å]	b MSe [Å]	$a \operatorname{TSe}_2[\mathring{A}]$
PbV	6.079(3)	= a	3.435(3)
BiNb	4.45(1)	4.25(1)	3.497(6)
SnTi	5.969(6)	6.078(3)	3.555
SnV	5.919(1)	= a	3.4025(6)
BiTi	5.565(3)	4.247(3)	3.590(2)

Figure 4.3 shows the reciprocal space maps of the 1:1 ferecrystals. The corresponding in-plane scans are on top of the space maps and the (hk0) reflections are indexed. Along the Q_z direction, unexpected reflections are identified, that are not consistent with the binary compound.

The reciprocal lattice mismatch along Q_z of the $[20l]_{MSe}$ and $[10l]_{TSe_2}$ reflections is given as ΔQ . For those ferecrystals revealing nearly coinciding in-plane reflections (BiTi and SnV) with $\Delta Q \approx 0$, the (hkl) reflections in the reciprocal space maps are very sharp and in line along Q_{par} (Figure 4.3). BiNb, PbV and SnTi have a higher deviation of the in-plane reflection positions and more diffuse and smeared (hkl) reflections with a distinct offset in Q_{par} of the (hkl) reflections.



Figure 4.3: Reciprocal space maps of the investigated ferecrystals along with in-plane diffraction intensity (top).

To analyze the $[20l]_{MSe}$ and $[10l]_{TSe_2}$ reflections series, intensity profiles along Q_z were integrated. The out-of-plane modulation distance $\Delta \mu$ is the mean distance between two reflection maxima in the intensity profiles along Q_z . $\Delta \mu$ was determined by Gaussian fits of all reflections along the Q_z direction as shown exemplarily for SnV in Figure 4.4 (remaining fits can be found in the appendix chapter A.2). The individual reflections were fitted with individual reflection positions (position of the Gaussian maxima) and intensities. All reflections could be fitted with same width, indicating that the reflections are either generated by the same compound or by compounds with the same correlation length. $\Delta \mu$ relates to the lattice parameter of the compound generating the (hkl) reflections along Q_z (referred to as z-lattice parameter) according to:

$$\frac{2\pi}{\Delta\mu} = z \text{-lattice parameter}$$
(4.1)

The z-lattice parameters calculated from the modulation distance and the c-lattice parameter determined from Le Bail fit of the out-of-plane diffraction patterns are plotted in Figure 4.4. For all samples, the z-lattice parameter derived from the modulation distance is in good agreement with the superstructure lattice parameter c determined in the (00*l*) direction of the ferecrystals, indicating that the repetition



unit is one or a multiple of $[(MSe)_{1+\delta}]_1(TSe_2)_1$ structural units.

Figure 4.4: Intensity profile along Q_z with Gaussian fits shown exemplary for the SnV ferecrystal (left) and z-lattice parameter compared with the superstructure *c*-lattice parameter, as a function of ΔQ (right).

As the (00*l*) reflections of the ferecrystal superstructure are highly diffuse in Q_{par} direction (Figure 4.5 left) the reflections along the $[20l]_{MSe}$ and $[10l]_{TSe_2}$ series might arise from an overlap of the binary (*hkl*) reflections and the (00*l*) reflections of the superstructure. The intensity profile along Q_z of the 1:1 ferecrystals together with the out-of-plane diffraction pattern of SnV are shown in Figure 4.5 (right). The intensity profiles along Q_z of the 1:1 ferecrystals do not match the reflection position of the out-of-plane diffraction pattern. This provides strong evidence that the unexpected reflections along the $[20l]_{MSe}$ and $[10l]_{TSe_2}$ series do not arise from an overlap of (00*l*) reflections, but indicate an interlayer correlation for 1:1 ferecrystals.



Figure 4.5: Reciprocal space maps along the (00l) reflections (left) and intensity profile along Q_z of selected m = n = 1 ferecrystals (right).

The reflection full width at half maximum (FWHM) can be used to calculate the coherence length D in the corresponding direction. By using the FWHM, D can

	001	00 <i>l</i>	hkl	hkl
	FWHM $[Å^{-1}]$	D $[Å]$	FWHM $[Å^{-1}]$	D $[Å]$
SnTi	0.016	392.70	0.506	12.42
PbV	0.018	349.07	0.426	14.75
BiNb	0.020	314.16	0.586	10.72
SnV	0.015	418.88	0.484	12.98
BiTi	0.020	314.16	0.574	10.95

Table 4.3: Coherence lengths determined for the ferecrystal superstructure (00l) and the interlayer correlation (hkl).

be approximated by $D \approx \frac{2\pi}{FWHM}$. In ferecrystals, the structural coherence length of the (00*l*) reflections is in most cases near the total sample thickness. The (*hk*0) reflections give the average grain size in-plane, which is usually in the range of 0.9-12 nm.^[105,106] For individual (*hkl*) reflections, the width along Q_z should correspond to the individual layer thickness of the binary compounds.

The coherence length D approximated by $D \approx \frac{2\pi}{FWHM}$ for the (00*l*) superstructure is in the order of magnitude of the total sample thickness of 25-35 [MSe][TSe₂] double layers (Table 4.3). In contrast, the coherence length D obtained for the (*hkl*) superstructure is much smaller, underlining that the (*hkl*) reflections along the $[20l]_{MSe}$ and $[10l]_{TSe_2}$ are independent from the (00*l*) reflections. This supports that there is an interlayer correlation between the binary compounds in 1:1 ferecrystals.

4.3. Higher order reflections

For the 1:1 SnV ferecrystal, higher order reflection series of $[20l]_{VSe_2}$ $[40l]_{SnSe}$ and $[30l]_{VSe_2}$ $[60l]_{SnSe}$ were also investigated to determine if the correlation is limited to the first overlapping reflections. Reciprocal space maps and intensity profiles are presented in Figure 4.6. For these reflection series, no superstructure reflections were observed. Instead, the out-of-plane lattice parameter in the range of c = 6(1) Å corresponds well with the *c*-lattice parameters of the binary compounds, and all observed reflections can be indexed according to the binary crystal structure.

This indicates that the interlayer correlation between the binary compounds effects only the $[20l]_{MSe}$ and $[10l]_{VSe_2}$ direction and not the higher order reflections. It is also possible that the intensity of the correlation reflections is weaker at higher Q than the intensity of $[20l]_{VSe_2}$ $[40l]_{SnSe}$. $[30l]_{VSe_2}$ $[60l]_{SnSe}$ in in-plane direction (Figure 4.2) is much weaker than the $[20l]_{SnSe}$ and $[10l]_{VSe_2}$ reflections indicating that the reflections of the correlation might have an intensity too low for detection.



Figure 4.6: Reciprocal space maps in l direction for the higher order reflection series in the SnV ferecrystal (left) and corresponding intensity profiles with Gaussian fits (right).

4.4. Reciprocal space maps along MSe and TSe₂ reflection series



Figure 4.7: Reciprocal space maps for SnV and SnTi ferecrystals with mixed m,n, along $[22l]_{SnSe}$.

For the SnV and SnTi series with $m, n \neq 1$ and m = n = 1, reciprocal space maps along the $[22l]_{\text{SnSe}}$, $[31l]_{\text{SnSe}}$ and $[11l]_{\text{TSe}_2}$ were measured (Figure 4.7 - 4.10). The intensity profiles of SnV and SnTi are given in Figure 4.8. (2*m*-1) Laue oscillations in between Bragg reflections are observed, as expected for the samples with $m \neq$ 1 (indicated by white arrows in Figure 4.7).^[106,107] The in-plane and out-of-plane diffraction patterns for the ferecrystals with higher m, n order give no evidence for an (*hkl*) superstructure and are in agreement with previously published data (appendix chapter A.3).^[103,108,109]



Figure 4.8: Intensity profiles of SnV (left) and SnTi (right) ferecrystals with mixed m, n, along $[22l]_{SnSe}$.

Along $[22l]_{\text{SnSe}}$, additional reflections are observed for m, n = 1 but not for $m, n \neq 1$ (Figure 4.7 and 4.8). This shows that the correlation is not limited to the $[20l]_{\text{MSe}}$ $[10l]_{\text{TSe}_2}$ series but is not present in higher order ferecrystals with $m, n \neq 1$. The additional reflections due to the correlation along $[22l]_{\text{SnSe}}$ are not strong enough to overlap the (hkl) reflections as they have a higher intensity and the reflections of the correlation appear as shoulders of the (hkl) reflections. This indicates that the correlation effect is weaker with increased Q.

Interlayer correlations are not observed for the $[31l]_{SnSe}$ (Figure 4.9). This might be due to the lower reflection intensity of the $[31l]_{SnSe}$. The reflection of the correlation might be present as weak shoulders under the more intense (*hkl*) reflections.

In addition to reciprocal space maps along the rock salt reflections, scans along the $[11l]_{VSe_2}$ also were performed (Figure 4.10). As for the scans along the rock salt reflections, no correlation reflections can be observed for the ferecrystals with $m, n \neq 1$. For the 1:1 samples, also only (hkl) reflections are present.

Additional reflections of the correlation can only be seen along $[22l]_{SnSe}$ this indicates that the correlation mostly affects the rock salt layer.


Figure 4.9: Reciprocal space maps for SnV and SnTi ferecrystals with mixed m,n, along $[31l]_{SnSe}$ (left) and corresponding intensity profiles (right).



Figure 4.10: Reciprocal space maps for SnV and SnTi ferecrystals with mixed m, n, along $[11l]_{VSe_2}$ (left) and corresponding intensity profiles (right).

4.5. Potential candidates for interlayer correlations

The previous chapters showed evidence for an interlayer correlation in 1:1 ferecrystals. A detailed discussion of previous work and a connection to the presented results will be given in this chapter.



Figure 4.11: a) Relative in-plane orientation for an in-plane lattice of the binary compounds MSe (blue) and TSe₂ (red). Schematic view along b) a- and c) b-axis TSe₂ is represented in the orthorhombic analogue.

Figure 4.11 shows the geometry of the 2D lattices of the binary compounds MSe (blue) and TSe₂ (red). The hexagonal dichalcogenide lattice can be presented in its orthorhombic analogue where $b'_{TSe_2} = \sqrt{3}a_{TSe_2}$. Therefore, a commensurate superstructure in $[10l]_{TSe_2}$ $[20l]_{MSe}$ direction is only possible if the a_{MSe} and b'_{TSe_2} lattice parameters coincide. The difference $a_{MSe} - b'_{TSe_2}$ is the lattice mismatch $\Delta b'$. The unidirectional lattice mismatch of $[10l]_{TSe_2}$ and $[20l]_{MSe}$ (ΔQ) decreases with decreasing $\Delta b'$. Figure 4.12 shows ΔQ and $\Delta b'$ as a function of the misfit parameter δ . The misfit parameter is determined from the relative area of the binary compounds (MSe_{area} and TSe_{2area}) per formula unit in the binary compounds (MSe_{unit} and TSe_{2unit}):

$$\frac{\text{MSe unit/MSe area}}{\text{TSe}_2 \text{ unit/TSe}_2 \text{ area}} = 1 + \delta$$
(4.2)

A perfect match of the b_{MSe} and b'_{TSe_2} lattice parameters would result in a misfit parameter δ of 0.155:

$$b_{\rm MSe} = b'_{\rm TSe_2} \tag{4.3}$$

$$\Delta b' = b_{\rm MSe} - \sqrt{3}a_{\rm TSe_2} \tag{4.4}$$

$$1 + \delta = \frac{2(b_{\rm MSe} - \Delta b')}{\sqrt{3}b_{\rm MSe}^2} \tag{4.5}$$

Therefore, samples with a small lattice mismatch $\Delta b'$ have a misfit parameter δ close to 0.155 (BiTi, SnV). Figure 4.12 gives $\Delta b'$ as function of δ (blue line). The $b_{\rm MSe}$ was set to 6.01 Å which is the in-plane lattice parameter of PbSe in PbV. The inplane lattice parameters of the rock salt in SnV (5.92 Å) and BiTi (6.23 Å) are also close to 6.01 Å, and therefore these values of $\Delta b'$ (black dots) match to the calculated values (blue line). BiNb and and SnTi have in-plane lattice parameters with $a \neq b$. Therefore can two different values for $\Delta b'$ be calculated and $\Delta b'$ as a function of δ is unable to describe the BiNb and SnV.



Figure 4.12: Lattice mismatch $\Delta b'$ (left y-axis) and reciprocal lattice mismatch ΔQ and (right y-axis) as a function of the misfit parameter δ . For a clearer visualisation, the absolute value of $\Delta b'$ is given. The equation 4.5 with $b_{MSe} = 6.01 \text{ Å}$ is plotted in blue.



Figure 4.13: (a)HAADF-STEM image of the (SnSe)_{1.15}VSe₂ film annealed at 300 °C. The magnified areas clearly reveal the presence of different stacking sequences, (b) SnSe₂-VSe₂-SnSe₂,and (c)VSe₂-SnSe-VSe₂. (Reprinted figure with permission from M.Falmbigl, M. Esters, D. C. Johnson, *Cryst. Res. Technol.* 52, 2017.)^[47] DOI: 10.1002/crat.201700067 Copyright (2017) by John Wiley and Sons.



Figure 4.14: Calculated energies for a SnSe "dimer" (islandwith zero radius) sandwiched between 4x4 VSe₂ layers with offsets scanned across a VSe₂ unit cell. Structures are not relaxed. The minimum occurs at d = (0,0), where the dimer sits centered over a Se triangle and in line with a V ion (inset); the maximum is at d = (-1/3, -1/3), where the dimer sits centered in a V triangle with the Sn ion adjacent to a Se ion (inset). The latter geometry but with the dimer's Se ion adjacent to a Se ion (not shown) occurs at d = (+1/3, +1/3), where the energy surface exhibits a third point with zero slope. (Reprinted figure with permission from S. P.Rudind, D. C. Johnson, *Phys. Rev. B* 91, 2015.)^[110] DOI: 10.1103/PhysRevB.91.144203 Copyright (2015) by the American Physical Society.

Johnson *et al.* showed for $(SnSe)_{1.15}VSe_2$ that by annealing the sample, besides VSe_2 and SnSe, $SnSe_2$ is formed.^[47] The $SnSe_2$ forms with VSe_2 correlated areas in the 1T polytype (Figure 4.13). By annealing to higher temperatures the $SnSe_2$ transforms into SnSe. Pure transition metal dichalcogenides (TMDs) prepared by the modulated elemental reactants (MER) method show a high disorder if they are able to form not only the 1T polytype but also the 2H or $3R.^{[31]}$ Johnson *et al.* proposed that the disorder in the ferecrystals is controlled by a template growth.^[31] An overview on the possible polytypes in TMDs is given in chapter 3.4.



Figure 4.15: Representative HAADF-STEM image of a (SnSe)_{1.2}TiSe₂ heterostructure. (Reprinted figure with permission from D. Hamann, D. Merril, S. Bauers, G. Mitchson, J. Ditto, S. P. Rudin, D. C. Johnson, *Inorg. Chem.* 56, 2017.)^[102] DOI: 10.1021/acs.inorgchem.6b03063 Copyright (2017) by the American Chemical Society.

DFT studies on SnV showed that the SnSe energetically favours the to be in line with the vanadium of the VSe₂ layer (Figure 4.14).^[110] The resulting 12 fold symmetry has been confirmed by nano-beam electron diffraction (NBED).^[101] The preferred orientation can also be seen in high-angle annular dark-field imaging (HAADF)-STEM images of $(SnSe)_{1.15}VSe_2^{[101]}$ and $(SnSe)_{1.20}TiSe_2$ (Figure 4.15).^[102]

The correlation during the annealing might act as a template for the 12-fold symmetry in 1:1 ferecrystals which correspond to the superstructure *c*-lattice parameter. The 12 fold symmetry also allows a correlation only for the rock salt layer as the individual TMDs would be distorted to each other. This explains why no correlation reflections could be seen in the reciprocal space map along the $[11l]_{TSe_2}$.

This indicates that the best correlating sample can be prepared with a TMD that only crystallizes in 1T and a rock salt that forms a 2D layered dichalcogenide. The transformation from precursor to the TMD template with mixture of TSe₂-MSe₂-TSe₂ in the 1T polytype and TSe₂-MSe-TSe₂ into TSe₂-MSe-TSe₂ is shown in a schematic free energy landscape as a function of annealing temperature in Figure 4.16.

The TMDs of vanadium^[111] and titanium^[112] have only been reported in the 1T polytype. NbSe₂ can form multiple polytypes in bulk^[113] and ferecrystalline materials.^[79] As NbSe₂ can crystallize in 1T or 2H polytype, the NbSe₂ layer has a higher distortion which is reducing its ability to build the template 1T NbSe₂-BiSe₂-NbSe₂ structure. In consequence, the BiNb has less coinciding in-plane lattice parameters.

The TMD of lead and selenium can only be synthesized in a high pressure synthesis (4.5 GPa) at 650 °C, and therefore, there is probably no intermediate in the annealing process.^[114] Even if PbSe₂ would be formed during the annealing process, it would



Figure 4.16: Free energy landscape for the transformation of the as deposited precursor into the mixture of $TSe_2-MSe_2-TSe_2$ and $TSe_2-MSe-TSe_2$ to the lower energy state with only $TSe_2-MSe-TSe_2$.

not promote a template crystallization as $PbSe_2$ does not crystallize in a 2D-layered structure.^[114]

In line with these preconditions, largest ΔQ (0.0452Å) is observed for PbV, even though VSe₂ crystallizes only in 1T, and the second smallest ΔQ (0.0093Å) of the investigated ferecrystals is observed for SnV.

SnTi has a much larger ΔQ (0.0268 Å) than BiTi (0.0006 Å) and SnV (0.0093 Å) which is surprising as the SnSe is able to form a TMD and TiSe₂ crystallizes, like VSe₂, only in 1T. In comparison to SnV, the SnSe in SnTi exhibits a peak splitting and therefore a higher offset in ΔQ , as the *a* and *b*-lattice parameter deviate below and above *b*'. Johnson *et al.* showed a transformation from α - to β -SnSe with increasing rock salt layer thickness $m.^{[45,109]}$ Due to a higher Sn content in SnV exhibits SnSe a peak splitting with high Sn/V ratios (1.37).^[115] Therefore, might the peak splitting in SnTi be due to a higher Sn content. The different SnSe symmetry in SnTi and SnV might also result from different annealing temperatures. α -SnSe has a temperature dependent change in the ratio of a/b lattice parameters and, above 880 K, a phase transition to β -SnSe.^[116]

In consequence, the correlation in 1:1 ferecrystals depends on the ability of the TMD to crystallize in 1T or multiple polytypes and if the rock salt forms a 2D layered dichalcogenide. This templating might then influence the in-plane lattice parameter. It is also possible that the coinciding lattice parameters allow a better formation of a template crystallization of the TMD and the dichalcogenide of the rock salt. There-

fore, a small $\Delta b'$ seems to be essential for interlayer correlations but not necessarily all 1:1 ferecrystals with $\Delta b' \approx 0$ show interlayer correlations. The ability of the inplane lattice parameter to be distorted to reduce $\Delta b'$ might also be important. For example a (PbSe)_{1+ δ}NbSe₂ should have a higher ΔQ than (PbSe)_{1+ δ}VSe₂ as NbSe₂ crystallizes contrary to VSe₂ not only in 1T.

Applying this model on other 1:1 ferecrystals, a high deviation from the ideal value of the misfit parameter (0.155) is expected for ferecrystals with TMDs that form multiple polytypes. This can be seen for MoSe₂ (0.03)^[97] and WSe₂ (-0.01)^[97] compounds but not for all NbSe₂ (SnNb 0.136)^[117] ferecrystals. Also, PbTi has a misfit parameter of 0.160,^[118] even though PbSe is unable to form a 2D layer dichalcogenide. If the proposed model is correct have those ferecrystals with a δ of 0.155 not necessarily a high correlation and therefore should in reciprocal space maps of PbTi reflections of the binary compounds along $[20l]_{PbSe}$ and $[10l]_{TiSe_2}$ be visible.

4.6. Summary

A systematic study of structural interlayer correlations was performed for five different 1:1 ferecrystals by reciprocal space mapping. Additional correlation reflections in these 1:1 ferecrystals were observed, in particular in $[10l]_{TSe_2}$ $[20l]_{MSe}$ and along $[22l]_{MSe}$ reflection series. These additional reflections are associated with interlayer correlations in these particular directions. For samples with a small lattice mismatch in-plane, the $[10l]_{TSe_2}$ $[20l]_{MSe}$ reflections are better aligned in the lateral direction. This indicates that the degree of correlations depends on the lattice mismatch. A correlation with the lateral Q position, *i.e.*, a lateral smearing of the very strong (00*l*) reflections, could be ruled out as the correlation length in *l* direction is much different and the Q_z position of the additional reflections does not match the Q_z position of the (00*l*) superlattice reflections.

For higher order reflections, correlation can only be seen in the rock salt layer indicating that TSe₂ does not nucleate randomly but crystallizes and acts as a template for following layers as proposed by Johnson *et al.*.^[31] It is essential for a high degree of correlation that the TMD crystallizes only in the 1T polytype and that the rock salt is able to form a 2D layered TMD as intermediate. The misfit parameters of previously published 1:1 ferecrystals that do not obey this rule but have a low $\Delta b'$ indicates that a low $\Delta b'$ does not necessarily mean that a high degree of correlation is present in these samples. Further reciprocal space maps on 1:1 ferecrystals with a low $\Delta b'$ but a rock salt that is unable to form a 2D TMD like PbV could confirm that a low $\Delta b'$ does not necessarily give samples with interlayer correlations. The results show that correlation of 1:1 ferecrystals is found in all five investigated 1:1 ferecrystals and probably also can be found in other 1:1 ferecrystals with appropriate TMD and rock salt. This is according to the previous work on correlations in 1:1 ferecrystals^[31,101,102] and is an important step in understanding the 3D structure and nucleation of multilayered materials containing TMDs, especially ferecrystals.

5. $[(Cu_x Cr_y Se_z)_{1+\delta}]_1 (NbSe_2)_3$ ferecrystals

5.1. Introduction and aims

In nanolayer synthesis the challenge is the synthesis of materials with a small size distribution and precise control of the structure. Via modulated elemental reactant (MER) method materials with finely, (sub-Å) tunable, monodisperse layer thickness are accessible.^[22,119] The MER method allows preparation of nanolaminates with systematically designed compositions.^[118] The individual components (typically chalcogenide materials) of these ferecrystals are precisely oriented in the stacking direction (c-axis) but rotationally disordered in plane.

Therefore magnetic ferecrystals are ideal for the investigation of surface and finite size induced structural effects. The typical rock salt in $[(MSe)_{1+\delta}]_m (TSe_2)_n$ (M = Pb, Sn, Bi, or rare earth metal; Te; T = transition metal) was exchanged with the cubic spinel CuCr₂Se₄. CuCr₂Se₄ thin films have first been prepared by Bettinger *et al.* by pulsed laser deposition (PLD).^[57] The X-ray diffraction patterns of the films revealed impurities of CuCrSe₂ and Cr_{2.8}Se₄. For the preparation of CuCr₂Se₄ via the MER method a Se|Cr|Cu|Cr|Se layering scheme is essential to prevent the formation of Cu-Se compounds as reaction intermediates.^[46,59] Previous work on CuCr₂Se₄ showed that it is possible to prepare phase pure CuCr₂Se₄ layers via the MER method.^[58,120] These CuCr₂Se₄ films were crystallographically aligned with [111] perpendicular to the substrate and had a Curie temperature of 406 K.^[58] First experiments indicated that an alternative layering with NbSe₂ is possible.^[46]

We explored the synthesis of heterostructures within the Cr-Cu-Se-Nb system, focusing on the Se rich phases using modulated elemental reactants in an attempt to control the structure of the products formed.

5.2. Sample calibration and preparation

The $[(Cu_x Cr_y Se_z)_{1+\delta}](NbSe_2)_n$ ferecrystals were prepared using a previously reported layering scheme for preparing CuCr_2Se_4 with the MER method (Figure 5.1).^[46,59] As it is not necessarily that CuCr_2Se_4 forms in ferecrystalline materials this layer will be referred to as Cu_xCr_ySe_z in the following.

The deposition parameters for the Nb-Se layers were based on parameters successfully used in prior studies on $[(MX)_m]_{1+\delta}(NbSe_2)_n$. A number of precursors were prepared during the course of this investigation by depositing elemental layers in designed sequences to probe the potential formation of heterostructures containing alternating layers of $Cu_x Cr_y Se_z$ and NbSe₂.



Figure 5.1: Layering scheme for the preparation of $(Cu_x Cr_y Se_z)(NbSe_2)_n$.

As explained in chapter 3.3 $CuCr_2Se_4$ has a preferential formation along [111] with a double layered structure if a c-lattice parameter of $12 \,\mathrm{A}$ is considered. To determine the constituent c-lattice parameters samples with 1, 3 and 5 $NbSe_2$ layers were prepared. The Nb|Se deposition parameters were used as previously calibrated by the Johnson group. Tooling factors and deposition rates were inherited from previous calibrations performed in the Johnson group. For Cu|Se|Cr arbitrary starting values were tested. By plotting the change in c-lattice parameter vs. the number of NbSe₂ layer (Figure 5.2) the individual constituent c-lattice parameters can be calculated from the linear trend given that the choosen parameters are roughly in the range. The slope of the trend line is 6.31 Å and corresponds to the *c*-lattice parameter of NbSe₂ and is close to the bulk value of 6.29 Å. The y-axis intercept corresponds to the $Cu_x Cr_y Se_z$ c-lattice parameter and is with 12.31 Å slightly larger than what would be expected from the bulk material. Even though the constituent lattice parameters are close to the desired values, a lot of (00l) reflections in the samples are not visible indicating a poor crystallinity and that further optimization of the deposition parameters is necessary.

Therefore the amount of niobium and selenium deposited in Få was kept constant and the Cu/Cr ratio deposited was systematically varied to obtain highly crystalline samples. Preliminary experiments revealed that samples with a m:n ratio 1:3 are the best choice to prepare a crystalline sample. Therefore the 1:3 sample was used to calibrate the Cu/Cr ratio.

To optimize the Cr deposition parameters samples with copper thickness of 2.1 and 2.9 Få and varying chromium thickness were prepared (Figure 5.3). The goal were samples with the best crystallinity *i.e.* samples with most (00l) reflections that have a high intensity and are sharp. For the samples with a copper layer thickness of



Figure 5.2: Change in *c*-lattice parameter vs. the number of NbSe₂ layers (left). Specular diffraction pattern (right).



Figure 5.3: Specular diffraction patterns of samples with varying chromium layer thickness in Få and constant copper layer thickness. 2.1 Få of copper (left) and 2.5 Få of copper (right).

2.1 Få a chromium layer of 4.0 Få gave the best result, for a copper layer thickness of 2.9 Få 5.1 Få of chromium gave the best sample. The formation of secondary phases would be expected for samples with thicker copper layers than 2.5 Få (pure copper or $CuSe_2$) and for samples with a copper layer thinner than 2.1 (CrSe₂).

Comparing those two samples directly (Figure 5.4) it can be seen that samples with 2.1 Cu Få and 4.0 Cr Få give the best crystallinity. The used parameters for sample preparation are given in Table 5.1.

Additional samples with slightly different deposition parameters were prepared as the screening for optimal deposition parameters showed that variation in a huge range of deposition parameters gave crystalline materials. The used parameters and the corresponding samples are given in table 5.1.



Figure 5.4: Specular diffraction patterns of the samples with 2.9 CuFå, 5.1 CrFå (left) and 2.1 CuFå, 4.0 CrFå (right). * = silicon

Table 5.1: Parameters for preparation of $[(Cu_x Cr_y Se_z)_{1+\delta}]_1(NbSe_2)_n$ samples

	sample 1 and 4			sample 2 and 3			sample 5		
	Få	Rate	Tooling	Få	Rate	Tooling	Få	Rate	Tooling
			Factor			Factor			Factor
Nb	7.7	0.2	64	7.8	0.2	64	7.8	0.2	64
Se	8.3	0.5	65	8.3	0.5	68	8.3	0.5	68
Se	7.4	0.5	65	7.4	0.5	68	7.4	0.5	68
Cr	5.1	0.2	64	3.3	4.0	0.2	64	0.2	64
Cu	4.1	0.2	64	4.5	2.1	0.2	64	0.2	64
Cr	5.1	0.2	64	3.3	4.0	0.2	64	0.2	64
Se	7.4	0.5	65	7.4	7.4	0.5	68	0.5	68

5.3. Annealing study

An annealing study was performed to determine the changes in structure as a function of temperature and time. The annealing time and temperature as well as the coherence of the obtained heterostructure were optimized. The annealing studies were performed with $[Se|Cr|Cu|Cr|Se]_1[Nb|Se]_3$ precursors in a glove box with nitrogen atmosphere with O₂ and H₂ concentration below 0.5 ppm. For annealing the samples were heated heated on a costume made hot plate to temperatures between 100 and 600 °C. During the annealing the sample was covered with a clean silicon-wafer to reduce the selenium loss. After each annealing step X-ray reflectivity and X-ray diffraction patterns were taken, and the total thickness and *c*-lattice parameter are determined.

Figure 5.5 shows the time dependent X-ray reflectometry and diffraction patterns with



Figure 5.5: X-ray reflectometry (left) and diffraction patterns (right) obtained after different annealing times of sample 1 $[(CuCr_xSe_y)_{1+\sigma}]_1[NbSe_2]_3$ at 400 °C reflections of secondary phase are indexed in italic. Heterostructures A and C are indexed as brown and orange lines, respectively. * = silicon, + = stage



Figure 5.6: Total thickness and elemental modulation / *c*-lattice parameter as a function of time.

indexed (00*l*) reflections. One piece of sample 1 was annealed at 400 °C in 5 min steps. Uniform Kiessig fringes and the first five Bragg reflections in the as-deposited material indicate that the precursor already is nicely layered with a repeating thickness of 33.9(1)Å and contains significant order. With increasing annealing time additional reflections appear, reflections sharpen, and the intensity of the (00*l*) reflections increases indicating optimization of crystallographic alignment of the film along the modulation axis. The *c*-lattice parameter as well as the total thickness (Figure 5.6) reduce with increasing temperature due to loss of excess selenium and increasing crystallinity, *i.e.* a more efficient packing of the atoms in the structure. After annealing for 5 min already additional reflections appear and the *c*-lattice parameter decreases. After 30 min all reflections can be indexed as (00*l*) reflections of a common superlattice, indicating that this is the optimum annealing time for $400 \,^{\circ}$ C. The heterostructure A formed after 30 min of annealing and has a *c*-lattice parameter of 32.2(2) Å. After 35 min two new reflections appear in the XRR scan, indicating the formation of heterostructure C with a larger *c*-axis lattice parameter of 36.13(6) Å based on indexing them as the 2nd and 3rd order reflections.

By varying the annealing time the system evolves into two heterostructure. The calculated total thickness obtained from the Kiessig fringes and the thickness of the elemental modulation determined from the sharp reflections present at low Q in the as deposited sample and after short annealing times, and the c-axis lattice parameter from the crystalline heterostructures that form during the annealing over time are given in Figure 5.6.



Figure 5.7: X-ray reflectometry (left) and diffraction patterns (right) obtained after different annealing temperatures of sample 2 $[(CuCr_xSe_y)_{1+\sigma}]_1(NbSe_2)_3$.

Considering the complexity of the evolution of the precursor as a function of time, an annealing study was performed on sample 2 to determine the impact of annealing temperature on structures that are formed. Nine individual samples were heated on a hot plate to different temperatures for 30 min (Figure 5.7). In the temperature range of 100 to 600 °C four distinct structural transitions are observed in the XRR and XRD (Figure 5.7) and the derived total thickness and *c*-lattice parameter (Figure 5.8 right).

Low temperature annealing at 100 and 200 °C transforms the as deposited material into heterostructure A with a smaller *c*-lattice parameter. Heterostructure A has the highest amount of reflections and the highest intensity by annealing at 300 °C. The *c*-lattice parameter of the material decreases about 1 Å from 33.20(4) Å in the precursor to 31.95(3) Å in heterostructure A. Increasing the annealing temperature to $300 - 400 \,^{\circ}\text{C}$ further the *c*-lattice parameter decreases and heterostructure A (indexed in brown in Figure 5.7 left) transforms to heterostructure B (indexed in green in Figure 5.7 left). The *c*-lattice parameter of heterostructure B (31.50(7)Å) is about 0.5Å smaller than heterostructure A. The reflections of heterostructure B sharpen by annealing at 450 °C. A third heterostructure C forms between 400 and 500 °C with a larger *c*-lattice parameter (indexed in orange in Figure 5.7 left). The XRR at $500 \,^{\circ}\text{C}$ has less uniform Kiessig fringes at low Q due to an increased surface roughness because heterostructure B and C coexist. By annealing to $600 \,^{\circ}\text{C}$ heterostructure C is eliminated and a heterostructure D (indexed in blue in Figure 5.7 left) with a *c*lattice parameter similar to heterostructure B forms. The formation of the different heterostructures is visualized by colour blocks in Figure 5.8.



Figure 5.8: Total thickness (gray) and *c*-lattice parameter as function of annealing temperature. The *c*-lattice parameters are plotted in the colour of the corresponding heterostructures A red, B green, C orange, and D blue.

5.4. Heterostructure formation in a broader set of samples

A third sample (3) was prepared with the same parameters as sample 2 to determine the reproducibility of the sample preparation and heterostructure formation in a broader set of samples. Sample 3 was divided into three pieces, one annealed at $350 \,^{\circ}$ C to form heterostructure A, one annealed at $400 \,^{\circ}$ C to form heterostructure B and one annealed to $600 \,^{\circ}$ C to form heterostructure D. The influence of different Cu/Cr ratios on the heterostructures were investigated. Therefore samples with three different Cu/Cr (0.96, 1.19, 1.8) ratios were prepared.

The diffraction patterns of the three heterostructures A, B and D of sample 3 are given in Figure 5.9. The different annealing conditions clearly produce samples with



Figure 5.9: Specular diffraction pattern in the range of $0.4 - 4.5 \text{ Å}^{-1}$ for the $[(\text{CuCr}_x \text{Se}_y)_{1+\sigma}]_1[\text{NbSe}_2]_3$ compound of sample 3 with heterostructure A, B, and D. Heterostructure C is indicated by vertical lines. * = sample holder

different *c*-lattice parameters. This can be seen in the offset to higher Q for heterostructure A relative to that for heterostructure B. For heterostructure A of sample 3, reflections of heterostructure C can be seen, which has a significantly higher intensity than observed in the sample prepared from precursor 2 (5.10 right). The reflections of heterostructure C might not be visible due to the lower resolution of the XRD data of sample 2 A. Sample 2 was measured on an in house diffractometer and sample 3 at the ID03 instrument at the ESRF. Comparing the *c*-lattice parameters of the samples prepared from precursor 2 and 3, we find that the as deposited material has a slightly smaller *c*-lattice parameter for sample 3 and the *c*-lattice parameters of all heterostructures are slightly smaller (Table 5.2).

	a lattice permeter [Å]					
	<i>c</i> -lattice parameter [A]					
	А	В	С	D[A]		
Sample 2	33.20(4)	31.50(7)	34.34(8)	31.34(4)		
Sample 3	31.77(2)	31.48(1)		31.1(1)		

Table 5.2: c-lattice parameters of samples 2 and 3 and their corresponding heterostructures.

Figure 5.10 compares the samples 2 and 3 annealed at 350 °C with heterostructure A and the samples 2 and 3 annealed at 400 °C with heterostructure B. The higher background for sample 2 A and 2 B is due to the lower resolution of the measurement. Both samples 3 A and B have a different intensity profile in comparison to their corresponding sample 2. This reflects the potentially different composition and thickness of the precursor and our limits on reproducing the deposition process.

Likewise a sample was prepared with the same parameters as sample 1. This sample 4 differs from sample 3 in the amount of copper and chromium that was deposited.



Figure 5.10: Specular diffraction pattern in the range of $0.4 - 4.5 \text{ Å}^{-1}$ for the $[(\text{CuCr}_x \text{Se}_y)_{1+\sigma}]_1[\text{NbSe}_2]_3$ compound of sample 2 (grey) and 3 (colour) with heterostructure A and B. Heterostructure C is indicated by vertical lines. *= sample holder

Additionally a fifth sample (sample 5) was prepared with a third variation in copper and chromium deposition parameters than sample 3 and 4 aiming for higher Cu/Cr ratio. To determine the Cu/Cr ratio XRF measurements of sample 3, 4 and 5 were performed. The results of the XRF measurements are summarized in table 5.3. The three different samples have similar Se/Nb ratios as their deposition parameters where not varied. The Cu/Cr ratio of the sample increases from sample 3 to 5.

	sample $3 A$	sample 4 B $$	sample 5 B $$		
Cu/Cr	0.96	1.19	1.85		
$\mathrm{Cu/Nb}$	0.03	0.05	0.04		
$\mathrm{Cr/Nb}$	0.03	0.04	0.02		
$\mathrm{Se/Nb}$	2.60	2.69	2.50		
[tip] full for the second state of the secon					

Table 5.3: Cu/Cr and Se/Nb atomic ratios determined by XRF.

Figure 5.11: Specular diffraction pattern in the range of 0.4 - 4.5 Å^{-1} for the $[(\text{CuCr}_x \text{Se}_y)_{1+\sigma}]_1[\text{NbSe}_2]_3$ compounds 3, 4 and 5 annealed at 400 °C. * = sample holder

The intensity profiles of sample 3, 4, and 5 differ due to the variation in Cu/Cr ratio (Figure 5.11). The Cr/Nb and Cu/Nb ratios have been increased from sample 3 to sample 4. Sample 5 has completely different Cu/Cr ratio and a lower Cr/Nb ratio than sample 3 and 4 but only a slight offset in the reflection position. Sample 3, 4, and 5 have visible (00l) reflections to wide Q range, this shows that over a wider range of copper and chromium ratios a crystalline material could be obtained. For sample 4 are a lot of (00l) reflections are not visible indicating a poorer crystallinity than in sample 3 and 4.

Figure 5.12 gives the evolution of the *c*-lattice parameter with temperature of the samples 3, 4, and 5. All three samples show a temperature dependent change in *c*-lattice parameter similar to sample 2. This indicates that in the prepared range of Cu/Cr ratio it is possible to form the different heterostructures A to D by varying the annealing temperature. A table with the *c*-lattice parameters of the samples 3, 4, and 5 at varying annealing temperatures can be found in the appendix chapter B.1.



Figure 5.12: *c*-lattice parameter as a function of temperature for sample 3, 4, and 5. The corresponding heterostructures are marked by coloured boxes.

For sample 5 a lot of (00l) reflections are not visible indicating a poorer crystallinity (Figure 5.13). The sample annealed at 600 °C has more visible reflections than the sample 2 A and B. Due to the higher Cu/Cr ratio more energy might be needed to form material with a good crystallinity. Johnson *et al.* showed for SnSe that excess material migrates out of the sample to the surface.^[109] This might be the case for sample 5 D indicating that the Cu/Cr ratio of sample 5 is the upper limitation for the production of a crystalline sample under the applied conditions. It also possible that for the Cu/Cr ratio in sample 5 the selenium content in the $Cr_xCu_ySe_z$ layer is too high and a higher annealing temperature than 400 °C or a longer time is needed to evaporate the excess selenium. The Cr/Nb ratio of 0.2 might too low to form a smooth

homogeneous $Cu_x Cr_y Se_z$ layer in every unit cell, this explains the low crystallinity in the sample.



Figure 5.13: Specular diffraction pattern in the range of 0.4 - 4.5 Å^{-1} for the $[(\text{CuCr}_x \text{Se}_y)_{1+\sigma}]_1[\text{NbSe}_2]_3$ compound of sample 5 with heterostructure A, B, and D. * = sample holder

5.5. Structural investigation of the in-plane structure



Figure 5.14: In-plane diffraction patterns of sample 3, 4, and 5 with heterostructure B and sample 3 with heterostructure A .

Further structural information of the samples 3, 4, and 5 was obtained from inplane diffraction patterns. Due to the formation of heterostructure A and B, it was investigated, if the change in superstructure c-lattice parameter, due to the formation of heterostructure A and B, also has an effects on the a-lattice parameter. Further, the effect of the Cu/Cr ratio on the in-plane lattice parameters was investigated.

Sample 3 A (annealed at 350 °C) and 3 B (annealed at 400 °C) and sample 4 B and 5 B (annealed at 400 °C) where probed with in-plane X-ray diffraction (Figure 5.14). The lattice parameters were obtained by the Le Bail method.^[121] The detailed results

of the Le Bail fitting are presented in appendix chapter D.2. The two constituents can be indexed independently which is characteristic for ferecrystalline materials.^[108] All reflections can be indexed as (hk0) reflections of a hexagonal plane for either $Cu_x Cr_y Se_z$ or NbSe₂.

For indexing the cubic spinel $Fd\bar{3}m$ was transformed along [111] direction into a hexagonal subgroup $R\bar{3}m$.

The *a*-lattice parameters for the $\text{Cu}_x \text{Cr}_y \text{Se}_z$ (given in Table 5.4) are slightly smaller than for the hexagonal transformation of the bulk $\text{Cu}\text{Cr}_2\text{Se}_4$ material (7.31 Å).^[56] All *a*-lattice parameters for $\text{Cu}_x\text{Cr}_y\text{Se}_z$ are larger than the reported bulk value for CrSe_2 (3.399 Å).^[122] An additional candidate for the $\text{Cu}_x\text{Cr}_y\text{Se}_z$ compound is CuCrSe_2 , with an *a*-lattice parameter nearly 1/2 of the obtained lattice parameter (3.679 Å),^[123] (compare table 5.4). The obtained in-plane lattice parameters indicate that the compound is not CrSe_2 , but might be either a $\text{Cu}_{0.5}\text{CrSe}_2$ or a $\text{Cu}\text{Cr}_2\text{Se}_4$ analogue with varying Cu/Cr content.

NbSe₂ is indexed with the hexagonal space group $P\bar{3}m1$. Ferecrystals give in in-plane geometry only (*hk*0) reflections and therefore there is no information for the packing symmetry of NbSe₂ along the c-axis accessible with in-plane diffraction. Because of that the use of the higher symmetry space group $P6_3/mmc$ of NbSe₂ is not reasonable and usually all dichalcogenides in ferecrystals are indexed with $P\bar{3}m1$. All *a*-lattice parameters for the NbSe₂ compound (given in Table 5.4) are larger than the reported bulk value $(3.4461 \text{ Å})^{[124]}$ or the copper intercalation product Cu_{0.667}NbSe₂ (3.487 Å),^[125] indicating a rather high degree of copper intercalation into the NbSe₂ layer.

The annealing temperature for sample 3 has no effect on the NbSe₂ *a*-lattice parameter and only affects the second decimal place of the $Cu_x Cr_y Se_z$ *a*-lattice parameter (Table 5.4). The different samples with heterostructure B show that the NbSe₂ *a*lattice parameter is not linked to the Cu/Cr ratio in the sample. $Cu_x Cr_y Se_z$ *a*-lattice parameter shows some slight variation with changing Cu/Cr ratio but the ratio of $Cu_x Cr_y Se_z$ *a*-lattice parameter and *c*-lattice parameter of the superstructure are almost the same for the three different samples (Table 5.5). This shows that the total volume of the $Cu_x Cr_y Se_z$ layer is not effected by the Cu/Cr ratio but the varied occupation with copper and chromium effects the *a*- and *c*-lattice parameter differently.

Table 5.4: Calculated a-lattice parameters and misfit parameter of the 1:3 samples 2 and3 and their corresponding heterostructures along with literature values for bulkmaterials.

	space group	$\mathrm{Cu}_x \mathrm{Cr}_y \mathrm{Se}_z \ a \ [\mathrm{\AA}]$	NbSe ₂ a [Å]	misfit δ
Sample 3 A		$7.293(3) \ 3.646$	3.508(6)	0.463
Sample 3 B		7.258(9) 3.629	3.504(6)	0.466
Sample 4 B		$7.30(1) \ 3.65$	3.501(9)	0.460
Sample 5 B		7.228(9) 3.614	3.526(6)	0.476
$CuCr_2Se_4^{[56]}$	$Fd\bar{3}m$	10.337		
$\mathrm{CuCr}_2\mathrm{Se}_4$	$R\bar{3}m$	7.31		
$\operatorname{CrSe}_2^{[122]}$	$P\bar{3}m1$	3.399		
$CuCrSe_2^{[123]}$	R3m	3.679		
$NbSe_2^{[124]}$	$P6_3/mmc$		3.4461	
$Cu_{0.667}NbSe_2^{[125]}$	$P6_3/mmc$		3.487	

Table 5.5: Ratio of $Cu_x Cr_y Se_z$ *a*-lattice parameters and superstructure *c*-lattice parameter for samples 3 A, 3 B, 4 B and 5 B.

	a / c
Sample 3 A	0.230
Sample $3 B$	0.231
Sample 4 B	0.229
Sample 5 B $$	0.229

5.6. Scanning transmission electron microscopy

To get a better insight into the layering and lattice parameters of the films High-angle annular dark-field - scanning transmission electron microscope (HAADF-STEM) images of sample 3 and 4 with heterostructure B were collected. The local composition of the films was investigated by EDX-line scans.

HAADF-STEM images were collected from sample 3 which was expected to form heterostructure B, a representative image is shown in Figure 5.15 (left). The STEM images reveal distinct and regularly ordered layers along the c-axis with a double layer structure with four selenium layers. The distinct layering can clearly be seen in the plot of the gray value in the STEM as function of distance (Figure 5.15, right). Since CuCr₂Se₄ forms with its [111] plane parallel to the surface, the number of potential ways to slice the cubic structure into layers is limited. Previous reports on V₃Se₄ showed that the structures terminated on its Se plane.^[126] Therefore the bulk $CuCr_2Se_4$ structure has two possible atomic arrangements along the 111 axis, with four selenium layers, a chromium- or a copper-deficient structure, $Cu_1Cr_{1.25}Se_4$ and $Cu_{0.5}Cr_{1.75}Se_4$, respectively (Figure 5.16). The two parts of the bulk structure differ in the occupation and atomic positions. Both structural models would result in a double layer structure.

The distinct layering can also be seen in the gray value plot (Figure 5.15 right). Due to the atomic number contrast,^[127] the NbSe₂-layers appear much brighter than the $Cu_x Cr_y Se_z$ -layers ($Z_{Cu} = 29$, $Z_{Cr} = 24$, $Z_{Nb} = 41$). Due to the turbostratic disorder of the nanolaminate material, the in-plane orientation of the layers parallel to the beam may vary, resulting in varying brightness of the layers.



Figure 5.15: Representative STEM image of sample 3 (left). Plot of the Gray value in the STEM image vs. the distance in Å (right).



Figure 5.16: Structural models of the Cu deficient $CuCr_2Se_4$ and Cr deficient $CuCr_2Se_4$.

EDX line scans (Figure 5.17 right) suggest as expected a structure of a double layer of chromium in the $Cu_x Cr_y Se_z$ phase, whereas a less occupied chromium layer inbetween cannot be excluded. As expected, three niobium positions are observed in the NbSe₂ phase, with potentially a small amount of niobium in the chromium layer. The EDX line scans also reveal that copper has likely diffused over the whole material. Whereas copper diffusion is a known issue^[66] especially in thin films,^[67,68] the amount of copper detected here might have been affected by the Cu TEM grid used, despite careful background correction.



Figure 5.17: Representative STEM image of sample 3 together with plot of the Gray value in the STEM image vs. the distance in Å (left). EDX maps and corresponding Gray value vs. the distance in Å (right).

Atomic distances along the c-axis were measured from the gray value profile (Figure 5.17 left) to compare with the diffraction data. The chromium in the $Cu_x Cr_y Se_z$ layer has to be in the centre of one $Cu_x Cr_y Se_z$ regardless of the structure is copper deficient $CuCr_2Se_4$, chromium deficient $CuCr_2Se_4$, $CuCrSe_2$ or $CrSe_2$. Therefore, the plots of the gray values in the STEM can be used to determine the Cr-Cr distance. The measured atomic distances and bulk values for comparison are given in table 5.6. The measured Cr-Cr distance is 5.8(3) Å which is in the range of $CrSe_2$.^[122] The Cr-Cr distance also matches to $CuCr_2Se_4$ assuming a third chromium layer in-between the two chromium layers. The Nb-Nb distance is 6.7(3) Å and larger than the Nb-Nb distance in the bulk material^[124] and previously published $[(MSe)_1]_{1+\delta}(NbSe_2)_3^{[32,55,128]}$ ferecrystals. The larger Nb-Nb distance might be due to copper intercalation into NbSe₂ as EDX data indicate a copper diffusion into the NbSe₂ layers. $Cu_{0.667}NbSe_2$ has a Nb-Nb distance of 6.82 Å which is in the range of the measured Nb-Nb distance. This confirms that the NbSe₂ layers have an enlarged unit cell due to copper intercalation.

 $Cu_x Cr_y Se_z$ layer has a double layer structure with four selenium layers. The Cr-Cr atomic distance of 5.7 Å is in the range of $CrSe_2$. The Cr-Cr distance also matches $CuCr_2Cr_4$ assuming a third chromium with a lower occupation in-between the two

chromium layers. This indicates that the $Cu_x Cr_y Se_z$ layer is a $Cu_x CrSe_2$ double layer or $CuCr_2Cr_4$.

$\begin{tabular}{ c c c c c } \hline Nb-Nb & distance [Å] \\ \hline NbSe_2^{[124]} & 6.29 \\ \hline Cuo & sezNbSe_2^{[125]} & 6.82 \\ \hline \end{tabular}$
NbSe2 ^[124] 6.29 Cuo 667NbSe2 ^[125] 6.82
$C_{110,667}NbSe_{2}^{[125]}$ 6.82
$n = 3 \text{ NbSe}_2^{[128]} 6.28$
ferecrystals
$ \begin{array}{c} 150\\ 140\\ 130\\ 120\\ 100\\ 90\\ 80\\ 70\\ 220\\ 40\\ 60\\ 80\\ 70\\ 20\\ 40\\ 60\\ 80\\ 100\\ 120\\ 100\\ 100\\ 100\\ 100\\ 100\\ 120\\ 12$

Table 5.6: Cr-Cr and Nb-Nb distances in Å along the c-axis for different bulk and thinfilm materials.

Figure 5.18: Representative STEM image of sample 3 (left). An additional layer is marked by a red ellipsoid. Area in green box was used for plot of the Gray value in the STEM image vs. the distance in Å (right).

In a small part of the sample an additional layer in the $Cu_x Cr_y Se_z$ phase was observed (red mark in Figure 5.18), which can be either a stacking fault or a secondary phase in the material. The interplanar distances H and K in the thicker $Cu_x Cr_y Se_z$ layer are in range of 2.9 - 3.1 Å and very similar (H, I and K in Figure 5.18) to the Se-Se distances in CuCrSe₂. Se-Se distances in CuCr₂Se₄ and CrSe₂ are between 2.9 and 3.0 Å indicating that the secondary phase might consist of an additional selenium layer. This secondary phase might be heterostructure C as this heterostructure has a slightly larger *c*-lattice parameter than heterostructure B. The X-ray diffraction patterns give no evidence that heterostructure C is present next to heterostructure B in sample 3 annealed at 400 °C. This could be due to low concentration of heterostructure C. Figure 5.19 (left) shows the STEM (ER-C) image of sample 4 annealed at 400 °C. Same as sample 3 sample 4 shows distinct layers with a double layered structure for the $\operatorname{Cu}_x \operatorname{Cr}_y \operatorname{Se}_z$ layer similar to sample 3. The gray value profile gives a larger *c*-lattice parameter for the superstructure which is according to the (00*l*) data of sample 4. The Cr-Cr distance is with 6.1 Å slightly larger than the Cr-Cr distance in sample 3 (5.7 Å). As the Cr-Cr distances in CuCrSe₂, CrSe₂, and CuCr₂Se₄ are rather similar an assignment of the structures based on the Cr-Cr distance is not possible. The Se-Se distance in a Cu_xCr_ySe_z single layer Figure 5.19 (right) corresponds to the Se-Se distance in CuCrSe₂, CuCr₂Se₄ and CrSe₂. The Nb-Nb distance in sample 4, as shown for sample 3, is larger than the bulk value. The larger Nb-Nb distance indicates that the copper intercalation into the NbSe₂ layer also occurs in sample 4.

Sample 3 and 4 have the same stacking along the c-axis and the individual layers have similar distances although their *c*-lattice parameters are slightly different and they were prepared with different deposition parameters. This shows that slight variations in the atomic composition of the precursor do not change the layering in the sample and only have a small effect on the atomic distances. Similarly, Johnson *et al.* revealed that SnV ferecrystals exhibit a change in atomic distances if the Sn/V ratio is varied but keep the atomic layering scheme.^[115] This suggests that the heterostructure B can be prepared in a wide range of Cu/Cr ratios. Which is surprising as only small variations in the annealing temperature are needed to transform the heterostructure B into heterostructure C and D.



Figure 5.19: Representative STEM images of sample 4 annealed at 400 °C (left). Area in green box was used for plot of the gray value in the STEM image vs. the distance in Å (right).

5.7. Summary

A new set of ferecrystals has been successfully prepared, were the usual rock salt phase was exchanged by a $Cu_x Cr_y Se_z$ layer. These new ferecrystals allow the preparation of four structurally different heterostructures by varying the annealing temperature. This is the first ferecrystalline material which gives access to multiple heterostructures depending on the used annealing temperature. The precise transition temperatures of the heterostructures and if two heterostructures are present at the same annealing temperature could be revealed by further, high resolution, temperature dependent X-ray diffraction studies.

X-ray diffraction patterns revealed that the reproducibility of the samples is not perfect due to limitations of the used deposition system. Samples with three different Cu/Cr ratios were prepared with distinct variations in the *c*-lattice due to the variation of the Cu/Cr ratio. Heterostructures A, B, and D could be prepared in all investigated samples regardless of the Cu/Cr ratio.

In contrast to the superstructure *c*-lattice parameter, the in-plane lattice parameters are not affected by the transformation into the different heterostructures or the Cu/Cr ratio. The *a*-lattice parameters of NbSe₂ indicate a copper intercalation into the NbSe₂ layers as the *a*-lattice parameter is in comparison to the bulk values considerably enlarged. Copper intercalation into TMDs especially NbSe₂ is a known phenomenon^[65,66] as copper has a high tendency to diffuse through nanolayers^[67–69] and even bulk materials.^[65] The in-plane lattice parameters of the Cu_xCr_ySe_z double layer do not allow an unambiguous assignment of the crystal structure to one of the possible structures. The atomic distances and lattice parameters of Cu_xCrSe₂ and the copper deficient part of CuCr₂Se₄ are too similar for a clear distinction.

STEM images reveal a double layered structure for $Cu_x Cr_y Se_z$, supporting the assumption that the $Cu_x Cr_y Se_z$ layer consists of either $Cu_x CrSe_2$ or copper deficient part of $CuCr_2Se_4$. EDX line scans and STEM gray values indicate that the $Cu_x Cr_y Se_z$ layer consists of two Cr layers indicating the $Cu_x CrSe_2$. A less occupied chromium position in between the two chromium layers, which would correspond to the copper deficient part of $CuCr_2Se_4$, could not be ruled out. In some parts of the samples a secondary phase is observed. This might be another heterostructure or heterostructure C indicating that with the transformation into the different heterostructures a change in the layering along the c-axis occurs.

In future work EDX line scans with higher resolution will be performed in order to get a better understanding how the different heterostructures are formed and how they transform into each other. Another objective of this EDX study will be the investigation of the secondary phase found in sample 3 and whether the secondary phase corresponds to one of the observed heterostructures or if it is a new, fifth heterostructure.

6. Structural investigation of the $Cu_x Cr_y Se_z$ constituent

6.1. Introduction and aim

Transformation of crystal symmetry in bulk as well as in nanomaterials^[129,130] has a major impact on the materials properties. Even subtle modifications of the structure such as strain,^[131-134] change in site occupency^[135-137] or lattice distortions^[138-140] may have a major impact on electrical, catalytic, and magnetic properties. Therefore, a detailed analysis of the crystal structure of a material is essential for an explanation of its properties.

Slight variations in the site occupancies in SnV ferecrystals have a strong effect on the lattice parameters, the electric resistivity, and the Hall coefficient.^[115] Similarly, the structure transformation from α to β -SnSe heavily affects the electric properties in associated ferecrystals.^[109]

In the previous chapter, the formation of various heterostructures with varying annealing temperatures was presented. In the present chapter, different model layering schemes for the $Cu_x Cr_y Se_z$ part of the structure are discussed and applied as starting models for Rietveld refinement.

6.2. Comparison of different models for the $Cu_x Cr_y Se_z$ layer

The bulk CuCr₂Se₄ structure has two possible atomic arrangements along the [111] axis, that contain four selenium layers, a Cu deficient and a Cr deficient structure. It is also possible that the Cu_xCr_ySe_z layer is made of CuCrSe₂. CuCrSe₂ has a layered structure of CdI₂-type CrSe₂²⁻ layers that are stacked along the c-axis (Figure 6.1, left). Copper is tetrahedrally coordinated by Se²⁻ and fills ¹/₂ of the tetrahedra. The selenium forms a distorted octahedral coordination sphere around the Cr³⁺.^[123,141] It crystallizes in the trigonal space group R3m with an *a*-lattice parameter of 3.679(1) Å and a *c*-lattice parameter of 19.385(5) Å.^[123]

For the model of CuCrSe₂ layers in the ferecrystals, a model where copper is in a symmetrically position between the $CrSe_2^{2-}$ layers has been used (Figure 6.1, right). The double layer structure has the composition $Cu_{0.5}CrSe_2$, *i.e.*, $CuCr_2Se_4$, but differs in its layering scheme from the CuCr₂Se₄ spinel. As the copper distances between the different $CrSe_2^{2-}$ layers are not equal in the bulk structure,^[123] an asymmetrical

model was also considered.



Figure 6.1: Crystal structure of $CuCrSe_2^{[123]}$ and assumed layering scheme for the ferecrystal with Cu in symmetrical position between the $CrSe_2^{2-}$ layers (Cu occupation might be lower).



Figure 6.2: Crystal structure of CrSe₂.^[142]

As we assume that copper might diffuse through the system, it is also possible that the $Cu_x Cr_y Se_z$ layer is made of a $CrSe_2$ double layer with intercalated copper, *i.e.*, $Cu_x CrSe_2$. $CrSe_2$ crystallizes in the $Cd(OH)_2$ structure type with the space group $P\bar{3}m1$.^[142,143] Chromium is octahedrally coordinated by selenium and forms $CrSe_2$ layers that are stacked along the c-axis.

All three structural models would result in a double layer structure as seen in the STEM image for set 3 (chapter 5, Figure 5.17). EDX line scan indicated that the $Cu_x Cr_y Se_z$ layer consists of a $Cu_x CrSe_2$ double layer.

As EDX line scans revealed that copper diffused over the whole system and chromium is hard to refine next to copper in a Rietveld refinement based on X-ray data, it is challenging to make an unambiguous assignment of the atomic positions in $Cu_x Cr_y Se_z$. Therefore, individual refinements according to the proposed structure models are carried out and discussed in comparison in the following.

Ferecrystalline materials usually exhibit Kiessig fringes due to interferences at the film/substrate and air/film interfaces along the (00l) direction. These Kiessig fringes overlap with Bragg reflections and can not be modelled in a Rietveld refinement. Prior to the Rietveld refinement Le Bail fits were therefore performed to reduce the error and stabilize the refinement of reflection profiles. During the Le Bail fit, clattice parameter, zero shift, background and profile parameters are refined. These parameter are fixed in the Rietveld refinement, leaving only atomic site parameters to be refined. The Le Bail fit represents the best possible fit for the data and was compared to the Rietveld refinement results. X-ray diffraction in out-of-plane geometry gives for ferecrystals only information on the projection of the crystal structure along c, due to the orientation of the layers along the c-axis. This preferred orientation is simulated by setting the a and b-lattice parameters to very small values (0.5 A)which shifts the h and k reflections to Q ranges larger than the simulated range. The in-plane diffraction patterns were handled similarly by setting the *c*-lattice parameter to 0.5 Å. During the Rietveld refinement the z coordinate, occupation, and isotropic vibrational parameter are refined. The vibrational parameter is kept equal for all atoms. The space group $P\bar{3}m1$ was used for the refinement. $P\bar{3}m1$ imposes a mirror plane in the center of the unit cell, which limits the number of atomic planes required to model the data.

The sample with two NbSe₂ layers prepared with the parameters of sample 3 annealed at 350 °C was taken to test the Rietveld refinement. This sample was easily fitted by a Le Bail fit and is therefore an ideal candidate to test different models. For all refinements, the same profile parameters, *c*-lattice parameters, background, and zero shift derived from the same Le Bail fit are used. The sample was modeled as a stack of two NbSe₂ layers and two $Cu_x Cr_y Se_z$ layers. The layering in the $Cu_x Cr_y Se_z$ layer was changed according to the Cu-deficient $CuCr_2Se_4$, Cr-deficient $CuCr_2Se_4$ and $CuCrSe_2$ structure. These three different types of layering were used as starting models for the Rietveld refinement. A propagation of copper over the whole unit cell was not considered in the models.

The Cu-deficient $CuCr_2Se_4$ model was used to refine the out-of-plane data. Figure 6.3 shows the measured and simulated patterns. For visualization of the low intensity reflections, the data is also plotted in log scale. The obtained occupation and atomic plane distances are illustrated in Figure 6.4. For the Cu-deficient $CuCr_2Se_4$ model, the (0.0.14) reflection appears to be extinct, whereas the reflection is clearly visible in the experimental data. Besides that the calculated pattern from the Rietveld refinement still gives a good simulation of the reflection intensities. Calculated occupations

for the Cr1 strongly deviate from those expected for Cu-deficient $CuCr_2Se_4$ (Figure 6.4 left). Moreover, the atomic distances in the $CuCr_2Se_4$ layer determined from the Rietveld refinement are completely different from the bulk material (Figure 6.4). This indicates that the Cu-deficient model is not appropriate to describe the data.



Figure 6.3: X-ray diffraction patterns of the 1:2 sample with the calculated background and difference between experimental and simulated pattern using the Cudeficient model in linear (left) and log scale (right).



Figure 6.4: Comparison of atomic plane distances in Å along c-axis and site occupancies from the Rietveld refinement (left) and from the starting model derived from the bulk values for the Cu-deficient model (right).

Refinement results of the Cr-deficient model were used to refine the (00l) data. The results of the Rietveld refinement are shown in Figure 6.5. Calculated atomic distances and site occupanies for the bulk model as well as the refined values are given in Figure 6.6. Rietveld refinement does not simulate the (0.0.11) reflection besides that the calculated pattern from the Rietveld refinement still gives a good simulation of the peak intensities. The copper and chromium occupations are double of the

expected values. The atomic distances for Cu1-Cr1 in the $Cu_x Cr_y Se_z$ layer are much smaller than in the bulk material. The z-coordinates and site occupancies appeared to be heavily correlated indicated by unstable fits. Therefore, these parameters were excluded from the last step of the refinement. This underlines that the Cr-deficient $CuCr_2Se_4$ is not an appropriate model to describe the sample.



Figure 6.5: X-ray diffraction patterns of the 1:2 sample with the calculated background and difference between experimental and simulated pattern using the Crdeficient model in linear (left) and log scale (right).



Figure 6.6: Comparison of atomic plane distances in Å along c-axis and site occupancies from the Rietveld refinement (left) and from the starting model derived from the bulk values for the Cr-deficient model (right). * not refined in last refinement step.

The Rietveld refinement using the $CuCrSe_2$ model gives a match of the simulated and observed reflections as shown in Figure 6.7. Moreover, atomic distances along the c-axis obtained from the Rietveld refinement are in good agreement with the model (Figure 6.8). For example the Se1-Cu1 distance is close to the bulk distances 1.67 and 1.74 Å calculated and bulk values, respectively. The copper occupation is lower than the expected value for $CuCrSe_2$. The atomic distances derived from the Rietveld refinement are according to the atomic distances determined from the gray value plot of the STEM image (5.19).

Besides the copper occupation all the other parameters are in agreement with the bulk material. The fit profile matches the intensity profile of the data, which indicates that CuCrSe₂ is the best model to describe the data.



Figure 6.7: X-ray diffraction patterns of the 1:2 sample with the calculated background and difference between experimental and simulated pattern using the $CuCrSe_2$ model in linear (left) and log scale (right).

Occ	Rietveld result	Occ		Starting model	
1	1.92	Origin	1 -	1.68	Origin
1	1.36	Sel Nb1	1 -	1.68	- Nb1
1	1.32	Se2	1 =	1.68	Se2
	3.69		-	2.89	
0.988(2)	1.41	Se3	1 - 1 -	1.34	Se3 Cr1
0.988(2) 0.988(2)	1.26	Cr1 Se4	1 -	1.49	Se1
0.30(1)	1.67	0.5, Cu1	0.5 -	1.74	0.5, Cu1
• • •		-			

Figure 6.8: Comparison of atomic plane distances in Å along c-axis and site occupancies from the Rietveld refinement (left) and from the starting model derived from the bulk values for the CuCrSe₂ model (right).

The bulk structure of CuCrSe_2 has a layered structure of CrSe_2^{2-} layers with copper (Cu1) filling tetrahedral sites. For the previous refinement, a model where copper is in symmetrically located between the CrSe_2 layers has been used. As in the bulk

structure copper is not in a symmetrical position between the $CrSe_2$ layers, an asymmetrical model has to be considered.

The results of the symmetrical CuCrSe₂ have been used as starting parameters and the Cu z-coordinate starting value was set to 0.45. A refinement of all z-coordinates simultaneously was not possible as the fit diverges. Apparently, the site occupancies and remaining z-coordinates are not significantly affected by the change in copper position. As the variation of the copper position has no major effect on the refined parameters, the symmetric CuCrSe₂ seems to be an appropriate model to describe the (Cu_xCr_ySe_z)_{1+ δ}(NbSe₂)₂ sample annealed at 350 °C.

The R-values of the four different refinements in Table 6.1 are for all models in the same range for all models and do not allow to differentiate a better fit.



 Table 6.1: R-values of the Rietveld refinements.

Figure 6.9: X-ray diffraction patterns of the 1:2 sample with the calculated background and difference between experimental and simulated pattern using the asymmetric $CuCrSe_2$ model in linear (left) and log scale (right).



Figure 6.10: Comparison of atomic plane distances in Å along c-axis and site occupancies from the Rietveld refinement (left) and from the starting model derived from the bulk values for the asymmetric CuCrSe₂ model (right). * not refined in last refinement step.

6.3. Structural differences in heterostructure A and B

The Rietveld refinement of the 1:2 sample annealed at 350 °C indicated that $Cu_x CrSe_2$ is the best starting model of the tested models to refine the out-of-plane data. Therefore this model was used to refine the out-of-plane data of the 1:3 sample of set 3 annealed at 350 °C (sample 3 A) and 400 °C (sample 3 B).

Figure 6.11 gives the Rietveld refinement of sample 3 annealed at $350 \,^{\circ}$ C. All reflections besides the (0.0.22) are simulated by the Rietveld refinement, indicating that the CuCrSe₂ model is a suitable model to describe heterostructure A of sample 3. During the Rietveld refinement it was not possible to refine the copper occupation. As the 1:3 sample contains an additional NbSe₂ layer, the model became more complex and therefore less stable than the refinement of the 1:2 sample. Sample 3 is also very smooth and has Kiessig Fringes to high Q which increases the background. Sample 3 A contains reflections of heterostructure A and C, which makes the simulation of the peak profile more challenging.

The Rietveld refinement of sample 3 B is given in Figure 6.12, showing that besides the (0.0.12) and (0.0.22) all reflections are simulated. Same as for sample 3 A it was not possible to refine the copper occupation. The refined atomic distances for the CuCrSe₄ layer agree well with the atomic distances from the CuCrSe₂ model indicating that the model is suitable to describe the heterostructures A and B of sample 3. The atomic Se1-Se2 distance in NbSe₂ depicted in Figure 6.13 (left) is larger than in bulk NbSe₂ (6.13 right), indicating an intercalation of copper between the layers. The Se1-Se2 distance decreases from sample 3 A (6.13 middle) to sample 3 B, indicating that

the amount of intercalated copper is reduced. Sample 3 B was annealed to a higher temperature and therefore contains less selenium. A more uniform propagation of copper is also possible.

This indicates that in heterostructures A and B, the $Cu_x Cr_y Se_z$ layer is a $Cu_x CrSe_2$ with a lower copper occupation than in the bulk compound. The different heterostructures might vary in their copper intercalation in the van der Waals gaps and consequential in their atomic distances.



Figure 6.11: X-ray diffraction patterns of sample 3 A with the calculated background and difference between experimental and simulated pattern using the CuCrSe₂ model in linear (left) and log scale (right).



Figure 6.12: X-ray diffraction patterns of sample 3 B with the calculated background and difference between experimental and simulated pattern using the $CuCrSe_2$ model in linear (left) and log scale (right).


Figure 6.13: Atomic plane distances in Å along c-axis and occupation from the Rietveld refinement using the symmetric CuCrSe₂ model for sample 3 A (left), sample 3 B (middle), and the bulk values for symmetric CuCrSe₂ model (right). * not refined in last refinement step.

6.4. Preparation of $[(Cu_x Cr_y Se_z)_{0.5}]_{1+\delta}(NbSe_2)_3$

The atomic distances derived from STEM gray values, EDX line scan and Rietveld refinement of the 1:2 and 1:3 sample, indicate that the $Cu_x Cr_y Se_z$ double layer has four selenium layers.

A sample with only one copper layer would reduce the amount of parameters to be refined. Therefore, it was tried to prepare a sample with only one $\text{Cu}_x \text{Cr}_y \text{Se}_z$ layer. It was aimed for a $[(\text{Cu}_x \text{Cr}_y \text{Se}_z)_{0.5}]_{1+\delta}(\text{NbSe}_2)_3$ sample (sample 6) as samples with three NbSe₂ were easier prepared with a suitable crystallinity in previous experiments.

For the sample preparation, the same layering scheme as for the 1:3 samples has been used to prevent the formation of CuSe₂. The deposition parameters for the Cu_xCr_ySe_z layer were reduced by 1/2 resulting in the deposition parameters in Table 6.2. The deposition parameters are based on the parameters of sample 4.

		sample 6				
	Få	Rate	Tooling Factor			
Nb	7.7	0.2	64			
Se	8.3	0.5	65			
Se	3.7	0.5	65			
Cr	2.6	0.2	64			
Cu	2.1	0.2	64			
Cr	2.6	0.2	64			
Se	3.7	0.5	65			

Table 6.2: Parameters for preparation of the $[(Cu_x Cr_y Se_z)_{0.5}]_{1+\delta}(NbSe_2)_3$ sample 6

6.5. Structure of $[(Cu_xCr_ySe_z)_{0.5}]_{1+\delta}(NbSe_2)_3$



Figure 6.14: X-ray diffraction patterns of sample 6 (black line) and sample 4 (green line) annealed at 400 °C in the range of 0.4 - 4.5 Å.

In comparison to sample 4, sample 6 has a lower crystallinity as reflections for example the reflections (005) - (007), are extinct. All reflections can be indexed as (00*l*) reflections indicating that even though the sample has a poor crystallinity, it is aligned along the c-axis. This indicates that a double layer structure of $Cu_x CrSe_2$ is essential for a good crystallinity of the $[(Cu_x CrSe_2)_{1+\delta}]_1(NbSe_2)_n$ ferecrystals.

For the Rietveld refinement of sample 6, a variation of the CuCrSe₂ model with Cr in the 0.5 position was used (Figure 6.15, right). The atomic distances derived from the Rietveld refinement in the NbSe₂ layers and the Cu_xCrSe₂ are much lower than the expected bulk values (Figure 6.15, left). This indicates that the Cu_xCrSe₂ model is not appropriate to describe the single Cu_xCr_ySe_z layer.

The *c*-lattice parameter of sample 6 is 25.48(3) Å which corresponds to the *c*-lattice parameter of sample 4 reduced by 1/2 of the $Cu_x Cr_y Se_z$ double layer thickness. This

indicates that even though the structure of sample 6 seems to be different, the total thickness of the $Cu_x Cr_y Se_z$ single layer is similar to the $Cu_x Cr_y Se_z$ layer in sample 4. This is not surprising since all discussed compounds for the $Cu_x Cr_y Se_z$ double layer have similar *c*-lattice parameters.



Figure 6.15: Comparison of atomic plane distances in Å along c-axis and site occupancies from the Rietveld refinement for sample 6 (left) and from the starting model derived from the bulk values for the $CuCrSe_2$ model (right).

Figure 6.16 gives the in-plane diffraction patterns of sample 4 and 6. Due to the lower content of $Cu_x Cr_y Se_z$, the reflections of NbSe₂ have a higher intensity in sample 6. As a result, the $(220)_{Cu_x Cr_y Se_z}$ and $(520)_{Cu_x Cr_y Se_z}$ reflections appear in sample 6 only as shoulder of the NbSe₂ reflections. Therefore, the determination of the *a*-lattice parameter is more challenging and the *a*-lattice parameters of $Cu_x Cr_y Se_z$ in sample 6 might be underestimated. No reflections of a secondary phase can be seen in sample 6.

By reducing the $\text{Cu}_x \text{Cr}_y \text{Se}_z$ party to a single layer, the *a*-lattice parameter of NbSe₂ was not affected (Table 6.3). The *a*-lattice parameters of the $\text{Cu}_x \text{Cr}_y \text{Se}_z$ layer in sample 6 (7.21(1) Å) is reduced by 0.1 Å in comparison to sample 4 (7.30(1) Å), which might be due to a change in structure.

Table 6.3: Calculated a-lattice parameters and misfit parameter of the samples 4 B and 6and their corresponding heterostructures.

	$\mathrm{Cu}_x \mathrm{Cr}_y \mathrm{Se}_z \ a \ [\mathrm{\AA}]$	NbSe ₂ a [Å]	misfit δ
Sample 4 B	7.30(1)	3.501(9)	0.460
Sample 6	7.21(1)	3.515(3)	0.475



Figure 6.16: In-plane diffraction patterns of sample 4 and 6.

6.6. Summary

Diffraction and electron microscopy data discussed in the previous chapter 5 indicated a $Cu_x CrSe_2$ structure. A variation of the $CuCr_2Se_4$ structure could not be excluded. A $(Cu_xCr_ySe_z)_{1+\delta}(NbSe_2)_n$ compound with n = 2 was prepared and Rietveld refinement of the out-of plane diffraction pattern was performed to determine the structure of the $Cu_xCr_ySe_z$ layer. Four structure models for the $Cu_xCr_ySe_z$ layer were tested. A symmetric variation of the $CuCrSe_2$ structure gave the best fit for the data of the 1:2 data set.

In order to gain more detailed information on the different heterostructures in the 1:3 samples, the Cu_xCrSe_2 model was used to refine samples with three NbSe₂ layers annealed to 350 and 400 °C. A refinement with all parameters was not possible but an adequate description of the atomic distances was achieved. The refined Se-Se distances in the NbSe₂ and between NbSe₂ and Cu_xCrSe_2 are considerably larger in the sample annealed to 350 °C (heterostructure A) than in the sample annealed to 400 °C (heterostructure B). This indicates that the structural difference in the heterostructures is based on the copper intercalation in the van der Waals gaps.

Rietveld refinement on samples with only one $Cu_x Cr_y Se_z$ layer did not give a sufficient fit indicating that the $Cu_x CrSe_2$ model is not appropriate to describe the data. The sample with a $Cu_x Cr_y Se_z$ single layer had a poorer crystalinity underlining that the $Cu_x Cr_y Se_z$ double layer is essential for a decent crystallinity.

The Rietveld refinement data indicates that the $Cu_x Cr_y Se_z$ double layer in $(Cu_x Cr_y Se_z)_{1+\delta} (NbSe_2)_n$ has the structure of $Cu_x CrSe_2$. For further investigation, EDX line scans focusing on the copper intercalation would allow an assignment of copper occupations and verify if the structural changes in the heterostructures are based on the copper intercalation in the van der Waals gaps.

7. $[(Cu_x Cr_y Se_z)_{1+\delta}]_1 [NbSe_2]_n$ ferecrystals

7.1. Introduction and aims

In the previous chapter 5, the influence of the annealing condition and the copper chromium ratio on the formation of different heterostructures in $[(Cu_x Cr_y Se_z)_{1+\delta}]_1(NbSe_2)_3$ ferecrystals was discussed. Previous work showed that increasing the amount of TSe₂ dimensionality *n* systemically changes structure,^[79] resistivity,^[104,128,144] charge density wave transition temperature,^[104] transport properties,^[145] and superconducting transition temperature.^[128] The amount of NbSe₂ reception units per superstructure *n* might therefore affect the heterostructure formation.

The magnetic properties such as interlayer coupling of multilayered materials can be modified by systematic variation of the non magnetic spacer thickness.^[146] Clake and Freedman^[147] showed that the interlayer (ferromagnetic) and intralayer (antiferromagnetic) coupling for $(BiSe)_{1.23}(CrS_2)_n$ misfit materials can be altered by introducing a BiSe spacer.

Changing the separation layer thickness n in range of n = 1 - 5 may alter the phase composition in case of significant copper diffusion as well as the structure and magnetic properties. To investigate the correlation of structural and magnetic interface effects in magnetic ferecrystals with n series, $[(Cu_x Cr_y Se_z)_{1+\delta}]_1(NbSe_2)_n$ ferecrystals were prepared.

7.2. Sample preparation

The deposition parameters, which were obtained through the calibration process described in chapter 5.2, enabled the preparation of smooth samples with a high crystallinity. The deposition parameters of sample 3 (Table 5.1) were used to obtain a set of samples with n = 1 - 5 layers, referred to as set 3 in the following discussion. The amount of Nb|Se repetitions deposited in between the Se|Cr|Cu|Cr|Se is equal to n. The samples of set 3 were annealed to 350 °C and 400 °C aiming for heterostructure A and B.

7.3. Structural investigation of set 3 with n = 1 - 5

Reflectivity scans of set 3 annealed at $400 \,^{\circ}\text{C}$ show uniform Kiessig fringes up to high Q (Figure 7.1 left) which indicates that the material is a smooth multilayered ma-



Figure 7.1: Specular diffraction patterns of set 3 annealed at 400 °C in the range of 0 - 0.5 Å^{-1} and 0.4 - 4.5 Å^{-1} . * = sample holder



Figure 7.2: Representation of the change in c-lattice parameter as a function of the number of NbSe₂ layers n.

terial. The superstructure is crystalline along the staking direction, and all Bragg reflections can be indexed as (00*l*) of the superlattice (Figure 7.1 right). The linear trend in the function of *c*-lattice parameter and amount of NbSe₂ layers, *n*, (Figure 7.2) enables to calculate the single layer thickness of the NbSe₂ and Cu_xCr_ySe_z layer, respectively. The slope of the measured multilayer thickness corresponds to the single layer thickness of the NbSe₂ along *c* and has a dimension of 6.47(4) Å, which is larger than found in bulk material (6.291 Å).^[124] The increased thickness might result from the copper intercalation in the NbSe₂ layer. The EDX data of $[(Cu_xCr_ySe_z)_{1+\delta}]_1[NbSe_2]_3$ annealed at 400 °C also indicates a copper intercalation into the NbSe₂ layer (chapter 5.6). In Cu_{0.06}NbSe₂ the *c*-lattice parameter is not affected by the copper intercalation.^[148] The change in *c*-lattice in the NbSe₂ might hence result from a larger amount of copper intercalation.

The y-axis intercept (Figure 7.2) corresponds to the $Cu_x Cr_y Se_z$ layer thickness along

c and has a value of 12.2(1) Å, which is slightly smaller than found in bulk CuCr₂Se₄ $(12.66 \text{ Å})^{[56]}$ or CuCrSe₂ $(12.93 \text{ Å}).^{[149]}$ This might be due to a loss of copper into the NbSe₂ layer. Scince the *c*-lattice parameter as a function of *n* has linear trend, the copper intercalation has to be systematically with *n*. A table with the *c*-lattice parameters of set 3 can be found in the appendix D.1.



Figure 7.3: Specular diffraction patterns of set 3 annealed at 350 °C in the range of 0 - 0.5 Å^{-1} and 2.9 - 4.5 Å^{-1} . The sample annealed at 400 ° is pictured below in black. *=sample holder

Figure 7.3 gives the specular diffraction patterns of set 3 annealed at 350 °C (colour) and 400 °C (gray). The samples of set 3 annealed at 400 °C have a slight shift of the reflection position to higher Q. This effect is observed at low Q ranges (Figure 7.3 left) and more distinct in high Q ranges (Figure 7.3 right). Surprisingly, the shift to higher Q values in the 1:4 sample is much smaller than for the other samples and the *c*-lattice parameter of the 1:1 samples is the same after annealing at 350 and 400 °C. Possibly the transition temperature from heterostructure A to B is not the same for all samples of set 3. It is also possible that the different heterostructures can not be formed in all samples of set 3. Another explanation would be that the heterostructures A and B have only a small shift or no shift in the *c*-lattice parameter for the n = 1, 4. Moreover, it is not clear which part of the layer is responsible for the heterostructure transformation. An effect of the NbSe₂ layer thickness *n* on the transformation can not be excluded.

Besides the different *c*-lattice parameters, the samples annealed at different temperatures have a slightly different intensity profile. This change in the intensity profile can be observed in the XRD pattern of the 1:4 sample (Figure 7.4 (left)). The different intensity profiles could be explained by a transition from heterostructure A to B even though the shift in *c*-lattice parameter is rather low. Distinct reflections of a heterostructure B can only appear for sample 1:3 (Figure 7.4). A detailed discussion on the different heterostructures in the 1:3 samples can be found in chapter 5.4. The separate diffraction pattern of the 1:1 sample has unsymmetrical Bragg reflections indicating the overlap with a second phase.^[150] The limitations of reproducibility in the sample series might be the reason that the other compounds in series 3 have no distinct reflections of heterostructure B. Another reason might be that the structure of the 1:3 sample in series 3 facilitates the formation of heterostructure B at lower temperatures.



Figure 7.4: Specular diffraction patterns of the 1:4 sample of set 3 annealed at 350 °C in the range of 0.4 - 4.5 Å^{-1} (right). The 1:4 sample of set 3 annealed at 400 °C is pictured below in black. Specular diffraction patterns of the $[(Cu_x Cr_y Se_z)_{1+\delta}]_1(NbSe_2)_4$ sample annealed at 350 °C in the range of 0.4 - 4.5 Å^{-1} (left).

7.4. Magnetic Properties of CuCr₂Se₄, CuCrSe₂, and CrSe₂

Bulk CuCr₂Se₄ is metallic conducting and has a Curie temperature T_C above room temperature. T_C is affected by impurities^[151–153] and deviations from the perfect spinel composition.^[154] Therefore, a rather broad range of Curie temperatures of 415 - 460 K^[155–158] has been stated. Zhang *et al.* investigated the T_C by various techniques and obtained a T_C value of 430 K.^[159] The magnetic easy axis in CuCr₂Se₄ is along [111].^[156] This affects the in-plane and out-of-plane field dependent magnetization in crystallographically aligned films.^[58] Besides structural and compositional variations, the T_C is also affected by the crystallite size.^[160] Wang *et al.* investigated that a decreasing particle size decreases the saturation magnetisation, the Curie constant, T_C , and the effective magnetic moment per Cr (values for the bulk material are given in Table 7.1).^[160,161] Nanocrystalline CuCr₂Se₄ is only ferromagnetic below its blocking temperature, which is also size dependent.^[159,161,162] Two contradicting models for the electronic and magnetic states in $CuCr_2Se_4$ have been discussed in literature and will be summarized in the following.

Lotgering and van Stapele proposed the electronic configuration $Cu^+(Cr^{3+}Cr^{4+})Se_4^{2-}$.^[155] Indirect coupling of the Cr^{3+} and Cr^{4+} ion spins via holes in the valence band explains the ferromagnetism. They propose that $CuCr_2Se_4$ conducts due to hole conduction, while e^- are transferred from Se_4^{2-} p-states to Cr^{4+} d-states.

Goodenough proposed a contradicting model with the suggested electronic configuration $\operatorname{Cu}^{2+}(\operatorname{Cr}^{3+})_2\operatorname{Se}_4^{2-}$.^[163] The overall ferrimagnetism is caused by nearest neighbour superexchange interactions, a ferromagnetic 90 ° cation-anion-cation interaction, and an antiferromagnetic cation-cation interaction (direct exchange and superexchange are shown in Figure 7.5). Neutron diffraction^[157,164] and nuclear magnetic resonance (NMR)^[165] experiments indicate a Cr^{3+} valence state.

Kimura *et al.*^[166] performed soft X-ray magnetic circular dichroism spectroscopy (XMCD) to characterize the electronic and magnetic states and showed that the valence state of Cr is 3^+ . They proposed a modified version of Goodenoughs model. The electronic structure is $\text{Cu}^+(\text{Cr}^{3+})_2\Box^{+1}\text{Se}_4^{2-}$. The holes induced into the Se 4p-states are necessary for the charge balance. Various band structure calculations^[57,167] and XMCD measurements^[168] support Kimuras model.

Saha-Dasgupta *et al.* performed multiple density of states (DOS) calculations revealing that the ferrimagnetism in CuCr₂Se₄ is stabilized if the angle Cr-Se-Cr gets close to 90° (in CuCr₂Se₄ the angle Cr-Se-Cr is 93.48°).^[169] They propose a kinetic energy driven mechanism. The Cr ions and the delocalized Se 4p band hybridization lead to a hole-mediated exchange. Their proposed electronic structure is $Cu^+Cr^{3+}_{\uparrow}Se^-_{\downarrow}Cr^{3+}_{\uparrow}Se^{2-}_{3}$. The metallicity is explained by the charge of the hole. This results are supported by modified Arrott plot, Kouvel–Fisher method,^[159] and band structure calculations.^[170]



Figure 7.5: Schematic illustration of direct exchange and superexchange.

In contrast to CuCr₂Se₄, CuCrSe₂ is an antiferromagnetic compound and a p-type

Table 7.1: Bulk values for the Curie constant C, effective magnetic μ_{eff} moment per Cr, Curie-Weiss Temperature Θ_W , Curie Temperature T_C , Néel temperature T_N , and second Néel temperature T_{N2} for CuCr₂Se₄, CuCrSe₂, and CrSe₂.

	$\mathrm{CuCr}_2\mathrm{Se}_4$	$CuCrSe_2$ ordered	CuCrSe ₂ disordered	CrSe_2
C [K]	$2.55^{[156]}$	$2.37^{[171]}$	$1.64^{[172]}$	
$\mu_{eff} \operatorname{Cr} \left[\mu_{\mathrm{B}} \right]$	$5.0^{[156,166]}$	$2.9^{[173]}$	$3.62^{[172]}$	$2.44^{[174]}$
Θ_W [K]		$5^{[173]}$	$31.82^{[172]}$	
T_C [K]	$430^{[159]}$			
T_N [K]		$55^{[173]}$	$55^{[172]}$	$157^{[175]}$
$T_{N2} \; [\mathrm{K}]$				$20^{[175]}$

conductor with a metal-like conductivity.^[176] The electronic configuration is $Cu^+Cr^{3+}Se^{2-}$.^[177] The indirect 90 ° Cr-Se-Se exchange is similar to $CuCr_2Se_4$ and ferromagnetic. The direct exchange between Cr-Cr is antiferromagnetic and depends on the Cr-Cr distance,^[149,171] while the magnetic easy axis is perpendicular to the c-axis as the direct exchange in CuCrSe₂ is stronger then the indirect interaction.^[178]

 $CrSe_2$ has a short Cr-Cr distance of 3.399 Å^[142] and is therefore a strong antiferromagnet. Its magnetic easy axis is perpendicular to the c-axis as the Cr-Cr is shorter along the a- and b-axis. The electronic configuration is $Cr^{4+}Se^{2-}$.^[174] CrSe₂ monolayers can be switched from antiferromagnetic to ferromagnetic by strain induction.^[179]

7.5. Macroscopic magnetization

Temperature dependent zero field (ZFC) and field cooled (FC) susceptibility χ curves have been measured for the 1:1, 1:2, 1:3, and 1:5 sample of set 3. χ was corrected for a diamagnetic contribution χ_D and a linear term χ_T . The linear term was derived phenomenologically and might be related to substrate impurities as the substrates were not necessarily pure silicon.

The corrected susceptibility χ_{corr} was calculated with a modified Curie-Weiss-law:

$$\chi_{\exp} = \frac{C}{T - \theta} + \chi_T T + \chi_D \tag{7.1}$$

$$\chi_{\rm corr} = \chi_{\rm exp} - \chi_T - \chi_D \tag{7.2}$$

Here M is the volume magnetization, H the applied magnetic field, T the temperature, C the Curie constant, and θ the Curie-Weiss temperature.

Figure 7.6 (left) shows χ before the correction with χ_D and χ_T . The modified Curie-Weiss-law has been fitted to χ (black line). Figure 7.6 (right) shows the corrected χ_{corr} as a function of temperature.



Figure 7.6: Temperature dependent susceptibility curves for the 1:1, 1:2, 1:3, and 1:5 samples of set 3 annealed at 400 °C (left). Corrected susceptibility as a function of the temperature (right). Samples were measured in FC and ZFC (pale colours) at 0.25 T.

The FC curves for the 1:1 sample exhibit a distinct splitting to the ZFC curve (Figure 7.4) giving strong evidence that there is a low temperature cooperative magnetism in this sample. This splitting is also present in the 1:2 sample but less pronounced. In the 1:3 and 1:5 samples, no splitting between the ZFC and FC curve is observed, which indicates that above a separation layer thickness of n = 2 no or a non detectable interlayer coupling occurs.

The χ_{corr} has been used to plot the inverse susceptibility χ^{-1} , which is represented in Figure 7.7. χ^{-1} has been used to fit C, and θ . Table 7.2 gives the calculated values for χ_D , χ_T , C, and θ . The corrected values for χ_D and χ_T are similar for the 1:2, 1:3, and 1:5 sample and have a larger deviation for the 1:1 sample. It might be that another type of silicon wafer has been used for the 1:1 sample which would lead to a different background. C increases with decreasing n, underlining the effect of non the interlayer coupling (Table 7.2). θ is -48 K for the 1:1 sample indicating an antiferromagnetic coupling which would be expected for CuCrSe₂. With increasing nincreases θ underlining a reduction of the magnetic coupling. All values for C and θ are below the bulk values of CuCrSe₂ (Table 7.1).

The effective magnetic moment μ_{eff} per Cr was calculated by a notional lattice with the in-plane lattice parameters of NbSe₂ and the *c*-lattice parameter of the supercell. By knowing that the amount of niobium atoms per supercell is $z(Nb) = \eta$, the z(Cr)



Figure 7.7: Temperature dependent inverse susceptibility curves for the 1:1, 1:2, 1:3, and 1:5 samples of set 3 annealed at 400 °C. Samples were measured in FC and ZFC (paler colours) at 0.25 T.

Table 7.2: Correction parameters for the diamagnetic susceptibility χ_D and linear susceptibility χ_T as well as Curie constant C and Curie-Weiss temperature θ for each sample.

	1:1	1:2	1:3	1:5
$\chi_T [\mathrm{K}^{-1}]$	$8.6(2) \cdot 10^{-6}$	$2.19(2) \cdot 10^{-6}$	$2.10(2) \cdot 10^{-6}$	$2.15(2) \cdot 10^{-6}$
$\chi_D \; [\mathrm{K}^{-1}]$	$-7.9(1) \cdot 10^{-3}$	$-2.914(7) \cdot 10^{-3}$	$-3.5394(6) \cdot 10^{-3}$	$-3.260(5) \cdot 10^{-3}$
C [K]	0.74(2)	0.0400(6)	0.0180(5)	0.0167(4)
θ [K]	-48(2)	-2.8(3)	-1.4(5)	1.1(5)

can be calculated from the Cr/Nb ratio derived from XRF. Dividing z(Cr) by the volume of the notional lattice $V_{\eta} \eta(Cr)$ can be derived. μ_{eff} is thus given by:

$$\frac{z(Cr)}{V_{\eta}} = \eta(Cr) \tag{7.3}$$

$$\mu_{eff}[J/T] = \sqrt{\frac{3 \cdot C k_{\rm B}}{\mu_0 \eta(\rm Cr)}} \tag{7.4}$$

$$\mu_{eff}[\mu_{\rm B}] = \frac{\mu_{eff}[J/T]}{\mu_{\rm B}} \tag{7.5}$$

Here, μ_B is the Bohr magneton $(9.274 \cdot 10^{-24} \text{ JT}^{-1})$ and k_B the Boltzmann constant $(1.380 \cdot 10^{-23} \text{ JK}^{-1})$.

 μ_{eff} given in Table 7.3, deviates strongly from the value for Cr⁺³ (3.87 µB) and the μ_{eff} of CuCrSe₂ (3.62 - 3.87 µB) (Table 7.1). The μ_{eff} of the 1:1 sample is even higher than the μ_{eff} of CuCr₂Se₄ (6.0 µB). Colominas calculated a μ_{eff} of 6 µB if a cation Cu⁺ occurs next to Cr⁺³.^[164] Therefore, the Cu_xCrSe₂ layer might contain a significant amount of Cu⁺. A change in the Cr-Se-Cr angle also has a major impact

	1:1	1:2	1:3	1:5
$\mu_{eff} [\mathrm{J/T}]$	$5.5(9) \cdot 10^{-23}$	$1.4(2) \cdot 10^{-23}$	$1.1(2) \cdot 10^{-23}$	$1.2(2) \cdot 10^{-23}$
$\mu_{eff} \; [\mu_{\mathrm{B}}]$	6(1)	1.5(2)	1.2(2)	1.3(2)
Cr $\%$	155	38	31	33

Table 7.3: Effective magnetic moment μ_{eff} per Cr and percentage of chromium assuming that only spin only Cr is present.

on the magnetism in CuCr₂Se₄.^[169] Distortions in the structure might be the cause of the increased μ_{eff} as well.

In Figure 7.8, temperature dependent plots of χ_{corr} and χ^{-1} are represented for the 1:2 samples annealed at 350 and 400 °C. It can be observed, that the sample annealed to $350 \,^{\circ}\text{C}$ has a slightly stronger susceptibility, a slightly larger C, and a smaller θ as the sample annealed to 400 °C. For the calculation of the μ_{eff} , the in-plane lattice parameters were used. As for the 1:2 sample annealed at 350 °C, the X-ray diffraction pattern in in-plane geometry was not measured. Instead the in-plane lattice parameters of the annealed at 400 °C have been used for this sample. The Curie-Weiss temperature is significantly smaller for the 1:2 sample annealed at 350 °C than for the 1:2 sample annealed at 400 °C indicating a stronger antiferromagnetic coupling for the sample annealed at 350 °C. The Curie constant is slightly larger for a lower annealing temperature and the derived μ_{eff} is slightly larger for the sample annealed at 350 °C. The previous chapter showed that the samples annealed at 350 and $400 \,^{\circ}\text{C}$ vary in their Se-Se distances which is probably caused by a variation in copper occupation. The sample annealed at 350 °C might therefore contain a higher amount of Cu⁺, leading to a higher μ_{eff} . This indicates that the different heterostructures might have varying μ_{eff} depending on the Cu⁺ distribution.

Field dependent isothermal magnetization measurements were performed between -2T and 2T. In order to determine the diamagnetic content in the field dependent measurements, linear fits between 1.7 and 2T were performed. The corrected magnetization M was plotted against the applied filed.

The field dependent measurements reveal a significant magnetization despite the small magnetic volume of the samples. According to the temperature dependent χ measurements, the samples exhibit a decreased saturation magnetization (M_S) with increasing n, and the samples with n = 1, 2 have a coercivity (Hc) > 0. Multiple temperature dependent magnetization curves were measured (Figure 7.10) to analyze the temperature-dependent change in M_S and Hc. The coercivity (Figure 7.10, right) shows a clear trend towards zero with increasing temperature. This is in line with



Figure 7.8: Temperature dependent corrected susceptibility and inverse susceptibility curves for the 1:2 samples of set 3 annealed at 350 and 400 °C. Samples were measured in FC and ZFC (pale colours) at 0.25 T.

Table 7.4: Correction parameters for the diamagnetic susceptibility χ_D , linear susceptibility χ_T , Curie constant C, Curie-Weiss temperature θ , effective magnetic μ_{eff} moment per Cr, and percentage of chromium assuming that only spin only Cr is present for 1:2 sample annealed at 350 and 400 °C.

	$1{:}2~350{}^{\circ}\mathrm{C}$	$1:2~400^{\circ}{\rm C}$
$\chi_T [\mathrm{K}^{-1}]$	$2.76(2) \cdot 10^{-6}$	$2.19(2) \cdot 10^{-6}$
$\chi_D [\mathrm{K}^{-1}]$	$-3.879(8) \cdot 10^{-3}$	$-2.914(7) \cdot 10^{-3}$
C [K]	0.0686(8)	0.0400(6)
θ [K]	-11.4(3)	-2.8(3)
$\mu_{eff} [{\rm J/T}]$	$1.8(2) \cdot 10^{-23}$	$1.4(2) \cdot 10^{-23}$
$\mu_{eff} \; [\mu \mathrm{B}]$	2.0(2)	1.5(2)
$\mathrm{Cr}~\%$	51	38

the ZFC/FC measurements as a splitting in those measurements is only observed to $\approx 13 \text{ K}$. M_S as a function of temperature as expected a similar trend as the ZFC measurement (Figure 7.10).



Figure 7.9: Field dependent magnetization curves at 5 K of the 1:1, 1:2, 1:3, and 1:5 sample of set 3 annealed at 400 °C.

Table 7.5: Saturation magnetization M_S and coercivity μ_0 Hc derived the field dependent magnetization curves at 5 K.

	1:1	1:2	1:3	1:5
$M_S [{\rm A/m}]$	19551(261)	8321(140)	4158(168)	4202(131)
$\mu_0 \text{Hc} [\text{T}]$	-0.04(1)	-0.03(1)	0	0



Figure 7.10: Temperature dependent corrected susceptibility for the 1:1 samples of set 3 annealed at 400 °C. The temperatures at which field depended measurements were performed are marked in the curve (left). Coercivity (left y-axis) and saturation magnetization (right y-axis) as a function of temperature (right).



7.6. Polarized neutron reflectometry

Figure 7.11: a) X-ray reflectometry data (blue) from the 1:1 sample annealed at 400 °C of set 3 and simulated data (continuous gray). b) The same data modelled with a lower resolution.

To obtain information about the depth resolved magnetometry of the modulated layers, polarized neutron reflectometry (PNR) experiments at 5 K were performed. Prior to the PNR measurements X-ray reflectometry (XRR) was performed to determine the nuclear scattering length density (SLD) profile. The *c*-lattice parameter was derived from the out-of plane diffraction patterns and not refined here. The refinement algorithm is based on the work of Bijerka *et al.*,^[180] a detailed description can be found in chapter 9.3.5. Ferecrystals usually have a less smooth bottom and top area than the core of the nanolaminate. Thus, a substrate area and an end area are defined were the SLD is allowed to deviate from the periodic area. Figure 7.11 a) shows the measured XRR pattern and the simulated data. A second fit was performed with a lower resolution to suppress the Kiessig Fringes and model only the pattern shape. Both fits are observed to model the XRR pattern. The corresponding SLD profiles are represented in Figure 7.12. Both profiles have a similar modulation underlining the reliability of the profile. The periodic area in the SLD has 39 repetitions and three distinct modulations. The STEM images of 1:3 samples

in chapter 5.6 showed that the Cu_xCrSe_2 layer has a double layer structure. Two layers of the modulation would then correspond to the Cu_xCrSe_2 layer and one to the NbSe₂ layer. Two of the modulations have a higher SLD of $\approx 70 \cdot 10^{-6} \text{ Å}^{-2}$ which is in the range of the bulk SLD of $CuCrSe_2$ (57.57 Å⁻²) indicating that these correspond to the Cu_xCrSe_2 double layer. The third layer has a SLD slightly above the SLD of NbSe₂.



Figure 7.12: Scattering length density profile as a function of the distance z. Bulk SLD values are given in purple, orange, and green for CuCrSe₂, CuCr₂Se₄, and NbSe₃, respectively. The area between the dotted lines corresponds to the unit cell and has 39 repetition units.

For the 1:1 and 1:3 samples, PNR measurements at 5 K under field cooled conditions were conducted at MARIA, MLZ and the results are represented in Figure 7.13. The 1:1 sample exhibits a distinct splitting of R^+ and R^- which is not present in the 1:3 sample. This underlines that above n = 2 no measurable magnetic interlayer coupling occurs. The splitting in the higher Q range $(0.7 - 0.1 \text{ Å}^{-1})$ is instrument related. Unfortunately, the real space resolution that can be derived from the PNR measurements is too low to distinguish the individual modulations in the SLD as for the XRR data. Therefore it was not possible to resolve the magnetic profile of the 1:1 sample. Further experiments should cover at least the first Bragg reflection (0.4 Å^{-1}) in order to get a reliable resolution of the SLD modulations.



Figure 7.13: a) Polarized neutron reflectometry curve for the 1:1 sample at 5 K under FC conditions with an applied field of 1 T. b) Polarized neutron reflectometry curve for the 1:3 sample at 5 K under FC conditions with an field of 1 T.

7.7. Summary

Diffraction and electron microscopy data as well as Rietveld refinement data discussed in the previous chapters 5 and 6 indicated a $Cu_x CrSe_2$ structure. Variations in annealing temperature and time showed a significant effect on the structure of the ferecrystals 5. In order to investigate the effect of NbSe₂ layers repetitions n on the magnetic properties, samples with n = 1 - 5 were prepared (set 3). In-plane and out-of-plane diffraction patterns confirm that samples with a systematic change in ncould be prepared. Set 3 could be prepared as heterostructure A and B by changing the annealing temperature from 350 °C to 400 °C.

Temperature dependent susceptibility measurements revealed a splitting of ZFC FC curves, which gives strong evidence that we prepared the first magnetic ferecrystals. The splitting of ZFC and FC is reduced with n revealing that the magnetic interlayer coupling depends strongly on n and is non detectable above n = 2.

The derived effective magnetic moment of the samples μ_{eff} is much higher for the 1:1 sample than for the bulk values of CuCrSe₂ or CuCr₂Se₄ indicating either the presence of Cu⁺ or the change in Cr-Se-Cr angle. The 1:2 sample annealed at 350 °C has a slightly higher μ_{eff} than the sample annealed at 400 °C. This reveals that the change in heterostructure due to a different annealing temperature also effects the magnetic properties of the samples. Rietveld refinements indicate increased copper intercalation into the NbSe₂ layers with increasing annealing temperature, which effects the change in heterostructure. The change in μ_{eff} might also be based on a change in copper occupation and an increase in concentration of Cu⁺ in the Cu_xCrSe₂ layer with decreasing annealing temperature.

The SLD profile derived from XRR data underlined that the $Cu_x Cr_y Se_z$ part of the structure is a derivative of CuCrSe₂. PNR showed a splitting in R^+ and R^- for the 1:1 sample but not for the 1:3 underlining the results of the ZFC FC measurements. An investigation of the magnetic modulation was not possible as the real space resolution that could be derived from the PNR data is not sufficient to distinguish the different layers in the unit cell. Future experiments should therefore measure at higher Q values to allow a clear assignment of the magnetic contribution to the different layers.

8. Conclusion and summary

Nanolaminates provide outstanding chemical, mechanical, and physical behaviours which are related to size-induced deviations of their atomic structure.^[7] Understanding the nucleation process and the atomic structure of the nanolaminates enables the prediction and modification of their properties.

1:1 ferecrystals were investigated using reciprocal space mapping revealing interlayer correlations particular in $[10l]_{TSe_2}$ $[20l]_{MSe}$. These correlations may arise due to three different factors: the a_{MSe} and b'_{TSe_2} need to coincide, the transition metal dichal-cogenide (TMD) should crystallize only in the 1T configuration, and the rock salt needs to be able to form a TMD during the nucleation step. This suggest that a wide range of 1:1 ferecrystals should contain interlayer correlations, but 1:1 ferecrystals without interlayer correlations may also exist. This model is critical in explaining the structure related properties in ferecrystals.

Using the modulated elemental reactants (MER) method, a new set of ferecrystals has been prepared exchanging the rock salt with a $Cu_x Cr_y Se_z$ layer. These ferecrystals allow the preparation of four structurally different heterostructures from one precursor by varying the annealing temperature. This demonstrates the ability of the MER method to synthesize kinetic products which are not accessible by other synthesis methods. Future EDX line scans with higher resolution will give a better understanding of the different heterostructures and might enable the preparation of further ferecrystals with controlled heterostructure formation.

Rietveld refinement has been used to gain a better understanding of the structure in the $Cu_x Cr_y Se_z$ layer. Comparing three different starting models, the goodness of fit indicates that the $Cu_x Cr_y Se_z$ layer is made of a $Cu_x CrSe_2$ double layer structure. Rietveld studies on samples annealed at 350 and 400 °C indicate that the structural variations in the different heterostructures is based on the copper intercalation. This information is critical in later studies to understand the magnetic properties of the materials. The knowledge that copper might be essential for the heterostructure formation will be crucial for the preparation of future ferecrystals containing copper.

Temperature dependent susceptibility measurements revealed that $[(Cu_xCrSe_2)_{1+\delta}]_1(NbSe_2)_n$ are the first magnetic ferecrystals. The distinct splitting of the polarized neutron reflectometry curves for the 1:1 raises the interesting question if the magnetism is based solely on the Cu_xCrSe_2 layer. Future PNR experiments will target a higher real space resolution to resolve the magnetic depth profile.

Furthermore, sample sets with a different TMD will reveal the influence of $NbSe_2$ on the structure and magnetic properties.

9. Experimental section

9.1. Sample preparation

All samples were prepared with the MER method (detailed description is given in section 3.2). The deposition parameters for the samples are given in Table 9.1 and 9.2. A detailed explanation how the deposition parameters are calibrated is given in chapter 5.2. The amount of deposited NbSe₂ layers n was varied between 1 - 5. For different n no further calibration was necessary and only the amount of Nb|Se repetitions between Se|Cr|Cu|Cr|Se has to be varied according to the desired n. Different amounts of atoms hit the substrate than the crystal monitor due to the different orientation of crystal monitor and substrate to the source. This is regulated by the tooling factor.

	<u> </u>				-					
	sample 1 and 4			sample 2 and 3			sample 5			
	F å	Rate	Tooling	$\mathrm{F} \mathrm{\mathring{a}}$	Rate	Tooling	F å	Rate	Tooling	
			Factor			Factor			Factor	
Nb	7.7	0.2	64	7.8	0.2	64	7.8	0.2	64	
Se	8.3	0.5	65	8.3	0.5	68	8.3	0.5	68	
Se	7.4	0.5	65	7.4	0.5	68	7.4	0.5	68	
Cr	5.1	0.2	64	3.3	0.2	68	64	0.2	64	
Cu	4.1	0.2	64	4.5	0.2	68	64	0.2	64	
Cr	5.1	0.2	64	3.3	0.2	68	64	0.2	64	
Se	7.4	0.5	65	7.4	0.5	64	68	0.5	68	

Table 9.1: Parameters for preparation of $[(Cu_x Cr_y Se_z)_{1+\delta}]_1(NbSe_2)_n$ samples.

The as deposited precursors were transferred into a glove box and annealed on a hot plate to temperatures between 100 and 600 °C.

9.2. Instruments

9.2.1. Bruker AXS D8

High angle and low angle X-Ray diffraction experiments were carried out on a *Bruker* AXS D8 X-ray diffractometer with $CuK_{\alpha 1}$ radiation ($\lambda = 1.54051$ Å) at the University of Oregon Center for Advanced Materials Characterization (CAMCORE), Eugene,

		sample 6				
	F å	Rate	Tooling Factor			
Nb	7.7	0.2	64			
Se	8.3	0.5	65			
Se	3.7	0.5	65			
Cr	2.6	0.2	64			
$\mathbf{C}\mathbf{u}$	2.1	0.2	64			
Cr	2.6	0.2	64			
Se	3.7	0.5	65			

Table 9.2: Parameters for preparation of the $[(Cu_x Cr_y Se_z)_{0.5}]_{1+\delta}(NbSe_2)_3$ sample 6.

USA. A series of alignment measurements was made with every sample to correct the sample position.

Wide angle $\theta/2\theta$ measurements were performed in the range of $2\theta = 6.0 - 65.1$ and a step size of 0.1. The exit beam was modulated with a 0.6 mm slit and a Nickel filter. X-ray reflectivity measurements were performed in the range of $2\theta = 0 - 7.0$ and a step size of 0.01. The exit beam was modulated with a 0.1 mm slit.

9.2.2. ID03

Synchrotron X-ray scattering was measured at the $ID03^{[181]}$ beamline at the European Synchrotron Radiation Facility (ESRF), Grenoble, France. An incident X-ray energy of 24 keV was used. Sample detector (maxipix detector) distance was 940 mm, the beam size $100 \cdot 50 \,\mu\text{m}$ with the central pixel at 339, 329 (referred to as ID03-1). The pixel size is $0.055 \,\text{mm}$. In a second beamtime (referred to as ID03-2) was the sample detector distance 961 mm, the beam size $600 \cdot 30 \,\mu\text{m}$ with the central pixel at 164, 292. The pixel size is $0.055 \,\text{mm}$.

All measurements were performed at room temperature. For data reduction of the X-ray diffraction patterns in in-plane (hk0) geometry and the reciprocal space maps the *BINoculars* software was used.^[182,183]

Background correction and data reduction of X-ray diffraction patterns in out-ofplane (00*l*) geometry were performed with the *aps_slicereduce* program written by Dominique Dresen, University of Cologne, Germany (section 9.3.2).

9.2.3. BM-33-C

Synchrotron X-ray scattering using a *Pilatus 100K* detector was measured at the BM-

33-C beamline at the Advanced Photon Source (APS), Chicago, USA. An incident X-ray energy of 16 keV was used. Sample detector distance was 1115 mm, the beam size $900 \cdot 500 \,\mu\text{m}$ with the central pixel at 214, 90. The pixel size is $0.172 \,\text{mm}$. All measurements were performed at room temperature. Background of the X-ray diffraction patterns in in-plane (hk0) geometry were corrected with the substract_two_areas code written by Dominique Dresen. A defined area on the edge of the detector image is defined as background and subtracted form each image. The data reduction was performed with powderscan by the APS which works similar to the BINoculars code. Background correction and data reduction of X-ray diffraction patterns in out-of-plane (00l) geometry were performed with the aps_slicereduce code written by Dominique Dresen (section 9.3.2).

9.2.4. Electron probe microanalyzer

The atomic ratios of the amorphous and crystalline materials where determined using the *Cameca SX50* electron probe microanalyzer. An 8 mm square section was cut out of the samples and glued on an aluminium sample holder. The sites of the sections were painted with carbon to provide a conductive path to the sample holder.

9.2.5. XRF

XRF measurements were performed on a *Rigaku ZSX-II* at room temperature. The instrument belongs to the *CAMCORE*, Eugene, USA. The instrument was calibrated with films whose compositions were determined by electron probe microanalyzer. The film contained a range of Cu, Cr, Nb and Se contents.

9.2.6. MARIA

Polarized neutron reflectometry measurements were performed at the *MAgnetic Re-flectometer with high Incident Angle (MARIA)*^[184] at the *Heinz Maier-Leibnitz Zentrum (MLZ)*, Garching, Germany. The instrument is operated by the *Jülich Center for Neutron Science (JCNS)*. Wavelength selection is achieved by a velocity selector. The incident beam is polarized by a polarizing guide, the expected polarized flux is $5 \cdot 10^7 \text{ n cm}^{-2} \text{ s}^{-1}$ for 3 mrad collimation. The sample detector distance was 1910 mm, the beam size was $50 \cdot 50 \text{ mm}$ with the central pixel at 24, 600. The pixel size was 0.63 mm.

The applied field of 1 T was generated by a *Bruker electromagnet*. The sample was cooled by a He closed cycle cryostat to 5 K. The used neutron wavelength was 6 Å. Measurements were performed in the range of $Q = 0.01 - 0.44 \text{ Å}^{-1}$

9.2.7. STEM

The STEM samples were prepared by the method developed by Schaffer *et al.* using a *FEI Helios D600*.^[185] Schaffer *et al.* modified the known in-situ lift out technique^[186] by applying a thick protective carbon layer. In second steps wedges are milled with a thinner bottom, while getting thinner the sides are adjusted to get parallel. Therefore, the protective layer will not be destroyed during thinning. An *Omniprobe 200* was used for the in-situ lift-out. STEM images were acquired on an FEI aberration-corrected *Titan 80-300*. All instruments belong to the *CAMCORE*, Eugene, USA. Gray values along the c-axis were determined using *ImageJ* by *National Institute of Health*, USA.^[187]

9.2.8. STEM and EDX at PNNL

Samples were prepared according to the description in chapter 9.2.7. STEM images and EDX measurements were performed on an FEI aberration-corrected *Titan* G2~80-200 with an acceleration voltage of 200 kV at the *Pacific Northwest National* Laboratory (PNNL), Portland, USA. The instrument is equipped with array of four *FEI SuperX* windowless X-ray detectors. To improve the quality of the EDX spectrum images, an integration over multiple drift corrected frames was conducted. Measurements and data processing were performed by Dr. Gavin Mitchson and Dr. Jeffrey Ditto.

9.2.9. STEM and EDX at ER-C

Samples were prepared according to the description in section 9.2.7 using an *FEI* Helios NanoLab 400S at the Ernst Ruska-Centre for Microscopy and Spectroscopy with Electrons (ER-C), Jülich, Germany. STEM images and EDX measurements were performed on an FEI aberration-corrected Titan G2 80-200 CREWLEY with an acceleration voltage of 200 kV at the ER-C. The instrument is equipped with a FEI SuperX EDX System with 120 mm² Combined Detector Area. Measurements and data processing were performed by Dr. Andras Kovacs.

9.2.10. SQUID

Temperature and field dependent magnetic moment measurements were performed at an *MPMS-XL SQUID Magnetometer* by *QuantumDesign*. The instrument belongs to the *JCNS*, Jülich, Germany. Samples were placed in a plastic straw which was sealed at the bottom with a plastic plug. The width of the sample was slightly larger than the diameter of the straw so the sample would be fixed without any additional attachment. The straw was pulled over the sample holder. Sample holder and plastic plug were secured with kapton tape. To enable the evacuation of the straw and prevent oxygen contamination it was punctured at the bottom with a needle. As all samples were weakly magnetic, a piece of floppy disk was placed on the back of the sample and attached with sticky tape. To protect the straw from contamination the sample was covered with a layer of sticky tape that was removed after the sample alignment. For centering multiple scans were performed until the sample position is $2 \,\mathrm{cm}$.

For all scans three measurements per point, with two scans per measurements, were performed. Zero field cooled measurements were performed between 5 and 300 K with a heating rate of 0.5 K/min and measuring in 1 K increments. The samples were cooled down in zero field, and after reaching 5 K the desired magnetic field (0.25 T) was applied and the sample heated to 300 K. Field cooled measurements were performed like ZFC measurements except that the field was applied prior cooling down.

Sample area $A_{\rm Si \ wafer}$ was calculated from its weight $m_{\rm sample}$ and thickness $h_{\rm wafer}$ using the density of silicon $\rho_{\rm Si}$ (2.336 g/cm³) (equation 9.1 and 9.2) as the weight of the sample is below the sensitivity of the used scale. Using the total film thickness $h_{\rm film}$ determined with the XRR data the volume $V_{\rm sample}$ of the film can be calculated (equation 9.3). The wafer thickness was determined with Micrometer by *Multoyo* with an accuracy of 0.01 mm. The susceptibility was calculated with equation 9.4.

$$V_{wafer} = m_{sample} * \rho_{\rm Si} \tag{9.1}$$

$$A_{\rm Si wafer} = V_{\rm wafer} / h_{\rm wafer} \tag{9.2}$$

$$V_{\text{sample}} = A_{\text{Si wafer}} * h_{\text{film}} \tag{9.3}$$

$$\chi = \frac{M[\text{emu/cm}^3] \cdot 10^3}{H[\text{Oe}] \cdot \frac{10^3}{4\pi}} = \frac{M[\text{emu/cm}^3]}{H[\text{Oe}]} \cdot 4\pi = \frac{M[\text{A/m}]}{H[\text{A/m}]}$$
(9.4)

9.3. Programs

9.3.1. Layer thickness

The total layer thickness of the samples was determined from the Kiessig fringes observed using XRR. The critical angle θ_c and fringe angles θ_i were determined with *Diffract Eva* by *Bruker*.

9.3.2. aps slicereduce

The *aps_slicereduce* code was written by Dominique Dresen. In the first step pixel ranges for a background slice and a specular slice were defined. The individual images generated by the 2D detectors then were corrected and rebinned to a rotated coordinate system. Usual rebinning algorithms use a near neighbour method. *aps_slicereduce* uses a pixel splitting. The rebinning algorithm used by *aps_slicereduce* performs a transformation from detector width coordinates into incident angles. The transformed data is saved on an evenly spaced rectangular grid. A rectangular area on the detector is not necessarily rectangular after transformation. The informations of the transformed rectangle is partitioned and assigned to the new rectangle. The new rectangle gets a proportional partition of the information depending on the degree of overlap between the old and new rectangle. The code of the rebinning algorithm is given in appendix chapter E.

The motor positions and corresponding angles are read from the spec file. Especially in the area of high intensity reflections the scaling of the background is not correct, therefore a background roi at the edge of the detector is defined and subtracted. In a second step the data is transformed to 2θ and in the final step xy-files of the specular and off-specular part of the scan are generated.

9.3.3. Le Bail fits and Rietveld refinements

Le Bail^[121] fits and Rietveld^[188] refinements were carried out with the *General Struc*tural Analysis System $(GSAS)^{[189]} EXPGUI^{[190]}$ software package. The background was fit using a shifted Chebyschev polynomial.

9.3.4. Fits

All fits that are not stated differently were performed with the built-in fit function of *Gnuplot*.

Yannic Falke, University of Cologne, assisted writing the code for the Gaussian fits of the intensity profiles along Q_z using the python package NumPy.

9.3.5. Refinement of X-ray reflectivity data

For refinement of XRR data the *periodic_reflectometry* code written by Dominique Dresen, University of Cologne was used. The algorithm in *periodic_reflectometry* is based on the algorithm of Bijkerka *et al.*.^[180] For the refinement sublayers of the substrate area, the periodic area, and the end area of the sample are defined. The optimum thickness of these sublayers d_{min} is defined by the maximal measured scattering vector Q_{max} :^[180]

$$d_{min} = \frac{\pi}{2Q_{max}} \tag{9.5}$$

For the analyzed XRR data d_{min} is 0.8 Å.

 χ^2 is supplemented to a regulation factor that reduces big steps in the SLD profile by motivating the second derivative to be minimized. A focus of the refinement on the first data points with high intensity and low deviations was avoided modifying χ^2 to:

$$\chi^2 = \sum (\log(\text{model}) - \log(\text{data}))^2$$
(9.6)

The SLD of the first point was fixed to the substrate SLD (silicon) and the SLD of the last point (air) was fixed to 0.

9.3.6. Diamond

For visualization of crystal structures *Diamond* - Crystal and Molecular Structure Visualization Software by *Crystal Impact* was used.

Appendix

A. Interlayer correlations in 1:1 ferecrystals

A.1. Le Bail and Rietveld refinement

	$[SnSe]_{1.14}[VSe_2]$		$[SnSe]_{1.2}$	$[SnSe]_{1.21}[TiSe_2]$		$.11[VSe_2]$
	SnSe	VSe_2	SnSe	TiSe_2	PbSe	VSe_2
Space group	I4	$P\bar{3}m1$	Pcmn	$P\bar{3}m1$	I4	$P\bar{3}m1$
a [Å]	5.919(1)	3.403(1)	5.969(6)	3.555(2)	6.079(3)	3.435(3)
b [Å]	= a	= a	6.078(3)	= a	= a	= a
GU	2912(46)	1023(95)	8218(254)	6639(457)	11750(422)	16060(1238)
GV	0	0	0	0	0	0
GW	0	0	0	0	0	0
LX	0	0	0	0	0	0
LY	50.2(9)	45(2)	131(2)	132(5)	189(3)	71(11)
wRp	0.0647		0.0443		0.0605	
RP	0.0469		0.0351		0.0475	
Zero	0.0048(2)		0.0022(6)		0.0091(6)	
Shift $[Å^{-1}]$						
Instrument	ID03-1		ID03-1	ID03-2	ID03-2	

 Table A.1: Le Bail fit results of the X-ray diffraction patterns in in-plane geometry.

	$[BiSe]_{1.}$	$_{11}[NbSe_2]$	$[BiSe]_{1.15}[TiSe_2]$		
	BiSe	$NbSe_2$	BiSe	TiSe_2	
Space group	Pcmn	$P\bar{3}m1$	Pcmn	$P\bar{3}m1$	
$a [{ m \AA}]$	4.50(1)	3.497(6)	4.565(3)	3.590(2)	
b [Å]	4.25(1)	= a	4.247(3)	= a	
GU	4.675(199)	32040(3247)	292(41)	4082(368)	
GV	0	0	0	0	
GW	0	0	0	0	
LX	0	0	0	0	
LY	432(16)	138(15)	245(4)	106(5)	
wRp	0.0374		0.0450		
RP	0.0281		0.0346		
Zero	0.019(2)		0.0172(6)		
Shift $[Å^{-1}]$					
Instrument	ID03-2		ID03-2		

 Table A.2: Le Bail fit results of the X-ray diffraction patterns in in-plane geometry.



Figure A.1: X-ray diffraction patterns in in-plane geometry with Le Bail fit background and difference between the experimental and the simulated pattern.



Figure A.2: X-ray diffraction patterns with out of plane geometry with the calculated fit background and difference between the experimental and the simulated pattern.

	$[SnSe]_{1.14}[VSe_2]$		$[SnSe]_{1.21}[TiSe_2]$		$[PbSe]_{1.11}[VSe_2]$	
	Le Bail	Rietveld	Le Bail	Rietveld	Le Bail	Rietveld
Space group	$P\bar{3}m1$		$P\bar{3}m1$		$P\bar{3}m1$	
c [Å]	12.079(2)		12.083(2)		12.282(6)	
GU	0		229(24)		829(357)	
GV	0		0		-81(39)	
GW	5.3(1)		4.0(1)		8.9(9)	
LX	0		1.34(2)		1.21(8)	
LY	23(5)		0		0	
wRp	0.1039	0.1453	0.1255	0.1595	0.2615	0.2631
RP	0.0949	0.1002	0.0725	0.0765	0.1598	0.1683
Zero Shift $[Å^{-1}]$	0.00057(8)		0.0004(1)		0.0025(2)	
Scale		86(2)		120.6(122)		12
	Z	Occ	Z	Occ	Z	Occ
Т	0	1	0	1	0	1
Se	0.1284(2)	1	0.1155(3)	1	0.1294(5)	1
Μ	0.3729(4)	0.55^{*}	0.3729(4)	0.588(1)	0.3634(7)	0.559(2)
Se	0.4046(5)	0.55^{*}	0.4182(3)	0.588(1)	0.424(2)	0.559(2)
Uios [Å 2*100]	1.6(3)		2.5*		20(1)	

Table A.3: Le Bail fit and Rietveld results. M = Sn, Pb T = V, Ti * Not refined

	$[BiSe]_{1.11}[NbSe_2]$		$[BiSe]_{1.15}[TiSe_2]$	
	Le Bail	Rietveld	Le Bail	Rietveld
Space group	$P\bar{3}m1$		$P\bar{3}m1$	
c [Å]	12.091(3)		11.817(3)	
GU	770(287)		1313(259)	
GV	-66(33)		-192(34)	
GW	8.9(9)		11(1)	
LX	0.9(2)		2.02(4)	
LY	1.6(5)		0	
wRp	0.1358	0.1453	0.2322	0.2760
RP	0.0804	0.1002	0.1412	0.1448
Zero Shift $[Å^{-1}]$	0.00057(8)		0.0023(2)	
Scale		86(2)		120.6(122)
	Z	Occ	Z	Occ
Т	0	1	0	1
Se	0.1284(2)	1	0.1258(6)	1
Μ	0.3729(4)	0.55^{*}	0.3683(9)	0.536(4)
Se	0.4046(5)	0.55^{*}	0.411(2)	0.536(4)
Uios [Å ² *100]	1.6(3)		2.5^{*}	

Table A.4: Le Bail fit and Rietveld results. M = Sn, Pb T = V, Ti * Not refined



A.2. Reciprocal space maps and Gaussian fits

Figure A.3: Intensity profiles of the reciprocal space maps along Q_z (left) with Gaussian fits of SnV (@ID03-1) and SnTi (@ID03-2) (right).



Figure A.4: Intensity profiles of the reciprocal space maps along Q_z (left) with Gaussian fits of PbV (@ID03-2) and BiTi (@ID03-2) (right).



Figure A.5: Intensity profiles of the reciprocal space maps along Q_z (left) with Gaussian fits of BiNb (@ID03-2) (right).


A.3. X-ray diffraction patterns of ferecrystals with m, n eq 1

Figure A.6: In-plane and out of plane X-ray diffraction patterns of SnV (top) and SnTi (bottom) ferecrystals.

In the (00l) and (hk0) X-ray diffraction scans, a few Si and secondary phase reflections are present. The in-plane diffraction data displays the increasing relative intensities expected for increasing m,n. Broad (11) and (31) reflections are observed in the rock salt phases. These are systematically extinct for the 3D crystal structures, but allowed for this 2D projection of the structure.^[99] The obtained results are consistent with previously published data.^[103,108,109] All scans were performed at ID03-2.

B. $[(Cu_xCr_ySe_z)_{1+\delta}]_1(NbSe_2)_3$ ferecrystals

B.1. Total thickness and c-lattice parameter of the 1:3 samples

Table B.1: c-lattice parameters and total thickness of the 1:3 samples 2 and 3 and theircorresponding heterostructures

	sample 2		sample 3	
	Total thickness $[Å]$	c [Å]	Total thickness $[Å]$	c [Å]
ad	1019(2)	33.20(4)	1010(10)	32.6(1)
$350^{\circ}\mathrm{C}$	987(2)	31.95(3)	950(6)	31.77(2)
$400^{\circ}\mathrm{C}$	931(1)	31.50(7)	926(4)	31.48(1)
$500^{\circ}\mathrm{C}$	932(4)	31.46(2)	-	-
600 °C	926(3)	31.34(4)	919(3)	31.1(1)

All scans on sample 1 and 2 were performed on the Bruker AXS D8.

Table B.2: Instruments used for measuring the out-of-plane diffraction patterns of 1:3samples 2 and 3 and their corresponding heterostructures

	sample 3	sample 4	sample 5
	Instrument	Instrument	
ad	Bruker AXS D8	Bruker AXS D8	-
$350^{\circ}\mathrm{C}$	ВМ-33-С	ВМ-33-С	Bruker AXS D8
$400^{\circ}\mathrm{C}$	ВМ-33-С	ID03-2	ВМ-33-С
600 °C	BM-33-C	Bruker AXS D8	Bruker AXS D8

Table B.3: c-lattice parameters and total thickness of the 1:3 samples 4 and 5 and theircorresponding heterostructures

	sample 4		sample 5		
	Total thickness $[Å]$	c [Å]	Total thickness [Å]	c [Å]	
ad	996(12)	32.3(1)	-	-	
$350^{\circ}\mathrm{C}$	-	-	1012(10)	32.18(7)	
$400^{\circ}\mathrm{C}$	956(12)	31.87(5)	928(5)	31.6(1)	
$500^{\circ}\mathrm{C}$	-	-	-	-	
$600^{\circ}\mathrm{C}$	-	-	812(22)	31.5(1)	



B.2. Le Bail fit of hk0 data

 $Q[A^{-1}]$ $Q[A^{-1}]$ **Figure B.1:** Gazing incident diffraction patterns of the $[(Cu_x Cr_y Se_z)_{1+\delta}]_1[NbSe_2]_3$ samples with Le Bail fit background and difference between experimental and simu-

lated pattern of sample 3 with heterostructure A and B.

In-plane diffraction patterns of samples 3 A, 3 B, and 5 B performed on BM-33-C. In-plane diffraction pattern of sample 4 B was performed on ID03-2.

	Sample 3 A		Sample	e 3 B
	$Cu_x Cr_y Se_z$	$NbSe_2$	$Cu_x Cr_y Se_z$	$NbSe_2$
Space group	$R\bar{3}m$	$P\bar{3}m1$	$R\bar{3}m$	$P\bar{3}m1$
$a \ [{ m \AA}]$	7.293(4)	3.508(6)	7.258(9)	3.504(6)
GU	8293(1207)	54860(5605)	0	0
GV	0	-17390(2559)	0	0
GW	619(64)	2340(292)	586(30)	387(81)
LX	9.5(9)	56(2)	28(1)	92(2)
LY	0	0	0	0
wRp	0.0771		0.0569	
RP	0.0591		0.0450	
Zero Shift $[Å^{-1}]$	0.119(2)		0.096(2)	

Table B.4: Le bail fit results of the x-ray diffraction patterns in in-plane geometry ofsample 3 with heterostructure A and B.



Figure B.2: Gazing incident diffraction patterns of the $[(Cu_xCr_ySe_z)_{1+\delta}]_1[NbSe_2]_3$ samples with Le Bail fit background and difference between experimental and simulated pattern of sample 4 and 5 with heterostructure B.

Table B.5: Le bail fit results of the x-ray diffraction patterns in in-plane geometry ofsample 4 and 5 with heterostructure B.

	Sample 4 B		Sample 5 B	
	$Cu_x Cr_y Se_z$	$NbSe_2$	$Cu_x Cr_y Se_z$	$NbSe_2$
Space group	$R\bar{3}m$	$P\bar{3}m1$	$R\bar{3}m$	$P\bar{3}m1$
a [Å]	7.30(1)	3.501(9)	7.228(9)	3.526(6)
GU	0	0	0	0
GV	0	0	0	0
GW	576(46)	192(20)	2856(354)	110(45)
LX	0	0	96(6)	63(2)
LY	300(13)	235(7)	0	0
wRp	0.0345		0.1141	
RP	0.0282		0.0870	
Zero Shift $[Å^{-1}]$	0.057(2)		0.089(2)	

B.3. XRF data of 1:3 data

Sample	e Cr $[at \%]$	Cu [at $\%$]	Nb [at %]	Se [at $\%$]
3 A	10.588	2.933	19.249	67.002
3 B	10.829	2.932	19.870	66.130
4 B	13.443	5.941	17.555	62.928
$5 \mathrm{B}$	7.615	5.759	19.881	66.503

Table B.6: Atomic % in sample 3 A, 3 B, 4 B, and 5 B determined by XRF.

C. Structural investigation of the Cu_xCr_ySe_z constituent

C.1. Rietveld refinement of 1:2 sample of set 3 annealed at $350 \ ^{\circ}C$

The measurements were performed at BM-33-C at the APS.

Space group	$P\bar{3}m1$
c [Å]	25.315(6)
GU	1941(135)
GV	129(27)
GW	21(2)
LX	3.04(6)
LY	0
wRp	0.1443
RP	0.0815
Zero Shift $[Å^{-1}]$	0.0106(2)

Table C.1: Le bail fit results of the X-ray diffraction patterns in out-of-plane geometry of 1:2 sample of set 3 annealed at 350 °C.

Cu-deficient				Cr-de	eficient		
wRp	0.1451			wRp	0.1461		
Rp	0.0814			Rp	0.0816		
Scale	345(5)			Scale	451()		
	Z	Occ	Occ		Z	Occ	Occ
		Rietveld	bulk			Rietveld	bulk
Se1	0.0767(2)	1	1	Se1	0.7486*	1	1
Nb1	0.1298(1)	1	1	Nb1	0.1300*	1	1
Se2	0.1814(2)	1	1	Se2	0.1886^{*}	1	1
Se3	0.329(2)	0.77(1)	0.910	Se3	0.3204*	0.892(2)	0.910
Cr1	0.322(8)	0.24(4)	0.683	Cu1	0.3704*	0.496(2)	0.228
Se4	0.3828(7)	0.77(1)	0.910	Cr1	0.3743*	0.496(2)	0.228
Cu1	0.4368(3)	0.30(1)	0.228	Cu2	0.4040*	0.496(2)	0.228
Cr2	0.5	0.228	0.228	Se4	0.4420*	0.892(2)	0.910
				Cr2	0.5	0.404(5)	0.683
Uios [Å2*100]	14.0(5)				14.5*		

 Table C.2: Rietveld results for the Cu and Cr-deficient models. * not refined in last refinement

($CuCrSe_2$ syn	n		$CuCrSe_2$ as	sym
wRp	0.1453		wRp	0.1457	
Rp	0.0822		Rp	0.0822	
Scale	367(5)		Scale	368(5)	
	Z	Occ		Z	Occ
		Rietveld			Rietveld
Se1	0.0758(2)	1	Se1	0.0758(2)	1
Nb1	0.1298(1)	1	Nb1	0.1297(1)	1
Se2	0.1821(2)	1	Se2	0.1823(2)	1
Se3	0.3282(2)	0.988(2)	Se3	0.3280(3)	0.985(2)
Cr1	0.3841(2)	0.988(2)	Cr1	0.3838(3)	0.985(2)
Se4	0.4338(3)	0.988(2)	Se4	0.4333(3)	0.985(2)
Cu1	0.5	0.30(1)	Cu1	0.4906^{*}	0.33(1)
Uios	15.7(4)				15.7(4)
$[Å^{2*}100]$					

Table C.3: Rietveld results for the symmetric and asymmetric $CuCrSe_2$ models. * notrefined in last refinement

C.2. Le Bail fit and Rietveld refinement of 00l data of 1:3 samples of set 3

The measurements were performed at BM-33-C at the APS.

	Le Bail	Rietveld
Space group	$P\bar{3}m1$	
c [Å]	31.687(6)	
GU	1086(84)	
GV	-136(15)	
GW	7.3(6)	
LX	1.49(4)	
LY	0	
wRp	0.2370	0.2686
RP	0.1611	0.2733
Zero Shift $[Å^{-1}]$	0.0022(1)	
Scale		120(3)
	Z	Occ
Nb	0	1
Se	0.050(2)	1
Se	0.151(2)	1
Se Nb	0.151(2) 0.205(2)	1 1
Se Nb Se	$\begin{array}{c} 0.151(2) \\ 0.205(2) \\ 0.254(2) \end{array}$	1 1 1
Se Nb Se Se3	$\begin{array}{c} 0.151(2) \\ 0.205(2) \\ 0.254(2) \\ 0.3532(2) \end{array}$	$ 1 \\ 1 \\ 1.120(3) $
Se Nb Se Se3 Cr1	$\begin{array}{c} 0.151(2) \\ 0.205(2) \\ 0.254(2) \\ 0.3532(2) \\ 0.4013(1) \end{array}$	$ \begin{array}{c} 1 \\ 1 \\ 1 \\ 1.120(3) \\ 1.120(3) \end{array} $
Se Nb Se Se3 Cr1 Se4	$\begin{array}{c} 0.151(2) \\ 0.205(2) \\ 0.254(2) \\ 0.3532(2) \\ 0.4013(1) \\ 0.4483(1) \end{array}$	$ \begin{array}{c} 1\\ 1\\ 1\\ 1.120(3)\\ 1.120(3)\\ 1.120(3) \end{array} $
Se Nb Se Se3 Cr1 Se4 Cu1	$\begin{array}{c} 0.151(2) \\ 0.205(2) \\ 0.254(2) \\ 0.3532(2) \\ 0.4013(1) \\ 0.4483(1) \\ 0.5 \end{array}$	$ \begin{array}{c} 1\\ 1\\ 1\\ 1.120(3)\\ 1.120(3)\\ 1.120(3)\\ 0.30^* \end{array} $

Table C.4: Le Bail fit and Rietveld results of 1:3 sample of set 3 annealed at 350 °C.

	Le Bail	Rietveld
Space group	$P\bar{3}m1$	
c [Å]	31.488(6)	
GU	0	
GV	0	
GW	6.5(2)	
LX	0	
LY	15.4(6)	
wRp	0.2937	0.3580
RP	0.1897	0.2291
Zero Shift $[Å^{-1}]$	0.013(2)	
Scale		120(3)
	Z	Occ
Nb	z 0	Occ 1
Nb Se	z 0 0.0531(3)	Occ 1 1
Nb Se Se	z 0 0.0531(3) 0.1513(3)	Occ 1 1 1
Nb Se Se Nb	z 0 0.0531(3) 0.1513(3) 0.2047(2)	Occ 1 1 1 1 1
Nb Se Se Nb Se	$\begin{array}{c} z \\ 0 \\ 0.0531(3) \\ 0.1513(3) \\ 0.2047(2) \\ 0.2554(3) \end{array}$	Occ 1 1 1 1 1 1 1
Nb Se Se Nb Se Se3	$\begin{array}{c} z \\ 0 \\ 0.0531(3) \\ 0.1513(3) \\ 0.2047(2) \\ 0.2554(3) \\ 0.3512(2) \end{array}$	Occ 1 1 1 1 1 1 1.158(5)
Nb Se Se Nb Se Se3 Cr1	$\begin{array}{c} z\\ 0\\ 0.0531(3)\\ 0.1513(3)\\ 0.2047(2)\\ 0.2554(3)\\ 0.3512(2)\\ 0.4020(2) \end{array}$	Occ 1 1 1 1 1 1.158(5) 1.158(5)
Nb Se Se Nb Se Se3 Cr1 Se4	$\begin{array}{c} z\\ 0\\ 0.0531(3)\\ 0.1513(3)\\ 0.2047(2)\\ 0.2554(3)\\ 0.3512(2)\\ 0.4020(2)\\ 0.4481(2) \end{array}$	$\begin{array}{c} \text{Occ} \\ 1 \\ 1 \\ 1 \\ 1 \\ 1 \\ 1 \\ 1.158(5) \\ 1.158(5) \\ 1.158(5) \end{array}$
Nb Se Se Nb Se Se3 Cr1 Se4 Cu1	$\begin{array}{c} z\\ 0\\ 0.0531(3)\\ 0.1513(3)\\ 0.2047(2)\\ 0.2554(3)\\ 0.3512(2)\\ 0.4020(2)\\ 0.4481(2)\\ 0.5 \end{array}$	$\begin{array}{c} \text{Occ} \\ 1 \\ 1 \\ 1 \\ 1 \\ 1 \\ 1 \\ 1.158(5) \\ 1.158(5) \\ 1.158(5) \\ 0.30^* \end{array}$

Table C.5: Le Bail fit and Rietveld results of 1:3 sample of set 3 annealed at 400 °C.

C.3. Le Bail fit and Rietveld refinement of 00I data of sample 6

The measurements of sample 6 $[(Cu_x Cr_y Se_z)_{0.5}]_{1+\delta}(NbSe_2)_3$ were performed at ID03-2 at the ESRF.



Figure C.1: X-ray diffraction patterns of sample 6 with the calculated background and difference between experimental and simulated pattern using the CuCrSe₂ model in linear (left) and log scale (right).

	Le Bail	Rietveld
Space group	$P\bar{3}m1$	
c [Å]	24.48(3)	
GU	0	
GV	0	
GW	34.3(8)	
LX	0	
LY	42(2)	
wRp	0.2766	0.2680
RP	0.1573	0.1543
Zero Shift $[Å^{-1}]$	0.0115(6)	
Scale		4.2(9)
	Z	Occ
Nb	0	1
Se	0.0320(8)	1
Se	0.220(1)	1
Nb	0.2536(8)	1
Se	0.2857(8)	1
Cu	0.3751^{*}	0.49(4)
Se	0.470(2)	1.25(2)
Cr	0.5	1.25(2)
Uios [Å ^{2*} 100]	0.734*	

Table C.6: Le Bail fit and Rietveld results of sample 6.

C.4. Le Bail fit of hk0 data of 6

The measurements were performed at ID03-2 at the ESRF.



Figure C.2: X-ray diffraction pattern in in-plane geometry of sample 6 with Le Bail fit background and difference between the experimental and the simulated pattern.

	$\mathrm{Cu}_x\mathrm{Cr}_y\mathrm{Se}_z$	$NbSe_2$
Space group	$R\bar{3}m$	$P\bar{3}m1$
a [Å]	7.203(6)	3.515(3)
GU	0	0
GV	0	0
GW	368(12)	634(12)
LX	0	0
LY	259(4)	329(4)
wRp	0.0241	
RP	0.0187	
Zero Shift [Å ⁻¹]	0.076(1)	

Table C.7: Le bail fit results of the X-ray diffraction patterns in in-plane geometry of 6 annealed at 400 $^{\circ}\mathrm{C}.$

D. $[(Cu_xCr_ySe_z)_{1+\delta}]_1[NbSe_2]_n$ ferecrystals

D.1. c-lattice parameters

All scans on set 3 were performed on BM-33-C. All scans on set 4 were performed on ID03-2.

	set 3 350 °C	set 3 400 $^{\circ}\mathrm{C}$	set 4
	c [Å]	c [Å]	c [Å]
1:1	18.402(2)	18.464(9)	15.1(6)
1:2	25.315(6)	25.2(1)	23.3(1.6)
1:3	31.687(6)	31.5(1)	31.9(4)
1:4	38.21(2)	38.2(1)	38.5(5)
1:5	44.76(1)	44.4(1)	44.4(5)

Table D.1: Calculated *c*-lattice parameters of set 3 and 4.



Figure D.1: Change in *c*-lattice parameter vs. the number of NbSe₂ layers of set 3 annealed at 400 °C.

The samples of set 4 have a poor crystallinity and therefor some 00l reflections are not visible. As the crystallinity of set 4 is inferior to set 3 a comparison of the intensity profile is pointless. There is no systematic change in the *c*-lattice parameter with increasing *n* (Figure D.2). The linear fit of the change in *c*-lattice parameter vs. *n* for n = 3 - 5 gives lattice parameters with rather high errors for NbSe₂ and CuCr₂Se₄ reflecting the irregular increase in *c*-lattice parameter. The estimated *c*lattice parameter for n = 1 - 3 gives values that are not related to NbSe₂, CuCr₂Se₄, CuCrSe₂ or CrSe₂.



Figure D.2: Specular diffraction patterns of set 4 annealed at 400 °C in the range of 0 - 0.5 Å^{-1} and $0.4 - 4.5 \text{ Å}^{-1}$. The samples of annealed at 350 °C is pictured below in black. Change in *c*-lattice parameter vs. the number of NbSe₂ layers. * = sample holder

D.2. Le Bail fit of hk0 data

High-resolution X-ray diffraction scans in the (hk0) direction were performed. The two constituents can be indexed independently for all samples like the corresponding 1:3 samples (see chapter 5.5). The 1:1 samples NbSe₂ could not be considered in the LeBail fit due to low reflection intensities. Therefore the *a*-lattice parameters of $Cu_x Cr_y Se_z$ in the 1:1 compounds might be overestimated. All sample sets show a systematic increase of the (hk0) reflection intensity for the NbSe₂ compound with increasing *n*. This can be clearly seen for the change of intensity for $(110)_{NbSe_2}$. By increasing the amount of NbSe₂ layers in the unit cell the intensity of $(110)_{NbSe_2}$ increases from a shoulder of the $(220)_{CuCr_2Se_4}$ to a distinct reflection (n = 4).

Besides the 1:1 and 1:5 sample of set 4, no other samples show reflections of a secondary phase as all reflection can be indexed as NbSe₂ or the hexagonal transformation of CuCr₂Se₄. The additional reflections (11) and (31) in set 4 are systematically extinct in the 3D crystal, but allowed for the 2D projection of the CuCr₂Se₄ structure.^[99] The *a*-lattice parameter of NbSe₂ in the ferecrystal is slightly larger than for the



bulk material (3.446 Å),^[56] indicating a certain degree of copper intercalation into Cu_xNbSe_2 . For comparison, $Cu_{0.667}NbSe_2$ has an *a*-lattice parameter of 3.487 Å.^[125]

Figure D.3: X-ray diffraction patterns in in-plane geometry with Le Bail fit background and difference between experimental and simulated pattern of set 3 annealed at 400 °C.

	1:1			1:2
	$CuCr_2Se_4$	$NbSe_2$	$\mathrm{CuCr}_2\mathrm{Se}_4$	$NbSe_2$
Space group	$R\bar{3}m$	$P\bar{3}m1$	$R\bar{3}m$	$P\bar{3}m1$
a [Å]	7.19(1)	Not refined	7.259(9)	3.491(6)
GU	2349000(1014)	-	9926(8089)	106300(7974)
GV	-1458000(0)	-	0	-45050(3667)
GW	208300(51)	-	446(43)	6039(450)
LX	30.8(6)	-	10.6(7)	46(3)
LY	0	-	0	0
wRp	0.0613		0.0746	
RP	0.0465		0.0577	
Zero Shift $[Å^{-1}]$	0.015(4)		0.076(2)	

Table D.2: Le Bail fit results of the X-ray diffraction patterns in in-plane geometry of set3 annealed at 400 °C.

Table D.3: Le Bail fit results of the X-ray diffraction patterns in in-plane geometry of set3 annealed at 400 °C.

	1:4	
	$CuCr_2Se_4$	$NbSe_2$
Space group	$R\bar{3}m$	$P\bar{3}m1$
a [Å]	7.230(6)	3.487(2)
GU	5257(604)	35940(2480)
GV	0	-10090(1042)
GW	1138(34)	1265(110)
LX	0	44.1(8)
LY	0	0
wRp	0.0511	
RP	0.0404	
Zero Shift $[Å^{-1}]$	0.085(1)	



Figure D.4: X-ray diffraction patterns in in-plane geometry with Le Bail fit background and difference between experimental and simulated pattern of set 3 annealed at 350 °C.

Table D.4: I	le Bail fit	results o	f the X-ra	y diffraction	patterns	in in-plane	geometry	of set
3	annealed	at 350°	С.					

	1:1		1	:5
	$CuCr_2Se_4$	$NbSe_2$	$CuCr_2Se_4$	$NbSe_2$
Space group	$R\bar{3}m$	$P\bar{3}m1$	$R\bar{3}m$	$P\bar{3}m1$
a [Å]	7.193(9)	Not refined	7.31(2)	3.51(2)
GU	15460(10450)	-	0	0
GV	-83350(6354)	-	0	0
GW	11570(897)	-	789(49)	1814(187)
LX	16.7(4)	-	31(2)	71(4)
LY	0	-	0	0
wRp	0.1134		0.0694	
RP	0.0731		0.0527	
Zero Shift $[Å^{-1}]$	0.015(2)		0.129(4)	



Figure D.5: X-ray diffraction patterns in in-plane geometry with Le Bail fit background and difference between experimental and simulated pattern of set 4 annealed at 400 °C.

	1:1		1:	2
	$\mathrm{CuCr}_2\mathrm{Se}_4$	$NbSe_2$	$\mathrm{CuCr}_2\mathrm{Se}_4$	$NbSe_2$
Space group	$R\bar{3}m$	$P\bar{3}m1$	$R\bar{3}m$	$P\bar{3}m1$
$a [{ m \AA}]$	7.23(1)	Not refined	7.330(9)	3.513(6)
GU	0	-	0	0
GV	0	-	0	0
GW	299(10)	-	570(4)	73(28)
LX	30.4(5)	-	0	71(1)
LY	0	-	0	0
wRp	0.0813		0.0407	
RP	0.0554		0.0298	
Zero Shift $[Å^{-1}]$	-0.003(2)		0.07(1)	

Table D.5: Le Bail fit results of the x-ray diffraction patterns in in-plane geometry of set4 annealed at 400 °C.

Table D.6: Le Bail fit results of the X-ray diffraction patterns in in-plane geometry of set4 annealed at 400 °C.

	1:4		1:5	
	$CuCr_2Se_4$	$NbSe_2$	$\mathrm{Cu}\mathrm{Cr}_2\mathrm{Se}_4$	$NbSe_2$
Space group	$R\bar{3}m$	$P\bar{3}m1$	$R\bar{3}m$	$P\bar{3}m1$
a [Å]	7.231(1)	3.482(2)	7.140(6)	3.490(3)
GU	0	0	0	0
GV	0	0	0	0
GW	1387(20)	453(52)	2390(17)	53(12)
LX	0	55(2)	0	51.2(7)
LY	0	0	0	0
wRp	0.1102		0.0323	
RP	0.0834		0.0243	
Zero Shift $[Å^{-1}]$	0.061(1)		0.0435(8)	

D.3. XRF data of 1:n data

Sample	Cr [at $\%$]	Cu [at $\%$]	Nb [at $\%$]	Se [at $\%$]
1:1	17.122	5.230	10.890	66.528
1:2	14.369	4.064	15.892	65.455
1:3	10.588	2.933	19.249	67.002
1:4	9.431	2.542	22.111	65.690
1:5	8.085	2.188	20.542	68.931

Table D.7: Atomic % in set 3 annealed at 350 °C determined by XRF.

Table D.8: Atomic % in set 3 annealed at $400 \,^{\circ}\text{C}$ determined by XRF.

Sample	Cr [at $\%$]	Cu [at %]	Nb [at %]	Se [at $\%$]
1:1	17.425	5.624	11.219	65.501
1:2	14.662	3.961	15.436	65.716
1:3	10.829	2.932	19.870	66.130
1:4	9.549	2.516	21.875	65.832
1:5	7.889	2.358	21.370	68.149

Table D.9: Atomic % in set 4 annealed at 400 $^{\circ}\mathrm{C}$ determined by XRF.

Sample	Cr [at $\%$]	Cu [at %]	Nb [at %]	Se [at %]
1:1	19.538	10.324	9.752	60.110
1:2	15.719	7.219	14.713	62.159
1:3	13.443	5.941	17.555	62.928
1:4	11.655	4.734	19.976	63.579
1:5	9.425	4.539	22.547	63.461

E. Rebinning algorithm of aps slicereduce

```
subroutine does_ray_intersect(ipoint, ipA, ipB, intersect_val)
1
       ! Given a point, does a ray going horizontally to the right
2
        ! intersict with line defined by pA and pB
3
        !\ compare with ray-casting algorithm of rosettacode.org
4
\mathbf{5}
        implicit none
        double precision, dimension(2), intent(in) :: ipoint, ipA, ipB
6
7
        logical, intent(out) :: intersect_val
        double precision, dimension(2) :: pA, pB, point
8
9
        double precision :: m_red, m_blue
10
        double precision, parameter :: eps = 1d-8
11
12
        intersect_val = .FALSE.
        ! make sure B is noted as point above A
13
14
        if (ipA(2) > ipB(2)) then
15
            pA = ipB
16
           pB = ipA
        else
17
18
           pA = ipA
19
            pB = ipB
20
        endif
21
        point = ipoint
22
        ! if point y value is on exactly same height as A or B, shift it upwards
23
        ! (avoid ray on vertex problem)
24
        if (point(2) = pA(2) . OR. point(2) = pB(2)) then
25
           point(2) = point(2) + eps
        endif
26
27
        ! is point above or below line or right of the line?
28
29
        if (point(2) > pB(2) . OR. point(2) < pA(2) . OR. point(1) > max(pA(1), pB(1))) then
30
            intersect_val = .FALSE.
31
        else
32
            ! is point left of A and B (and not above and not below) -> hit
33
            if (point(1) < min(pA(1), pB(1))) then
                intersect_val = .TRUE.
34
35
            ! point is in between, is it left or right of it?
            else
36
37
                ! find slope of AB
38
                if (abs(pB(1) - pA(1)) > tiny(0.d0)) then
39
                    m_{red} = (pB(2) - pA(2)) / (pB(1) - pA(1))
40
                else
41
                    m_{red} = huge(0.d0)
42
                end if
43
44
                ! find slope of AP
45
                if (abs(point(1) - pA(1)) > tiny(0.d0)) then
46
                    m_{blue} = (point(2) - pA(2)) / (point(1) - pA(1))
47
                else
48
                    m_blue = huge(0.d0)
49
                end if
50
51
                ! if slope of AP is greater than AB, it is left and therefore it hits
52
                if (m_blue >= m_red) then
53
                    intersect_val = .TRUE.
                else
54
                    intersect_val = .FALSE.
55
                end if
56
57
            end if
        end if
58
59
   end subroutine does_ray_intersect
60
61
    subroutine point_inside_polygon(point, polygon_trail, pip, Npolygon)
62
        implicit none
        !Check if pip using "Ray-casting algorithm"
63
64
        ! check whether point is inside polygon defined by polygon trail
        double precision, dimension(2), intent(in) :: point
65
66
        double precision, dimension(Npolygon, 2), intent(in) :: polygon_trail
        integer , intent(in) :: Npolygon
67
68
        logical, intent(out) :: pip
```

```
69
                 double precision, dimension(2) :: pA, pB
 70
 71
                  integer :: ipoly , jpoly , sumval
                 logical :: pipaddend
 72
 73
 74
                 sum val = 0
                 pip = .FALSE.
 75
 76
                  do ipoly=1, Npolygon
 77
                         jpoly = mod(ipoly+1, Npolygon+1)
 78
 79
                          if (jpoly .EQ. 0) jpoly = 1
 80
                         pA = polygon_trail(ipoly, :)
 81
                         pB = polygon_trail(jpoly, :)
 82
                         call does_ray_intersect(point, pA, pB, pipaddend)
 83
                          if (pipaddend) sumval = sumval + 1
 84
                 end do
 85
                  if (mod(sumval, 2) == 0) then
 86
                         pip = .FALSE.
 87
  88
                  else
                         pip = .TRUE.
 89
 90
                 end if
 91
         end subroutine point_inside_polygon
 92
 93
         subroutine append_point_to_polygon(point, poly_in, Npoly, poly_out)
 94
                  implicit none
 95
                 double precision, dimension(2), intent(in) :: point
 96
                 double precision, dimension(Npoly, 2), intent(in) :: poly_in
 97
                 integer , intent(in) :: Npoly
                 double precision, dimension(Npoly+1, 2), intent(out) :: poly_out
 98
 99
                 integer :: i
100
101
                 do i=1, Npoly
102
                         poly_out(i,:) = poly_in(i,:)
103
                  end do
                         poly_out(Npoly+1,:) = point
104
105
         end subroutine append_point_to_polygon
106
107
         subroutine append_point_to_poslist(point, poslist_in, Nposlist, poslist_out)
108
                 implicit none
109
                 integer, dimension(2), intent(in) :: point
110
                 integer, dimension(Nposlist, 2), intent(in) :: poslist_in
111
                 integer, intent(in) :: Nposlist
                 integer, dimension(Nposlist+1, 2), intent(out) :: poslist_out
112
113
                 integer :: i
114
115
                 do i=1, Nposlist
116
                          poslist_out(i,:) = poslist_in(i,:)
117
                 end do
118
                          poslist_out(Nposlist+1,:) = point
119
         end subroutine append_point_to_poslist
120
121
         subroutine append_point_to_list(point, list_in, Nlist, list_out)
122
                 implicit none
123
                 double precision, intent(in) :: point
                 double precision, dimension(Nlist), intent(in) :: list_in
124
125
                  integer, intent(in) :: Nlist
                 126
127
                 integer :: i
128
129
                 do i=1, N list
                        list_out(i) = list_in(i)
130
131
                  end do
132
                         list_out(Nlist+1) = point
133
         end subroutine append_point_to_list
134
135
         {\tt subroutine \ check\_if\_vector\_on\_vertical\_bin\_edge(point, vector, bin\_edge\_point, binheight, crosses, bin\_edge\_point, crosses, bin\_edge\_point, binheight, crosses, bin\_edge\_point, bin\_edge\_point, crosses, bin\_edge\_point, crosses, bin\_edge\_point, crosses, bin\_edge\_point, crosses, crosses,
                   crosspoint)
136
                  implicit none
                  double precision, dimension(2), intent(in) :: point, vector, bin_edge_point
137
                 double precision, intent(in) :: binheight
138
```

```
139
          logical, intent(out) :: crosses
140
          double precision, dimension(2), intent(out) :: crosspoint
141
142
          double precision :: m, cross_y , inner_length
143
          crosses = .FALSE.
144
          crosspoint = (/-1, -1/)
145
146
          if (vector(1) \neq 0) then
147
              m = (bin_edge_point(1) - point(1)) / vector(1)
          else
148
149
              \mathbf{m} = \mathbf{huge} (0.d0)
150
          end if
151
152
          if (0 \le m .AND. m \le 1) then
153
              cross_y = point(2) + m*vector(2)
154
              inner_length = (cross_y - bin_edge_point(2))/binheight
              if (0 \le \text{inner_length} .AND. \text{inner_length} \le 1) then
155
156
                   crosses = .TRUE.
157
                   crosspoint = (/bin_edge_point(1), cross_y/)
158
              end if
          end if
159
160
     end subroutine check_if_vector_on_vertical_bin_edge
161
162
     subroutine \ check_if_vector\_on\_horizontal\_bin\_edge(point\ ,\ vector\ ,\ bin\_edge\_point\ ,\ binwidth\ ,\ crosses
          , crosspoint)
163
          implicit none
164
          double precision, dimension(2), intent(in) :: point, vector, bin_edge_point
165
          double precision, intent(in) :: binwidth
166
          logical, intent(out) :: crosses
167
          double precision, dimension(2), intent(out) :: crosspoint
168
169
          double precision :: m, cross_x , inner_length
170
          crosses = .FALSE.
          crosspoint = (/-1, -1/)
171
172
173
          if (vector(2) \neq 0) then
174
              m = (bin_edge_point(2) - point(2)) / vector(2)
175
          else
176
             \mathbf{m} = \mathbf{huge}(0.d0)
177
          end if
178
179
          if (0 \le m .AND. m \le 1) then
              cross_x = point(1) + m*vector(1)
180
181
              inner_length = (cross_x - bin_edge_point(1))/binwidth
182
              if (0 \le \text{innerlength} AND. \text{innerlength} \le 1) then
183
                   crosses = .TRUE.
184
                   crosspoint = (/ \operatorname{cross}_x, \operatorname{bin}_edge_point(2)/)
185
              end if
186
          end if
187
     end \ subroutine \ check\_if\_vector\_on\_horizontal\_bin\_edge
188
189
     subroutine rebin(L, input_x, input_y, input_data, input_scale, input_bin_width_x,
          input_bin_width_y,&
190
                        output_x, output_y, Nx, Ny, Mx, My, output_data, output_scale)
191
          implicit none
192
193
          double precision, intent(in):: L
194
          double precision, intent(in), dimension(Nx) :: input_x
195
          double precision , intent(in) , dimension(Ny) :: input_y
196
          \texttt{double precision} \ , \ \texttt{intent(in)} \ , \ \texttt{dimension(Nx, Ny)} \ :: \ \texttt{input_data} \ , \ \texttt{input_scale}
197
          double precision, intent(in):: input_bin_width_x, input_bin_width_y
          double precision, intent(in), dimension(Mx) :: output_x
198
199
          double precision, intent(in), dimension(My) :: output_y
200
          integer, intent(in):: Nx, Ny, Mx, My
201
202
          double precision, intent(out), dimension(Mx, My) :: output_data, output_scale
203
204
          double precision , dimension (Mx, My) :: scale_factors
205
206
          integer:: ix, iy, jx, jy, ihelp, jhelp
          double precision :: \mathbf{x}, \mathbf{y}
207
```

```
208
         double precision :: dat_value, sca_value
209
210
         double precision, dimension(2) :: pA, pB, pC, pD
         double precision , dimension(2) :: rpA\,,\ rpB\,,\ rpC\,,\ rpD\,,\ bin\_edge\_point
211
212
         double precision, dimension(2) :: vAB, vBC, vCD, vDA
213
         double precision, dimension(2) :: hvector, h2vector, h2point, h2point, h3point
         double precision, dimension(4, 2):: transformed_polygon
214
         double precision, dimension(4, 2):: rectangle_polygon
215
216
         double precision, dimension(:, :), allocatable :: polygon_trail, hpolygon_trail
217
218
         ! for cleaning
219
         double precision, dimension(:, :), allocatable :: polygon_trail_cleaned
         integer :: Npoly_trail, Npoly_trail_cleaned
220
221
         logical :: point_is_double
222
223
         ! for sorting
         double precision, dimension(:, :), allocatable :: points_above
224
         double precision, dimension(:, :), allocatable :: points_below
225
226
         {\tt integer} \ :: \ {\tt num\_points\_above} \ , \ {\tt num\_points\_below}
227
         double precision, dimension(:, :), allocatable :: polygon_trail_sorted
         double precision , dimension(2) :: sort_min_point , sort_max_point
228
229
         double precision :: crossproduct
         integer :: sort_left_pos , sort_right_pos
230
231
232
         double precision, dimension(:), allocatable :: new_count_list, hnew_count_list
233
         integer, dimension(:, :), allocatable :: new_count_list_positions, hnew_count_list_positions
234
         integer :: number_of_new_counts
235
236
237
         double precision :: minx, miny, maxx, maxy
238
         double precision :: output_bin_width_x , output_bin_width_y , output_xmin , output_ymin
239
         {\tt double \ precision \ :: \ area\_polygon \ , \ area\_rectangle \ , \ overlap\_area}
240
         double precision :: rectbin_x, rectbin_y
         LOGICAL:: cf1, cf2, cf3, cf4, chelp
241
242
         double precision :: hbin_minx, hbin_maxx, hbin_miny, hbin_maxy
243
         integer :: bin_minx, bin_maxx, bin_miny, bin_maxy
244
245
         double precision :: current_polygon_area, triangle_area, normvalue, dot_result
246
         integer :: sign_of_area
247
248
         double precision :: initial_total_count, final_total_count
249
         !output arrays are supposed to be equidistant grids!
250
251
         !rectangular pattern is put around points
252
         output_bin_width_x = output_x(2) - output_x(1)
253
         output_xmin = output_x(1) - 0.5d0*output_bin_width_x
254
         output_bin_width_y = output_y(2) - output_y(1)
255
         output_ymin = output_y(1) - 0.5 d0 * output_bin_width_y
256
         area_rectangle = output_bin_width_x * output_bin_width_y
257
258
         initial_total_count = 0d0
259
           do \ ix = 1, \ Nx 
260
             do iy = 1, Ny
261
                  initial_total_count = initial_total_count + input_data(ix, iy)
262
             end do
263
         end do
264
         ! Initialize output arrays
265
         output_data = 0d0
266
         output_scale = 0d0
267
         scale_factors = 0d0
268
269
         do ix = 1, Nx
270
             x = input_x(ix)
271
             do iy = 1, Ny
272
                  y = input_y(iy)
273
                  dat_value = input_data(ix, iy)
274
                  sca_value = input_scale(ix, iy)
275
                  ! obtained x, y, and count + monitor value for an input point
276
277
                  ! span rectangle around given point
                  pA \;=\; (\,/\,x \;-\; 0.5\,d0*input\_bin\_width\_x \;,\; y \;-\; 0.5\,d0*input\_bin\_width\_y \,/\,)
278
```

```
279
                  pB = (/x + 0.5 d0 * input_bin_width_x, y - 0.5 d0 * input_bin_width_y/)
                  pC \;=\; (/\,x \;+\; 0.5\,d0*input\_bin\_width\_x \;,\; y \;+\; 0.5\,d0*input\_bin\_width\_y \;/)
280
                  pD = (/x - 0.5 d0*input_bin_width_x, y + 0.5 d0*input_bin_width_y/)
281
282
283
                  ! transform to quadrangle in new space
284
                  call coordinate_transform (pA, L)
                  call coordinate_transform (pB, L)
285
286
                  call coordinate_transform (pC, L)
287
                  call coordinate_transform (pD, L)
288
289
                  ! save corner points in polygon list
290
                  transformed_polygon(1, :) = pA
291
                  transformed_polygon(2, :) = pB
292
                  transformed_polygon(3, :) = pC
293
                  transformed_polygon(4, :) = pD
294
                  ! \ {\rm get} \ {\rm most} \ {\rm left} , right up and down points from the four corners
295
296
                  minx = min(pA(1), pB(1), pC(1), pD(1))
                  \max = \max(pA(1), pB(1), pC(1), pD(1))
297
298
                  miny = min(pA(2), pB(2), pC(2), pD(2))
299
                  maxy \; = \; max(pA(2) \; , \; pB(2) \; , \; pC(2) \; , \; pD(2))
300
301
                  !get idx position of corner points in new grid
302
                  hbin_minx = (minx - output_xmin)/output_bin_width_x
                  hbin_maxx = (maxx - output_xmin)/output_bin_width_x
303
304
                  hbin_miny = (miny - output_ymin)/output_bin_width_y
305
                  hbin_maxy = (maxy - output_ymin)/output_bin_width_y
306
                  ! Transformed Point outside of new grid? Then don't include it. Move on
307
308
                  if (hbin_minx < 0 .OR. hbin_maxx < 0 .OR. &
309
                      hbin_miny < 0 .OR. hbin_maxy < 0 .OR. &
310
                      hbin_minx >= Mx .OR. hbin_maxx >= Mx .OR. \&
                      hbin_miny >= My .OR. hbin_maxy >= My) cycle
311
312
313
                  ! to integer, remember that array counting starts with 1
314
                  bin_minx = int(hbin_minx)+1
315
                  bin_maxx = int(hbin_maxx)+1
316
                  bin_miny = int(hbin_miny)+1
317
                  bin_maxy = int(hbin_maxy)+1
318
319
                  ! Is the transformed Point completly in new bin? Add and move on
320
                  if (bin_minx == bin_maxx .AND. bin_miny == bin_maxy) then
321
                      output_data(bin_minx, bin_miny) =&
322
                          output_data(bin_minx, bin_miny) + dat_value
323
                      output_scale(bin_minx, bin_miny) =&
324
                           output_scale(bin_minx, bin_miny) + sca_value
325
                       scale_factors(bin_minx, bin_miny) =&
326
                           scale_factors(bin_minx, bin_miny) + 1.d0
327
                      cvcle
328
                  end if
329
330
                  ! Point inside new grid and streches over multiply bins...
331
                  ! so we will have to split it across the new bins
332
                  area_polygon = 0d0
333
                  if(allocated(new_count_list)) then
334
335
                      deallocate (new_count_list)
                  end if
336
                  allocate(new_count_list(0))
337
338
339
                  if (allocated (new_count_list_positions)) then
340
                      deallocate(new_count_list_positions)
341
                  end if
342
                  allocate (new_count_list_positions (0,2))
343
                  number_of_new_counts = 0
344
345
                  vAB = pB - pA
346
                  vBC = pC - pB
                  vCD = pD - pC
347
                  vDA = pA - pD
348
349
```

```
350
                  ! Loop over all considerable grid points in new grid
351
                 do jx=bin_minx, bin_maxx
352
                      if (jx > Mx .OR. jx < 1) cycle
                      rectbin_x = output_x(jx) - 0.5d0*output_bin_width_x
353
354
                      do jy=bin_miny, bin_maxy
                          if (jy > My .OR. jy < 1) cycle
355
                          rectbin_y = output_y(jy) - 0.5 d0 * output_bin_width_y
356
357
                          ! Current rectangle, find overlap area
358
359
                          rpA = (/rectbin_x, rectbin_y/)
360
                          rpB = (/rectbin_x + output_bin_width_x, rectbin_y/)
361
                          rpC = (/rectbin_x + output_bin_width_x, rectbin_y +&
362
                              output_bin_width_y/)
363
                          rpD = (/rectbin_x, rectbin_y + output_bin_width_y/)
364
365
                          rectangle_polygon(1, :) = rpA
366
                          rectangle_polygon(2, :) = rpB
                          rectangle_polygon(3, :) = rpC
367
                          rectangle_polygon(4, :) = rpD
368
369
370
                          ! check whether one of the four points is inside the new
371
                          if(allocated(polygon_trail)) then
372
                              deallocate(polygon_trail)
373
                          end if
374
                          allocate (polygon_trail(0,2))
375
                          N poly_trail = 0
376
377
                          call point_inside_polygon(rpA, transformed_polygon, cf1, 4)
378
                          if (cf1) then
379
                              allocate (hpolygon_trail (Npoly_trail+1,2))
380
                              call append_point_to_polygon(rpA, polygon_trail,&
381
                                   Npoly_trail, hpolygon_trail)
382
                               call move_alloc(hpolygon_trail, polygon_trail)
383
                              N poly_trail = N poly_trail + 1
384
                          end if
385
386
                          call point_inside_polygon(rpB, transformed_polygon, cf2, 4)
387
                          if (cf2) then
388
                              allocate(hpolygon_trail(Npoly_trail+1,2))
389
                              call append_point_to_polygon(rpB, polygon_trail,&
390
                                  Npoly_trail, hpolygon_trail)
                               call move_alloc(hpolygon_trail, polygon_trail)
391
392
                              Npoly\_trail = Npoly\_trail + 1
393
                          end if
394
395
                          call point_inside_polygon(rpC, transformed_polygon, cf3, 4)
396
                          if (cf3) then
397
                              allocate (hpolygon_trail (Npoly_trail+1,2))
398
                              call append_point_to_polygon(rpC, polygon_trail,&
399
                                   Npoly_trail, hpolygon_trail)
                              call move_alloc(hpolygon_trail, polygon_trail)
400
401
                              N poly_trail = N poly_trail + 1
402
                          end if
403
404
                          call point_inside_polygon(rpD, transformed_polygon, cf4, 4)
405
                          if (cf4) then
406
                              allocate (hpolygon_trail (Npoly_trail+1,2))
                              \verb| call append_point_to_polygon(rpD, polygon_trail, \&
407
408
                                   Npoly_trail, hpolygon_trail)
409
                              call move_alloc(hpolygon_trail, polygon_trail)
410
                              N poly_trail = N poly_trail + 1
411
                          end if
412
413
                          ! All four points inside the new polygon? easy case
414
                          ! Fraction of area count fills grid point completly
415
                          if (cf1 .AND. cf2 .AND. cf3 .AND. cf4) then
416
                              area_polygon = area_polygon + area_rectangle
417
                              allocate (hnew_count_list (number_of_new_counts+1))
418
                              allocate(hnew_count_list_positions(number_of_new_counts+1,2))
419
420
                              call append_point_to_list (area_rectangle,&
```

421	new_count_list , number_of_new_counts , hnew_count_list)
422	call append_point_to_poslist((/jx, jy/),&
423	${\tt new_count_list_positions}$, ${\tt number_of_new_counts}$,&
424	hnew_count_list_positions)
425	call move_alloc(hnew_count_list, new_count_list)
426	call move_alloc(hnew_count_list_positions, new_count_list_positions)
427	number_of_new_counts = number_of_new_counts + 1
420	and if
430	
431	! Not the case
432	! check whether edge points of polygon are inside the investigated rectangle
433	call point_inside_polygon(pA, rectangle_polygon, chelp, 4)
434	if (chelp) then
435	allocate(hpolygon_trail(Npoly_trail+1,2))
436	call append_point_to_polygon(pA, polygon_trail,&
437	Npoly_trail, hpolygon_trail)
438	$call move_alloc(npolygon_trail, polygon_trail)$
440	end if
441	
442	call point_inside_polygon(pB, rectangle_polygon, chelp, 4)
443	if (chelp) then
444	allocate(hpolygon_trail(Npoly_trail+1,2))
445	call append_point_to_polygon(pB, polygon_trail,&
446	Npoly_trail, hpolygon_trail)
447	call move_alloc(hpolygon_trail, polygon_trail)
448	Npoly_trail = Npoly_trail + 1
449	
451	call point_inside_polygon(pC, rectangle_polygon, chelp, 4)
452	if (chelp) then
453	allocate(hpolygon_trail(Npoly_trail+1,2))
454	call append_point_to_polygon(pC, polygon_trail,&
455	Npoly_trail, hpolygon_trail)
456	call move_alloc(hpolygon_trail, polygon_trail)
457	Npoly_trail = Npoly_trail + 1
458	end 11
459	call point inside polygon (pD) rectangle polygon chelp 4)
461	if (chelp) then
462	allocate(hpolygon_trail(Npoly_trail+1,2))
463	call append_point_to_polygon(pD, polygon_trail,&
464	Npoly_trail, hpolygon_trail)
465	call move_alloc(hpolygon_trail, polygon_trail)
466	Npoly_trail = Npoly_trail + 1
467	end if
408	L check whether edge lines of polygon gross rectangle edges
409	hin edge point = (/recthin x recthin y/)
471	
472	! pA, vAB
473	call check_if_vector_on_horizontal_bin_edge(pA, vAB, bin_edge_point,&
474	output_bin_width_x , chelp , hpoint)
475	if (chelp) then
476	allocate(hpolygon_trail(Npoly_trail+1,2))
477	call append_point_to_polygon(hpoint, polygon_trail,&
478	call move allog (boolygon trail polygon trail)
480	$N_{poly_trail} = N_{poly_trail} + 1$
481	end if
482	
483	$\verb call check_if_vector_on_horizontal_bin_edge(pA, vAB, bin_edge_point + (/0d0, vAB)) = 0.000 \text{ for all check_if_vector_on_horizontal_bin_edge(pA)} = 0.0000 \text{ for all check_if_vector_on_horizontal_bin_edge(pA)} = 0.00000 \text{ for all check_if_vector_on_horizontal_bin_edge(pA)} = 0.0000000000000000000000000000000000$
	output_bin_width_y/),&
484	<pre>output_bin_width_x , chelp , hpoint)</pre>
485	if (chelp) then
480 487	allocate (npolygon_trail(Npoly_trail+1,2))
488	Npoly_trail, hpolygon (npoint, polygon_trail, &
489	call move_alloc(hpolygon_trail, polygon_trail)
490	Npoly_trail = Npoly_trail + 1

492	end if
104	
493	call check_if_vector_on_vertical_bin_edge(pA, vAB, bin_edge_point, &
494	output_bin_width_v, chelp, hpoint)
495	if (chelp) then
496	allocate(hpolygon trail(Npoly trail+1.2))
497	call append point to polygon (hpoint polygon trail &
198	Nucle trail = hughgen trail)
498	soll more elles (hereiner strill - polygon treil)
4 <i>99</i>	Naclu troil = Naclu troil + 1
500	Npoly_trail = Npoly_trail + 1
501	end II
502	
503	call check_ll_vector_on_vertical_bin_edge(pA, VAB, bin_edge_point+(/
504	output_bin_width_x, Ud/),&
504	output_bin_width_y, cheip, npoint)
505	if (chelp) then
506	allocate (hpolygon_trail(Npoly_trail+1,2))
507	call append_point_to_polygon(hpoint, polygon_trail,&
508	Npoly_trail, hpolygon_trail)
509	call move_alloc(hpolygon_trail, polygon_trail)
510	Npoly_trail = Npoly_trail + 1
511	end if
512	
513	$!\mathrm{pB}, \ \mathrm{vBC}$
514	call check_if_vector_on_horizontal_bin_edge(pB, vBC, bin_edge_point,&
515	<pre>output_bin_width_x , chelp , hpoint)</pre>
516	if (chelp) then
517	allocate(hpolygon_trail(Npoly_trail+1,2))
518	call append_point_to_polygon(hpoint, polygon_trail,&
519	Npoly_trail, hpolygon_trail)
520	call move_alloc(hpolygon_trail, polygon_trail)
521	$Npoly_trail = Npoly_trail + 1$
522	end if
523	
524	call check_if_vector_on_horizontal_bin_edge(pB, vBC, bin_edge_point+(/0d0,
	output_bin_width_y/),&
525	output_bin_width_x, chelp, hpoint)
526	if (chelp) then
526 527	if (chelp) then allocate(hpolygon_trail(Npoly_trail+1.2))
526 527 528	<pre>if (chelp) then allocate(hpolygon_trail(Npoly_trail+1,2)) call append_point_to_polygon(hpoint, polygon_trail.&</pre>
526 527 528 529	<pre>if (chelp) then allocate(hpolygon_trail(Npoly_trail+1,2)) call append_point_to_polygon(hpoint, polygon_trail,&</pre>
526 527 528 529 530	<pre>if (chelp) then allocate(hpolygon_trail(Npoly_trail+1,2)) call append_point_to_polygon(hpoint, polygon_trail,& Npoly_trail, hpolygon_trail) call move alloc(hpolygon trail, polygon trail)</pre>
526 527 528 529 530 531	<pre>if (chelp) then allocate(hpolygon_trail(Npoly_trail+1,2)) call append_point_to_polygon(hpoint, polygon_trail,& Npoly_trail, hpolygon_trail) call move_alloc(hpolygon_trail, polygon_trail) Npoly_trail = Npoly_trail + 1</pre>
526 527 528 529 530 531 532	<pre>if (chelp) then allocate(hpolygon_trail(Npoly_trail+1,2)) call append_point_to_polygon(hpoint, polygon_trail,& Npoly_trail, hpolygon_trail) call move_alloc(hpolygon_trail, polygon_trail) Npoly_trail = Npoly_trail + 1 end if</pre>
526 527 528 529 530 531 532 533	<pre>if (chelp) then allocate(hpolygon_trail(Npoly_trail+1,2)) call append_point_to_polygon(hpoint, polygon_trail,& Npoly_trail, hpolygon_trail) call move_alloc(hpolygon_trail, polygon_trail) Npoly_trail = Npoly_trail + 1 end if</pre>
526 527 528 529 530 531 532 533 534	<pre>if (chelp) then allocate(hpolygon_trail(Npoly_trail+1,2)) call append_point_to_polygon(hpoint, polygon_trail,& Npoly_trail, hpolygon_trail) call move_alloc(hpolygon_trail, polygon_trail) Npoly_trail = Npoly_trail + 1 end if call_check if vector on vertical bin edge(pB_vBC_bin edge point_%)</pre>
526 527 528 529 530 531 532 533 534 535	<pre>if (chelp) then allocate(hpolygon_trail(Npoly_trail+1,2)) call append_point_to_polygon(hpoint, polygon_trail,& Npoly_trail, hpolygon_trail) call move_alloc(hpolygon_trail, polygon_trail) Npoly_trail = Npoly_trail + 1 end if call check_if_vector_on_vertical_bin_edge(pB, vBC, bin_edge_point, & output bin width v, chelp_hpoint)</pre>
526 527 528 529 530 531 532 533 534 535 535	<pre>if (chelp) then allocate(hpolygon_trail(Npoly_trail+1,2)) call append_point_to_polygon(hpoint, polygon_trail,& Npoly_trail, hpolygon_trail) call move_alloc(hpolygon_trail, polygon_trail) Npoly_trail = Npoly_trail + 1 end if call check_if_vector_on_vertical_bin_edge(pB, vBC, bin_edge_point, & output_bin_width_y, chelp, hpoint) if (chelp) then</pre>
526 527 528 529 530 531 532 533 534 535 536 537	<pre>if (chelp) then allocate(hpolygon_trail(Npoly_trail+1,2)) call append_point_to_polygon(hpoint, polygon_trail,& Npoly_trail, hpolygon_trail) call move_alloc(hpolygon_trail, polygon_trail) Npoly_trail = Npoly_trail + 1 end if call check_if_vector_on_vertical_bin_edge(pB, vBC, bin_edge_point, & output_bin_width_y, chelp, hpoint) if (chelp) then allocate(hpolygon_trail(Npoly_trail+1,2))</pre>
526 527 528 529 530 531 532 533 534 535 536 537 538	<pre>if (chelp) then allocate(hpolygon_trail(Npoly_trail+1,2)) call append_point_to_polygon(hpoint, polygon_trail,& Npoly_trail, hpolygon_trail) call move_alloc(hpolygon_trail, polygon_trail) Npoly_trail = Npoly_trail + 1 end if call check_if_vector_on_vertical_bin_edge(pB, vBC, bin_edge_point, & output_bin_width_y, chelp, hpoint) if (chelp) then allocate(hpolygon_trail(Npoly_trail+1,2)) call append_point to polygon(hpointpolygon_trail fr </pre>
526 527 528 529 530 531 532 533 534 535 536 537 538 539	<pre>if (chelp) then allocate(hpolygon_trail(Npoly_trail+1,2)) call append_point_to_polygon(hpoint, polygon_trail,& Npoly_trail, hpolygon_trail) call move_alloc(hpolygon_trail, polygon_trail) Npoly_trail = Npoly_trail + 1 end if call check_if_vector_on_vertical_bin_edge(pB, vBC, bin_edge_point, & output_bin_width_y, chelp, hpoint) if (chelp) then allocate(hpolygon_trail(Npoly_trail+1,2)) call append_point_to_polygon(hpoint, polygon_trail,& Npoly_trail = hpolygon_trail)</pre>
526 527 528 529 530 531 532 533 534 535 536 537 538 539 540	<pre>if (chelp) then allocate(hpolygon_trail(Npoly_trail+1,2)) call append_point_to_polygon(hpoint, polygon_trail,& Npoly_trail, hpolygon_trail) call move_alloc(hpolygon_trail, polygon_trail) Npoly_trail = Npoly_trail + 1 end if call check_if_vector_on_vertical_bin_edge(pB, vBC, bin_edge_point, & output_bin_width_y, chelp, hpoint) if (chelp) then allocate(hpolygon_trail(Npoly_trail+1,2)) call append_point_to_polygon(hpoint, polygon_trail,& Npoly_trail, hpolygon_trail) call move_alloc(hpolygon_trail) call move_alloc(hpolygon_trail)</pre>
526 527 528 529 530 531 532 533 534 535 536 537 538 539 540 541	<pre>if (chelp) then allocate(hpolygon_trail(Npoly_trail+1,2)) call append_point_to_polygon(hpoint, polygon_trail,& Npoly_trail, hpolygon_trail) call move_alloc(hpolygon_trail, polygon_trail) Npoly_trail = Npoly_trail + 1 end if call check_if_vector_on_vertical_bin_edge(pB, vBC, bin_edge_point, & output_bin_width_y, chelp, hpoint) if (chelp) then allocate(hpolygon_trail(Npoly_trail+1,2)) call append_point_to_polygon(hpoint, polygon_trail,& Npoly_trail, hpolygon_trail) call append_point_to_polygon(hpoint, polygon_trail,& Npoly_trail, hpolygon_trail) call move_alloc(hpolygon_trail, polygon_trail) Npoly_trail = Npoly_trail + 1</pre>
526 527 528 529 530 531 532 533 534 535 536 537 538 539 540 541 542	<pre>if (chelp) then allocate(hpolygon_trail(Npoly_trail+1,2)) call append_point_to_polygon(hpoint, polygon_trail,& Npoly_trail, hpolygon_trail) call move_alloc(hpolygon_trail, polygon_trail) Npoly_trail = Npoly_trail + 1 end if call check_if_vector_on_vertical_bin_edge(pB, vBC, bin_edge_point, & output_bin_width_y, chelp, hpoint) if (chelp) then allocate(hpolygon_trail(Npoly_trail+1,2)) call append_point_to_polygon(hpoint, polygon_trail,& Npoly_trail, hpolygon_trail) call move_alloc(hpolygon_trail, polygon_trail) Npoly_trail = Npoly_trail + 1 end if</pre>
526 527 528 529 530 531 532 533 534 535 536 537 538 539 540 541 542 543	<pre>if (chelp) then allocate(hpolygon_trail(Npoly_trail+1,2)) call append_point_to_polygon(hpoint, polygon_trail,& Npoly_trail, hpolygon_trail) call move_alloc(hpolygon_trail, polygon_trail) Npoly_trail = Npoly_trail + 1 end if call check_if_vector_on_vertical_bin_edge(pB, vBC, bin_edge_point, & output_bin_width_y, chelp, hpoint) if (chelp) then allocate(hpolygon_trail(Npoly_trail+1,2)) call append_point_to_polygon(hpoint, polygon_trail,& Npoly_trail, hpolygon_trail) call move_alloc(hpolygon_trail, polygon_trail) Npoly_trail = Npoly_trail + 1 end if</pre>
526 527 528 529 530 531 532 533 534 535 536 537 538 539 540 541 542 543	<pre>if (chelp) then allocate(hpolygon_trail(Npoly_trail+1,2)) call append_point_to_polygon(hpoint, polygon_trail,& Npoly_trail, hpolygon_trail) call move_alloc(hpolygon_trail, polygon_trail) Npoly_trail = Npoly_trail + 1 end if call check_if_vector_on_vertical_bin_edge(pB, vBC, bin_edge_point, & output_bin_width_y, chelp, hpoint) if (chelp) then allocate(hpolygon_trail(Npoly_trail+1,2)) call append_point_to_polygon(hpoint, polygon_trail,& Npoly_trail, hpolygon_trail) call move_alloc(hpolygon_trail, polygon_trail, moly_on_trail, npoly_trail + 1 end if call move_alloc(hpolygon_trail, polygon_trail) call append_point_to_polygon(hpoint, polygon_trail, moly_on_trail, npoly_trail + 1 end if </pre>
526 527 528 529 530 531 532 533 534 535 536 537 538 539 540 541 542 543 544	<pre>if (chelp) then allocate(hpolygon_trail(Npoly_trail+1,2)) call append_point_to_polygon(hpoint, polygon_trail,& Npoly_trail, hpolygon_trail) call move_alloc(hpolygon_trail, polygon_trail) Npoly_trail = Npoly_trail + 1 end if call check_if_vector_on_vertical_bin_edge(pB, vBC, bin_edge_point, & output_bin_width_y, chelp, hpoint) if (chelp) then allocate(hpolygon_trail(Npoly_trail+1,2)) call append_point_to_polygon(hpoint, polygon_trail,& Npoly_trail, hpolygon_trail) call move_alloc(hpolygon_trail, polygon_trail) Npoly_trail = Npoly_trail + 1 end if call check_if_vector_on_vertical_bin_edge(pB, vBC, bin_edge_point+(/</pre>
526 527 528 529 530 531 532 533 534 535 536 537 538 539 540 541 542 543 544	<pre>if (chelp) then allocate(hpolygon_trail(Npoly_trail+1,2)) call append_point_to_polygon(hpoint, polygon_trail,& Npoly_trail, hpolygon_trail) call move_alloc(hpolygon_trail, polygon_trail) Npoly_trail = Npoly_trail + 1 end if call check_if_vector_on_vertical_bin_edge(pB, vBC, bin_edge_point, & output_bin_width_y, chelp, hpoint) if (chelp) then allocate(hpolygon_trail(Npoly_trail+1,2)) call append_point_to_polygon(hpoint, polygon_trail,& Npoly_trail, hpolygon_trail) call move_alloc(hpolygon_trail, polygon_trail) Npoly_trail = Npoly_trail + 1 end if call check_if_vector_on_vertical_bin_edge(pB, vBC, bin_edge_point+(/ output_bin_width_x, 0d0/),&</pre>
526 527 528 529 530 531 532 533 534 535 536 537 538 539 540 541 542 543 544	<pre>if (chelp) then allocate(hpolygon_trail(Npoly_trail+1,2)) call append_point_to_polygon(hpoint, polygon_trail,& Npoly_trail, hpolygon_trail) call move_alloc(hpolygon_trail, polygon_trail) Npoly_trail = Npoly_trail + 1 end if call check_if_vector_on_vertical_bin_edge(pB, vBC, bin_edge_point, & output_bin_width_y, chelp, hpoint) if (chelp) then allocate(hpolygon_trail(Npoly_trail+1,2)) call append_point_to_polygon(hpoint, polygon_trail,& Npoly_trail, hpolygon_trail) call append_point_to_polygon(hpoint, polygon_trail,& Npoly_trail, hpolygon_trail, polygon_trail) call move_alloc(hpolygon_trail, polygon_trail) call move_alloc(hpolygon_trail, polygon_trail) Npoly_trail = Npoly_trail + 1 end if call check_if_vector_on_vertical_bin_edge(pB, vBC, bin_edge_point+(/ output_bin_width_x, 0d0/),& output_bin_width_y, chelp, hpoint) </pre>
526 527 528 529 530 531 532 533 534 535 536 537 538 539 540 541 542 543 544 545	<pre>if (chelp) then allocate(hpolygon_trail(Npoly_trail+1,2)) call append_point_to_polygon(hpoint, polygon_trail,& Npoly_trail, hpolygon_trail) call move_alloc(hpolygon_trail, polygon_trail) Npoly_trail = Npoly_trail + 1 end if call check_if_vector_on_vertical_bin_edge(pB, vBC, bin_edge_point, & output_bin_width_y, chelp, hpoint) if (chelp) then allocate(hpolygon_trail(Npoly_trail+1,2)) call append_point_to_polygon(hpoint, polygon_trail,& Npoly_trail, hpolygon_trail) call append_point_to_polygon(hpoint, polygon_trail,& Npoly_trail, hpolygon_trail) call move_alloc(hpolygon_trail, polygon_trail) call move_alloc(hpolygon_trail, polygon_trail) Npoly_trail = Npoly_trail + 1 end if call check_if_vector_on_vertical_bin_edge(pB, vBC, bin_edge_point+(/ output_bin_width_x, odd)/),& output_bin_width_y, chelp, hpoint) if (chelp) then</pre>
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526 527 528 529 530 531 532 533 534 535 536 537 538 539 540 541 542 541 542 543 544 544 545 546 547 548	<pre>if (chelp) then allocate(hpolygon_trail(Npoly_trail+1,2)) call append_point_to_polygon(hpoint, polygon_trail,& Npoly_trail, hpolygon_trail) call move_alloc(hpolygon_trail, polygon_trail) Npoly_trail = Npoly_trail + 1 end if call check_if_vector_on_vertical_bin_edge(pB, vBC, bin_edge_point, & output_bin_width_y, chelp, hpoint) if (chelp) then allocate(hpolygon_trail(Npoly_trail+1,2)) call append_point_to_polygon(hpoint, polygon_trail,& Npoly_trail, hpolygon_trail) call move_alloc(hpolygon_trail, polygon_trail) Npoly_trail = Npoly_trail + 1 end if call check_if_vector_on_vertical_bin_edge(pB, vBC, bin_edge_point+(/ output_bin_width_x, 0d0/),& output_bin_width_y, chelp, hpoint) if (chelp) then allocate(hpolygon_trail(Npoly_trail+1,2)) call append_point_to_polygon(hpoint, polygon_trail,&</pre>
526 527 528 529 530 531 532 533 534 535 536 537 538 539 540 541 542 541 542 543 544 544 545 546 547 548 549	<pre>if (chelp) then allocate(hpolygon_trail(Npoly_trail+1,2)) call append_point_to_polygon(hpoint, polygon_trail,& Npoly_trail, hpolygon_trail) call move_alloc(hpolygon_trail, polygon_trail) Npoly_trail = Npoly_trail + 1 end if call check_if_vector_on_vertical_bin_edge(pB, vBC, bin_edge_point, & output_bin_width_y, chelp, hpoint) if (chelp) then allocate(hpolygon_trail(Npoly_trail+1,2)) call append_point_to_polygon(hpoint, polygon_trail,& Npoly_trail, hpolygon_trail) call move_alloc(hpolygon_trail, polygon_trail) Npoly_trail = Npoly_trail + 1 end if call check_if_vector_on_vertical_bin_edge(pB, vBC, bin_edge_point+(/ output_bin_width_y, chelp, hpoint) if (chelp) then allocate(hpolygon_trail(Npoly_trail+1,2)) call check_if_vector_on_vertical_bin_edge(pB, vBC, bin_edge_point+(/ output_bin_width_y, chelp, hpoint) if (chelp) then allocate(hpolygon_trail(Npoly_trail+1,2)) call append_point_to_polygon(hpoint, polygon_trail,&</pre>
526 527 528 529 530 531 532 533 534 535 536 537 538 539 540 541 542 542 543 544 545 544 545 546 547 548 549 550	<pre>if (chelp) then allocate(hpolygon_trail(Npoly_trail+1,2)) call append_point_to_polygon(hpoint, polygon_trail,& Npoly_trail, hpolygon_trail) call move_alloc(hpolygon_trail, polygon_trail) Npoly_trail = Npoly_trail + 1 end if call check_if_vector_on_vertical_bin_edge(pB, vBC, bin_edge_point, & output_bin_width_y, chelp, hpoint) if (chelp) then allocate(hpolygon_trail(Npoly_trail+1,2)) call append_point_to_polygon(hpoint, polygon_trail,& Npoly_trail, hpolygon_trail) call move_alloc(hpolygon_trail, polygon_trail) Npoly_trail = Npoly_trail + 1 end if call check_if_vector_on_vertical_bin_edge(pB, vBC, bin_edge_point+(/ output_bin_width_y, chelp, hpoint) if (chelp) then allocate(hpolygon_trail, polygon_trail) Npoly_trail = Npoly_trail + 1 end if call check_if_vector_on_vertical_bin_edge(pB, vBC, bin_edge_point+(/ output_bin_width_x, odd/),& output_bin_width_y, chelp, hpoint) if (chelp) then allocate(hpolygon_trail(Npoly_trail+1,2)) call append_point_to_polygon(hpoint, polygon_trail,& Npoly_trail, hpolygon_trail, hpoint) if (chelp) then allocate(hpolygon_trail(Npoly_trail+1,2)) call append_point_to_polygon(hpoint, polygon_trail,& Npoly_trail, hpolygon_trail) call append_point_to_polygon(hpoint, polygon_trail,& Npoly_trail, hpolygon_trail, polygon_trail,& Npoly_trail, hpolygon_trail) call append_point_to_polygon(hpoint, polygon_trail,& Npoly_trail, hpolygon_trail, polygon_trail) call move_alloc(hpolygon_trail, polygon_trail) call move_alloc(hpol</pre>
526 527 528 529 530 531 532 533 534 535 536 537 538 539 540 541 542 543 544 543 544 545 544 545 544 545 546 547 548 549 550 551	<pre>if (chelp) then allocate(hpolygon_trail(Npoly_trail+1,2)) call append_point_to_polygon(hpoint, polygon_trail,& Npoly_trail, hpolygon_trail) call move_alloc(hpolygon_trail, polygon_trail) Npoly_trail = Npoly_trail + 1 end if call check_if_vector_on_vertical_bin_edge(pB, vBC, bin_edge_point, & output_bin_width_y, chelp, hpoint) if (chelp) then allocate(hpolygon_trail(Npoly_trail+1,2)) call append_point_to_polygon(hpoint, polygon_trail,& Npoly_trail, hpolygon_trail) call move_alloc(hpolygon_trail, polygon_trail) Npoly_trail = Npoly_trail + 1 end if call check_if_vector_on_vertical_bin_edge(pB, vBC, bin_edge_point+(/ output_bin_width_y, chelp, hpoint) if (chelp) then allocate(hpolygon_trail(Npoly_trail+1,2)) call check_if_vector_on_vertical_bin_edge(pB, vBC, bin_edge_point+(/ output_bin_width_y, chelp, hpoint) if (chelp) then allocate(hpolygon_trail(Npoly_trail+1,2)) call append_point_to_polygon(hpoint, polygon_trail,& Npoly_trail, hpolygon_trail) call move_alloc(hpolygon_trail) call move_alloc(hpolygon_trail) call move_alloc(hpolygon_trail) Npoly_trail = Npoly_trail + 1 }</pre>
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526 527 528 529 530 531 532 533 534 535 536 537 538 539 540 541 542 543 544 545 544 545 546 547 548 549 550 551 552 553	<pre>if (chelp) then allocate(hpolygon_trail(Npoly_trail+1,2)) call append_point_to_polygon(hpoint, polygon_trail,& Npoly_trail, hpolygon_trail, polygon_trail) call move_alloc(hpolygon_trail, polygon_trail) Npoly_trail = Npoly_trail + 1 end if call check_if_vector_on_vertical_bin_edge(pB, vBC, bin_edge_point, & output_bin_width_y, chelp, hpoint) if (chelp) then allocate(hpolygon_trail(Npoly_trail+1,2)) call append_point_to_polygon(hpoint, polygon_trail,& Npoly_trail, hpolygon_trail) call move_alloc(hpolygon_trail, polygon_trail) Npoly_trail = Npoly_trail + 1 end if call check_if_vector_on_vertical_bin_edge(pB, vBC, bin_edge_point+(/ output_bin_width_y, chelp, hpoint) if (chelp) then allocate(hpolygon_trail(Npoly_trail+1) end if call check_if_vector_on_vertical_bin_edge(pB, vBC, bin_edge_point+(/ output_bin_width_y, chelp, hpoint) if (chelp) then allocate(hpolygon_trail(Npoly_trail+1,2)) call append_point_to_polygon(hpoint, polygon_trail,& Npoly_trail, hpolygon_trail) call append_point_to_polygon(hpoint, polygon_trail,& Npoly_trail = Npoly_trail+1 end if call check_if_vector_on_vertical_bin_edge(pB, vBC, bin_edge_point+(/ output_bin_width_y, chelp, hpoint) if (chelp) then allocate(hpolygon_trail(Npoly_trail+1,2)) call append_point_to_polygon(hpoint, polygon_trail,& Npoly_trail, hpolygon_trail) call append_point_to_polygon(hpoint, polygon_trail,& Npoly_trail, hpolygon_trail) call append_point_to_polygon_trail) rolygon_trail = Npoly_trail + 1 end if </pre>
526 527 528 529 530 531 532 533 534 535 536 537 538 539 540 541 542 543 544 545 546 547 548 549 550 551 552 553 554	<pre>if (chelp) then allocate(hpolygon_trail(Npoly_trail+1,2)) call append_point_to_polygon(hpoint, polygon_trail,& Npoly_trail, hpolygon_trail, polygon_trail) call move_alloc(hpolygon_trail, polygon_trail) Npoly_trail = Npoly_trail + 1 end if call check_if_vector_on_vertical_bin_edge(pB, vBC, bin_edge_point, & output_bin_width_y, chelp, hpoint) if (chelp) then allocate(hpolygon_trail(Npoly_trail+1,2)) call append_point_to_polygon(hpoint, polygon_trail,& Npoly_trail, hpolygon_trail, polygon_trail, % Npoly_trail = Npoly_trail+1 end if call check_if_vector_on_vertical_bin_edge(pB, vBC, bin_edge_point, & Npoly_trail = Npoly_trail+1 end if call check_if_vector_on_vertical_bin_edge(pB, vBC, bin_edge_point+(/ output_bin_width_y, chelp, hpoint) if (chelp) then allocate(hpolygon_trail, polygon_trail) Npoly_trail = Npoly_trail+1 end if call check_if_vector_on_vertical_bin_edge(pB, vBC, bin_edge_point+(/ output_bin_width_y, chelp, hpoint) if (chelp) then allocate(hpolygon_trail, polygon_trail, polygon_trail, % Npoly_trail, hpolygon_trail, polygon_trail, polygon_trail, % Npoly_trail, hpolygon_trail, polygon_trail, polygon_trail, % Npoly_trail, hpolygon_trail) call append_point_to_polygon(hpoint, polygon_trail, % Npoly_trail, hpolygon_trail, polygon_trail, polygon_trail, % Npoly_trail = Npoly_trail + 1 end if if lpC, vCD </pre>
526 527 528 529 530 531 532 533 534 535 536 537 538 539 540 541 542 543 544 545 544 545 546 547 548 549 550 551 552 553 554 555	<pre>if (chelp) then allocate(hpolygon_trail(Npoly_trail+1,2)) call append_point.to_polygon(hpoint, polygon_trail,& Npoly_trail, hpolygon_trail) call move_alloc(hpolygon_trail, polygon_trail) Npoly_trail = Npoly_trail + 1 end if call check_if_vector_on_vertical_bin_edge(pB, vBC, bin_edge_point, & output_bin_width_y, chelp, hpoint) if (chelp) then allocate(hpolygon_trail(Npoly_trail+1,2)) call append_point_to_polygon(hpoint, polygon_trail,& Npoly_trail, hpolygon_trail) call move_alloc(hpolygon_trail, polygon_trail) Npoly_trail = Npoly_trail + 1 end if call check_if_vector_on_vertical_bin_edge(pB, vBC, bin_edge_point+(/ output_bin_width_y, chelp, hpoint) if (chelp) then allocate(hpolygon_trail(Npoly_trail+1,2)) call append_point_to_polygon(hpoint, polygon_trail,& Npoly_trail, hpolygon_trail) volupt_bin_width_y, chelp, hpoint) if (chelp) then allocate(hpolygon_trail(Npoly_trail+1,2)) call append_point_to_polygon(hpoint, polygon_trail,& Npoly_trail, hpolygon_trail) call move_alloc(hpolygon_trail, polygon_trail) Npoly_trail = Npoly_trail + 1 end if !pC, vCD call check_if_vector_on_horizontal_bin_edge(pC, vCD, bin_edge_point,& call check_if_vector_on_horizontal_bin_edge(pC, vCD, bin_edge_point,& call check_if_vector_on_horizontal_bin_edge(pC, vCD, bin_edge_point,& red if the to the tot to the to the to the to the to the to the tot</pre>
526 527 528 529 530 531 532 533 534 535 536 537 538 539 540 541 542 543 544 545 546 547 548 549 550 551 552 553 554 555 556	<pre>if (chelp) then allocate(hpolygon_trail(Npoly_trail+1,2)) call append_point_to_polygon(hpoint, polygon_trail,& Npoly_trail, hpolygon_trail) call move_alloc(hpolygon_trail, polygon_trail) Npoly_trail = Npoly_trail + 1 end if call check_if_vector_on_vertical_bin_edge(pB, vBC, bin_edge_point, & output_bin_width_y, chelp, hpoint) if (chelp) then allocate(hpolygon_trail(Npoly_trail+1,2)) call append_point_to_polygon(hpoint, polygon_trail,& Npoly_trail, hpolygon_trail) call move_alloc(hpolygon_trail, polygon_trail) Npoly_trail = Npoly_trail + 1 end if call check_if_vector_on_vertical_bin_edge(pB, vBC, bin_edge_point+(/ output_bin_width_y, chelp, hpoint) if (chelp) then allocate(hpolygon_trail(Npoly_trail+1,2)) call append_point_to_polygon(hpoint, polygon_trail,& Npoly_trail, hpolygon_trail) if (chelp) then allocate(hpolygon_trail(Npoly_trail+1,2)) call append_point_to_polygon(hpoint, polygon_trail,& Npoly_trail, hpolygon_trail) call move_alloc(hpolygon_trail, polygon_trail) Npoly_trail = Npoly_trail + 1 end if end if ind if !pC, vCD call check_if_vector_on_horizontal_bin_edge(pC, vCD, bin_edge_point,& output_bin_width_x, chelp, hpoint) call check_if_vector_on_horizontal_bin_edge(pC, vCD, bin_edge_point,& output_bin_width_x, chelp, hpoint)</pre>
526 527 528 529 530 531 532 533 534 535 536 537 538 539 540 541 542 543 544 545 546 547 548 549 550 551 551 552 553 554 555 556 557	<pre>if (chelp) then allocate(hpolygon_trail(Npoly_trail+1,2)) call append_point.to_polygon(hpoint, polygon_trail,& Npoly_trail, hpolygon_trail) call move_alloc(hpolygon_trail, polygon_trail) Npoly_trail = Npoly_trail + 1 end if call check_if_vector_on_vertical_bin_edge(pB, vBC, bin_edge_point, & output_bin_width_y, chelp, hpoint) if (chelp) then allocate(hpolygon_trail(Npoly_trail+1,2)) call append_point_to_polygon(hpoint, polygon_trail,& Npoly_trail, hpolygon_trail) call move_alloc(hpolygon_trail, polygon_trail) Npoly_trail = Npoly_trail + 1 end if call check_if_vector_on_vertical_bin_edge(pB, vBC, bin_edge_point+(/ output_bin_width_y, chelp, hpoint) if (chelp) then allocate(hpolygon_trail(Npoly_trail+1,2)) call append_point_to_polygon(hpoint, polygon_trail,& Npoly_trail, hpolygon_trail) call move_alloc(hpolygon_trail+1,2)) call append_point_to_polygon(hpoint, polygon_trail,& Npoly_trail = Npoly_trail+1,2)) call append_point_to_polygon(hpoint, polygon_trail,& Npoly_trail, hpolygon_trail(Npoly_trail+1,2)) call append_point_to_polygon(hpoint, polygon_trail,& Npoly_trail = Npoly_trail + 1 end if if pc, vCD call check_if_vector_on_horizontal_bin_edge(pC, vCD, bin_edge_point,& output_bin_width_x, chelp, hpoint) if (chelp) then</pre>

559	call append_point_to_polygon(hpoint, polygon_trail,&
560	Npoly_trail, hpolygon_trail)
561	call move_alloc(hpolygon_trail, polygon_trail)
562	$Npoly_trail = Npoly_trail + 1$
563	end if
564	
565	call check_if_vector_on_horizontal_bin_edge(pC, vCD, bin_edge_point+(/0d0,
	output_bin_width_y/),&
566	output_bin_width_x , chelp , hpoint)
567	if (chelp) then
568	allocate (hpolygon_trail(Npoly_trail+1,2))
569	call append_point_to_polygon(hpoint, polygon_trail,&
570	Npoly_trail, hpolygon_trail)
571	call move_alloc(hpolygon_trail, polygon_trail)
572	$Npoly_trail = Npoly_trail + 1$
573	end if
574	
575	call check_if_vector_on_vertical_bin_edge(pC, vCD, bin_edge_point, &
576	output bin width v. chelp. hpoint)
577	if (chelp) then
578	allocate (hpolygon trail(Npoly trail+1.2))
579	call append point to polygon (hpoint - polygon trail &
580	N noly trail = h nolygon trail)
581	call move alloc (brokgon trail polygon trail)
501	Nacha tasil – Nacha tasil + 1
502	N poly_trail = N poly_trail + 1
283	end 11
584	
585	call check_it_vector_on_vertical_bin_edge(pC, vCD, bin_edge_point+(/
	output_bin_width_x, 0d0/),&
586	output_bin_width_y, chelp, hpoint)
587	if (chelp) then
588	allocate(hpolygon_trail(Npoly_trail+1,2))
589	call append_point_to_polygon(hpoint, polygon_trail,&
590	Npoly_trail, hpolygon_trail)
591	call move_alloc(hpolygon_trail, polygon_trail)
592	Npoly_trail = Npoly_trail + 1
593	end if
594	
595	!pD, vDA
596	call check_if_vector_on_horizontal_bin_edge(pD, vDA, bin_edge_point,&
597	output_bin_width_x , chelp , hpoint)
598	if (chelp) then
599	allocate(hpolygon_trail(Npoly_trail+1,2))
600	call append_point_to_polygon(hpoint, polygon_trail,&
601	Npoly_trail, hpolygon_trail)
602	call move_alloc(hpolygon_trail, polygon_trail)
603	$Npoly_trail = Npoly_trail + 1$
604	end if
605	
606	call check_if_vector_on_horizontal_bin_edge(pD, vDA, bin_edge_point+(/0d0,
	output_bin_width_y/),&
607	output_bin_width_x, chelp, hpoint)
608	if (chelp) then
609	allocate (hpolygon trail(Npoly trail+1.2))
610	call append point to polygon (hpoint polygon trail &
611	N noly trail holygon trail)
612	call move alloc (brokgon trail polygon trail)
612	Nacla tasi - Nacla tasi - 1
614	$r_{poly=0}$ and $r_{poly=0}$ and $r_{poly=0}$
615	enu ii
616	call check if voctor on vortical his adva (nD wDA his adva - ist for
617	can check_n_vector_on_vertical_bin_edge(pD, vDA, bin_edge_point, &
619	if (cholm) then
610	if (cheip) then
019	allocate(npolygon_trail(Npoly_trail+1,2))
620	call append_point_to_polygon(hpoint, polygon_trail,&
621	Npoly_trail, hpolygon_trail)
622	call move_alloc(hpolygon_trail, polygon_trail)
623	Npoly_trail = Npoly_trail + 1
624	end if
625	

```
626
                           call check_if_vector_on_vertical_bin_edge(pD, vDA, bin_edge_point+(/
          output_bin_width_x , 0d0/),&
627
                               output_bin_width_y, chelp, hpoint)
628
                           if (chelp) then
629
                               allocate(hpolygon_trail(Npoly_trail+1,2))
630
                               call append_point_to_polygon(hpoint, polygon_trail,&
                                    Npoly_trail, hpolygon_trail)
631
632
                               call move_alloc(hpolygon_trail, polygon_trail)
633
                               N poly_trail = N poly_trail + 1
                           end if
634
635
636
637
                           if (Npoly\_trail >= 3) then
638
                               !clean double points
639
                               allocate(hpolygon_trail(Npoly_trail,2))
640
                               hpolygon_trail(1, :) = polygon_trail(1, :)
                               Npoly_trail_cleaned = 1
641
642
                               do ihelp=2, Npoly_trail
643
644
                                    point_is_double = .FALSE.
645
                                   do jhelp=1, Npoly\_trail\_cleaned
646
                                        if (polygon_trail(ihelp, 1) == hpolygon_trail(jhelp, 1) .AND.&
647
                                                  polygon_trail(ihelp, 2) == hpolygon_trail(jhelp, 2)) then
648
                                             point_is_double = .TRUE.
649
                                            exit
                                        end if
650
651
                                   end do
652
653
                                    if (.NOT. point_is_double) then
654
                                        Npoly_trail_cleaned = Npoly_trail_cleaned + 1
655
                                        hpolygon_trail(Npoly_trail_cleaned , :) = polygon_trail(ihelp , :)
656
                                    end if
                               end do
657
658
659
                               if (allocated (polygon_trail_cleaned)) then
660
                                    deallocate (polygon_trail_cleaned)
661
                               end if
662
                               allocate(polygon_trail_cleaned(Npoly_trail_cleaned, 2))
663
                               do ihelp=1, Npoly_trail_cleaned
664
                                   polygon_trail_cleaned(ihelp, :) = hpolygon_trail(ihelp, :)
665
                               end do
666
                               deallocate(hpolygon_trail)
667
668
                               if (Npoly\_trail\_cleaned >= 3) then
669
                                    !sort the polygon
670
                                    sort_min_point = (/huge(0d0), huge(0d0)/)
                                    sort_max_point = (/-huge(0d0), -huge(0d0)/)
671
672
                                    \operatorname{sort}_{-}\operatorname{left}_{-}\operatorname{pos} = -1
673
                                    sort_right_pos = -1
674
675
                                    ! find point that is most left and most right
676
                                   do jhelp=1, Npoly_trail_cleaned
677
                                        hpoint = polygon_trail_cleaned(jhelp, :)
678
                                        if (hpoint(1) < sort_min_point(1)) then
679
                                            sort_min_point = hpoint
680
                                            sort_left_pos = jhelp
681
                                        else
                                             if (hpoint(1) = sort_min_point(1) .AND.\&
682
683
                                                 hpoint(2) < sort_min_point(2)) then
684
                                                 sort_min_point = hpoint
685
                                                 sort_left_pos = jhelp
                                            end if
686
687
                                        end if
688
689
                                        if (hpoint(1) > sort_max_point(1)) then
690
                                            sort_max_point = hpoint
691
                                            \texttt{sort_right_pos} = \texttt{jhelp}
                                        else
692
693
                                            if (hpoint(1) == sort_max_point(1) .AND.&
                                                 hpoint(2) > sort_max_point(2)) then
694
695
                                                 sort_max_point = hpoint
```

696	$sort_right_pos = jhelp$
697	end if
698	end if
699	end do
700	
701	$num_points_above = 0$
702	if (allocated (points_above)) then
703	deallocate(points_above)
704	end if
705	num neints helew = 0
707	if(allocated(points below)) then
708	deallocate (points_below)
709	end if
710	allocate(points_below(num_points_below,2))
711	
712	hvector = sort_max_point - sort_min_point
713	!sort into points above and below min-max connection line
714	do jhelp=1, Npoly_trail_cleaned
715	if (jhelp == sort_left_pos .OR. jhelp == sort_right_pos) cycle
716	
717	hpoint = polygon_trail_cleaned(jhelp, :) - sort_min_point
718	crossproduct = hvector(1) * hpoint(2) - hvector(2) * hpoint(1)
719	if $(crossproduct \ge 0)$ then
720	allocate (hpolygon_trail(num_points_above+1,2))
721	call append_point_to_polygon(polygon_trail_cleaned(jneip, :),&
723	call move alloc (hpolygon trail points above)
724	num points above = num points above ± 1
725	else
726	allocate(hpolygon_trail(num_points_below+1,2))
727	call append_point_to_polygon(polygon_trail_cleaned(jhelp, :),&
728	points_below, num_points_below, hpolygon_trail)
729	call move_alloc(hpolygon_trail, points_below)
730	$num_points_below = num_points_below + 1$
731	end if
732	end do
733	
734	! sort points above connecting line
735	do ihelp=2, num_points_above
(30	jneip = ineip - 1 $hpoint = points shows (ihelp - i)$
738	d_0 while (idel $n \ge 1$ AND points above (idel $n \ge 1$) > hpoint (1))
739	points above (ihelp +1 :) = points above (ihelp :)
740	ihelp = ihelp - 1
741	end do
742	<pre>points_above(jhelp+1,:) = hpoint</pre>
743	end do
744	
745	! sort points below connecting line
746	do ihelp=2, num_points_below
747	jhelp = ihelp - 1
748	hpoint = points_below(ihelp, :)
749	do while ($jhelp \ge 1$.AND. $points_below (jhelp, 1) > hpoint(1))$
750	points_below(jhelp+1,:) = points_below(jhelp,:)
751	jneip = jneip - 1
752	rainta halaw(ihaln 1 :) = hnoint
754	end do
755	
756	! fill into sorted polygon
757	if (allocated (polygon_trail_sorted)) then
758	deallocate(polygon_trail_sorted)
759	end if
760	allocate(polygon_trail_sorted(Npoly_trail_cleaned,2))
761	
762	$polygon_trail_sorted(1, :) = sort_min_point$
763	do ihelp=1, num_points_below
764	<pre>polygon_trail_sorted(1+ihelp,:) = points_below(ihelp,:)</pre>
765	end do
100	$polygon_trail_sorted(num_points_below+2, :) = sort_max_point$

767	do ihelp=1, num_points_above
768	polygon_trail_sorted(ihelp+num_points_below+2, :) =&
769	$points_above(num_points_above-(ihelp-1), :)$
770	end do
771	
772	current_polygon_area = 0d0
773	do ihelp=1, Npoly_trail_cleaned
774	$jhelp = mod((ihelp+1), Npoly_trail_cleaned+1)$
775	if $(\text{jhelp }, \text{EQ}, 0)$ $\text{jhelp } = 1$
776	hpoint = polygon_trail_sorted (inelp, :)
778	n_{2} point = polygon_train_sorted(jneip, :)
779	$\frac{1}{1} \frac{1}{1} \frac{1}$
780	$\operatorname{triangle_area} = \operatorname{abs}(\operatorname{npoint}(1) + \operatorname{npoint}(2) = \operatorname{npoint}(2) + \operatorname{npoint}(1))$
781	normvalue = sort (hyector $(1) * * 2 + hyector (2) * * 2)$
782	h2vector(1) = -hvector(2)/normvalue
783	h2vector(2) = hvector(1)/normvalue
784	
785	h3point = hpoint + 0.5d0*hvector + h2vector
786	call point_inside_polygon(h3point, &
787	$polygon_trail_sorted$, $chelp$, $Npoly_trail_cleaned$)
788	if (chelp) then
789	h2vector = -1d0*h2vector
790	end if
791	
792	$dot_result = hpoint(1) * h2vector(1) + hpoint(2) * h2vector(2)$
793	if $(dot_result \ge 0)$ then
794	$sign_of_area = 1$
795	else
796	sign_of_area = -1
797	end if
798	triangle_area = triangle_area * sign_of_area
799	current_polygon_area = current_polygon_area + triangle_area
800	end do
801	$overlap_area = abs(current_polygon_area)/2.$
802	else
000	
803	$overlap_area = 0d0$
803 804	$overlap_area = 0d0$ end if
803 804 805	overlap_area = 0d0 end if
803 804 805 806	overlap_area = 0d0 end if !call_calc_area_of_polygon(polygon_trail, Npoly_trail, overlap_area) area_polygon = area_polygon + overlap_area
803 804 805 806 807 808	overlap_area = 0d0 end if !call calc_area_of_polygon(polygon_trail, Npoly_trail, overlap_area) area_polygon = area_polygon + overlap_area
 803 804 805 806 807 808 809 	overlap_area = 0d0 end if !call calc_area_of_polygon(polygon_trail, Npoly_trail, overlap_area) area_polygon = area_polygon + overlap_area
 803 804 805 806 807 808 809 810 	<pre>overlap_area = 0d0 end if !call calc_area_of_polygon(polygon_trail, Npoly_trail, overlap_area) area_polygon = area_polygon + overlap_area allocate(hnew_count_list(number_of_new_counts+1)) allocate(hnew_count_list_positions(number_of_new_counts+1,2))</pre>
 803 804 805 806 807 808 809 810 811 	<pre>overlap_area = 0d0 end if !call calc_area_of_polygon(polygon_trail, Npoly_trail, overlap_area) area_polygon = area_polygon + overlap_area allocate(hnew_count_list(number_of_new_counts+1)) allocate(hnew_count_list_positions(number_of_new_counts+1,2)) call append point to list(overlap_area & </pre>
 803 804 805 806 807 808 809 810 811 812 	<pre>overlap_area = 0d0 end if !call calc_area_of_polygon(polygon_trail, Npoly_trail, overlap_area) area_polygon = area_polygon + overlap_area allocate(hnew_count_list(number_of_new_counts+1)) allocate(hnew_count_list_positions(number_of_new_counts+1,2)) call append_point_to_list(overlap_area,&</pre>
 803 804 805 806 807 808 809 810 811 812 813 	<pre>overlap_area = 0d0 end if !call calc_area_of_polygon(polygon_trail, Npoly_trail, overlap_area) area_polygon = area_polygon + overlap_area allocate(hnew_count_list(number_of_new_counts+1)) allocate(hnew_count_list_positions(number_of_new_counts+1,2)) call append_point_to_list(overlap_area ,&</pre>
 803 804 805 806 807 808 809 810 811 812 813 814 	<pre>overlap_area = 0d0 end if !call calc_area_of_polygon(polygon_trail, Npoly_trail, overlap_area) area_polygon = area_polygon + overlap_area allocate(hnew_count_list(number_of_new_counts+1)) allocate(hnew_count_list_positions(number_of_new_counts+1,2)) call append_point_to_list(overlap_area,&</pre>
 803 804 805 806 807 808 809 810 811 812 813 814 815 	<pre>overlap_area = 0d0 end if !call calc_area_of_polygon(polygon_trail, Npoly_trail, overlap_area) area_polygon = area_polygon + overlap_area allocate(hnew_count_list(number_of_new_counts+1)) allocate(hnew_count_list_positions(number_of_new_counts+1,2)) call append_point_to_list(overlap_area,&</pre>
 803 804 805 806 807 808 809 810 811 812 813 814 815 816 	<pre>overlap_area = 0d0 end if !call calc_area_of_polygon(polygon_trail, Npoly_trail, overlap_area) area_polygon = area_polygon + overlap_area allocate(hnew_count_list(number_of_new_counts+1)) allocate(hnew_count_list_positions(number_of_new_counts+1,2)) call append_point_to_list(overlap_area,&</pre>
 803 804 805 806 807 808 809 810 811 812 813 814 815 816 817 	<pre>overlap_area = 0d0 end if !call calc_area_of_polygon(polygon_trail, Npoly_trail, overlap_area) area_polygon = area_polygon + overlap_area allocate(hnew_count_list(number_of_new_counts+1)) allocate(hnew_count_list_positions(number_of_new_counts+1,2)) call append_point_to_list(overlap_area,&</pre>
 803 804 805 806 807 808 809 810 811 812 813 814 815 816 817 818 	<pre>overlap_area = 0d0 end if !call calc_area_of_polygon(polygon_trail, Npoly_trail, overlap_area) area_polygon = area_polygon + overlap_area allocate(hnew_count_list(number_of_new_counts+1)) allocate(hnew_count_list_positions(number_of_new_counts+1,2)) call append_point_to_list(overlap_area,&</pre>
 803 804 805 806 807 808 809 810 811 812 813 814 815 816 817 818 819 	<pre>overlap_area = 0d0 end if !call calc_area_of_polygon(polygon_trail, Npoly_trail, overlap_area) area_polygon = area_polygon + overlap_area allocate(hnew_count_list(number_of_new_counts+1)) allocate(hnew_count_list_positions(number_of_new_counts+1,2)) call append_point_to_list(overlap_area,&</pre>
803 804 805 806 807 808 809 810 811 812 813 814 815 816 817 818 819 820	<pre>overlap_area = 0d0 end if !call calc_area_of_polygon(polygon_trail, Npoly_trail, overlap_area) area_polygon = area_polygon + overlap_area allocate(hnew_count_list(number_of_new_counts+1)) allocate(hnew_count_list_positions(number_of_new_counts+1,2)) call append_point_to_list(overlap_area,&</pre>
 803 804 805 806 807 808 809 810 811 812 813 814 815 816 817 818 819 820 821 	<pre>overlap_area = 0d0 end if !call calc_area_of_polygon(polygon_trail, Npoly_trail, overlap_area) area_polygon = area_polygon + overlap_area allocate(hnew_count_list(number_of_new_counts+1)) allocate(hnew_count_list_positions(number_of_new_counts+1,2)) call append_point_to_list(overlap_area,&</pre>
 803 804 805 806 807 808 809 810 811 813 814 815 816 817 818 819 820 821 822 	<pre>overlap_area = 0d0 end if !call calc_area_of_polygon(polygon_trail, Npoly_trail, overlap_area) area_polygon = area_polygon + overlap_area allocate(hnew_count_list(number_of_new_counts+1)) allocate(hnew_count_list_positions(number_of_new_counts+1,2)) call append_point_to_list(overlap_area,&</pre>
 803 804 805 806 807 808 809 810 811 813 814 815 816 817 818 819 820 821 822 823 	<pre>overlap_area = 0d0 end if !call calc_area_of_polygon(polygon_trail, Npoly_trail, overlap_area) area_polygon = area_polygon + overlap_area allocate(hnew_count_list(number_of_new_counts+1)) allocate(hnew_count_list_positions(number_of_new_counts+1,2)) call append_point_to_list(overlap_area,&</pre>
 803 804 805 806 807 808 809 811 812 813 814 815 816 817 818 819 820 821 822 823 824 	<pre>overlap_area = 0d0 end if !call calc_area_of_polygon(polygon_trail, Npoly_trail, overlap_area) area_polygon = area_polygon + overlap_area allocate(hnew_count_list(number_of_new_counts+1)) allocate(hnew_count_list_positions(number_of_new_counts+1,2)) call append_point_to_list(overlap_area,&</pre>
 803 804 805 806 807 808 809 810 811 813 814 815 816 817 818 819 820 821 822 823 824 825 	<pre>overlap_area = 0d0 end if ! call calc_area_of_polygon(polygon_trail, Npoly_trail, overlap_area) area_polygon = area_polygon + overlap_area allocate (hnew_count_list (number_of_new_counts+1)) allocate (hnew_count_list_positions (number_of_new_counts+1,2)) call append_point_to_list (overlap_area,&</pre>
 803 804 805 806 807 808 809 810 811 813 814 815 816 817 818 819 820 821 822 823 824 825 826 	<pre>overlap_area = 0d0 end if ! call calc_area_of_polygon(polygon_trail, Npoly_trail, overlap_area) area_polygon = area_polygon + overlap_area allocate(hnew_count_list(number_of_new_counts+1)) allocate(hnew_count_list_positions(number_of_new_counts+1,2)) call append_point_to_list(overlap_area,&</pre>
 803 804 805 806 807 808 809 810 811 812 813 814 815 816 821 822 823 824 825 826 827 	<pre>overlap_area = 0d0 end if !call calc_area_of_polygon(polygon_trail, Npoly_trail, overlap_area) area_polygon = area_polygon + overlap_area allocate(hnew_count_list(number_of_new_counts+1)) allocate(hnew_count_list_positions(number_of_new_counts+1,2)) call append_point_to_list(overlap_area,& new_count_list, number_of_new_counts, hnew_count_list) call append_point_to_poslist((/jx, jy/),& new_count_list_positions, number_of_new_counts,& hnew_count_list_positions) call move_alloc(hnew_count_list, new_count_list) call move_alloc(hnew_count_list_positions, new_count_list_positions) number_of_new_counts = number_of_new_counts + 1 end if end do end do end do do ihelp=1, number_of_new_counts if (area_polygon > 100) print*,overlap_area,area_polygon jx = new_count_list_positions(ihelp, 1) jy = new_count_list(ihelp) </pre>
 803 804 805 806 807 808 809 810 811 812 813 814 815 816 821 822 823 824 825 826 827 828 	<pre>overlap_area = 0d0 end if !call calc_area_of_polygon(polygon_trail, Npoly_trail, overlap_area) area_polygon = area_polygon + overlap_area allocate(hnew_count_list(number_of_new_counts+1)) allocate(hnew_count_list_positions(number_of_new_counts+1,2)) call append_point_to_list(overlap_area,& new_count_list, number_of_new_counts, hnew_count_list) call append_point_to_poslist((/jx, jy/),& new_count_list_positions, number_of_new_counts,& hnew_count_list_positions) call move_alloc(hnew_count_list, new_count_list) call move_alloc(hnew_count_list_positions, new_count_list_positions) number_of_new_counts = number_of_new_counts + 1 end if end do end do do ihelp=1, number_of_new_counts if (area_polygon > 100) print*,overlap_area, area_polygon jx = new_count_list_positions(ihelp, 1) jy = new_count_list_positions(ihelp, 2) overlap_area = new_count_list(help) output_data(jx, jy) = output_data(jx, jy) + dat_value*overlap_area/area_polygon</pre>
 803 804 805 806 807 808 809 810 811 813 814 815 816 821 822 823 824 825 826 827 828 829 	<pre>overlap_area = 0d0 end if !call calc_area_of_polygon(polygon_trail, Npoly_trail, overlap_area) area_polygon = area_polygon + overlap_area allocate(hnew_count_list_number_of_new_counts+1)) allocate(hnew_count_list_positions(number_of_new_counts+1,2)) call append_point.to_list(overlap_area,&</pre>
 803 804 805 806 807 808 809 810 811 812 813 814 815 816 821 822 823 824 825 826 827 828 829 830 	<pre>overlap_area = 0d0 end if !call calc_area_of_polygon(polygon_trail, Npoly_trail, overlap_area) area_polygon = area_polygon + overlap_area allocate(hnew_count_list(number_of_new_counts+1)) allocate(hnew_count_list_positions(number_of_new_counts+1,2)) call append_point_to_list(overlap_area,&</pre>
 803 804 805 806 807 808 809 810 811 812 813 814 815 816 821 822 823 824 825 826 827 828 829 830 831 	<pre>overlap_area = 0d0 end if !call calc_area_of_polygon(polygon_trail, Npoly_trail, overlap_area) area_polygon = area_polygon + overlap_area allocate(hnew_count_list(number_of_new_counts+1))) allocate(hnew_count_list_positions(number_of_new_counts+1,2)) call append_point.to_list(overlap_area,&</pre>
 803 804 805 806 807 808 809 810 811 812 813 814 815 816 821 822 823 824 825 826 827 828 829 830 831 832 	<pre>overlap_area = 0d0 end if !call calc_area_of_polygon(polygon_trail, Npoly_trail, overlap_area) area_polygon = area_polygon + overlap_area allocate(hnew_count_list(number_of_new_counts+1)) allocate(hnew_count_list_positions(number_of_new_counts+1,2)) call append_point_to_list(overlap_area,&</pre>
 803 804 805 806 807 808 809 810 811 812 813 814 815 816 821 822 823 824 825 826 827 828 829 830 831 832 833 	<pre>overlap_area = 0d0 end if !call calc_area_of_polygon(polygon_trail, Npoly_trail, overlap_area) area_polygon = area_polygon + overlap_area allocate(hnew_count_list(number_of_new_counts+1)) allocate(hnew_count_list_positions(number_of_new_counts+1,2)) call append_point_to_list(overlap_area,& new_count_list, number_of_new_counts, hnew_count_list) call append_point_to_poslist((/jx, jy/),& new_count_list_positions) call move_alloc(hnew_count_list, new_count_list) call move_alloc(hnew_count_list, new_count_list_positions) number_of_new_counts = number_of_new_counts + 1 end if end do end do do inhelp=1, number_of_new_counts if (area_polygon > 100) print*,overlap_area, area_polygon jx = new_count_list_positions(ihelp, 1) jy = new_count_list_positions(ihelp, 2) overlap_area = new_count_list(ihelp) output_scale(jx, jy) = output_scale(jx, jy) + dat_value*overlap_area/area_polygon scale_factors(jx, jy) = scale_factors(jx, jy) + overlap_area/area_polygon end do end do</pre>
803 804 805 806 807 808 809 810 811 812 813 814 815 816 817 818 819 820 821 822 823 824 825 826 827 828 829 830 831 832 833 834	<pre>overlap_area = 0d0 end if !call calc_area_of_polygon(polygon_trail, Npoly_trail, overlap_area) area_polygon = area_polygon + overlap_area allocate(hnew_count_list(number_of_new_counts+1)) allocate(hnew_count_list(number_of_new_counts+1,2)) call append_point_to_positions(number_of_new_count_list) call append_point_to_positions, hnew_count_list) call move_alloc(hnew_count_list, new_count_list) call move_alloc(hnew_count_list_positions, new_count_list_positions) number_of_new_counts = number_of_new_counts + 1 end if end do end do do if (area_polygon > 100) print*,overlap_area, area_polygon jx = new_count_list_positions(ihelp, 1) jy = new_count_list_positions(ihelp, 2) overlap_area = new_count_list(ihelp) output_data(jx, jy) = output_data(jx, jy) + dat_value*overlap_area/area_polygon scale_factors(jx, jy) = scale_factors(jx, jy) + overlap_area/area_polygon end do end do end do end do</pre>
 803 804 805 806 807 808 810 811 813 814 815 816 817 818 819 820 821 822 823 824 825 826 827 828 829 830 831 834 835 	<pre>overlap_area = 0d0 end if !call calc_area_of_polygon(polygon_trail, Npoly_trail, overlap_area) area_polygon = area_polygon + overlap_area allocate(hnew.count_list(number_of_new_counts+1)) allocate(hnew.count_list.positions(number_of_new_counts+1,2)) call append_point_to_list(overlap_area,&</pre>
 803 804 805 806 807 808 819 812 813 814 815 816 817 818 819 820 821 822 823 824 825 826 827 828 829 830 831 834 835 836 	<pre>overlap_area = 0d0 end if !call calc_area_of_polygon(polygon_trail, Npoly_trail, overlap_area) area_polygon = area_polygon + overlap_area allocate(hnew_count_list_positions(number_of_new_counts+1,2)) call append_point_to_isit(overlap_area,&</pre>

```
838
                 final_total_count = final_total_count + output_data(ix, iy)
                 sca_value = scale_factors(ix, iy)
839
840
                 if (sca_value > 0) then
                    output_scale(ix, iy) = output_scale(ix, iy)/sca_value
841
842
                end if
            end do
843
        end do
844
845
    end subroutine rebin
```

F. Abbreviations

$A_{Si wafer}$	Sample area $[\rm cm^2]$
Å	Angström; $1 \text{ Å} = 10^{-10} \text{ m}$
ad	As deposited
В	Applied Field [T]
b	Scattering length of atom
C	Curie constant [K]
d	Layer thickness [Å]
d	Film thickness
D	Coherence length $[Å]$
d_{min}	Thickness of sublayers
d_N	Material thickness
CDW	Charge density wave
EDX	Energy dispersive X-ray spectroscopy
emu	Electromagnetic unit; $1 \text{ emu} = 10^{-3} \text{ Am}^2$
eV	Electron Volt
Få	Fåkeström
FC	Field cooled
FCW	Field cooled warming
FWHM	Full width at half maximum
Н	Magnetic field [Oe]
h_{film}	Film thickness [cm]
h_{wafer}	Wafer thickness [cm]
HAADF	High-angle annular dark-field imaging
k _B	Boltzmann constant $1.38064852(79)\cdot10^{-23}\rm JK^{-1}$
$\vec{k_i}$	Incident ray
$\vec{k_r}$	Reflected ray
m_i	Diffraction order of i-th maximum
М	Molecular weight
М	Magnetic moment [emu]
М	(Volume) magnetization [A/m]
MER	Modulated elemental reactants
MLC	Misfit layer compound
MPMS	Magnetic property measurement system
Ν	Amount of layer

n	Refractive index
N _A	Avogadro constant $6.022140857(74) \cdot 10^{23}\mathrm{mol}^{-P1}$
NBED	Nano-beam electron diffraction
NMR	Nuclear magnetic resonance
M_S	Saturation magnetization [A/m]
m_{sample}	Sample mass [g]
Oe	Oersted; 1 Oe = $\frac{10^3}{4\pi}$ A/m
PLD	Pulsed laser deposition
PNP	Polarized neutron reflectometry
PPMS	Physical property measurement system
PVD	Physical vapour deposition
$ec{Q_z}$	Scattering vector
r	Reflectivity
r'	Fresnel coefficient
r_e	Electron radius $2.1879403227(19)\cdot10^{-15}\mathrm{m}$
SLD	Scattering length density
STEM	Scanning transmission electron microscope
SQUID	Superconducting quantum interference device
T	Temperature [K] or $[^{\circ}C]$
T_C	Superconducting transition temperature [K]
T_C	Curie temperature [K]
T_N	Néel temperature [K]
TEM	Transmission electron microscope
TMD	Transition metal dichalcogenide
V_m	Material volume
V_{sample}	Sample volume $[cm^3]$
VSM	Vibrating sample magnetometry
XRD	X-ray diffraction
XRF	X-ray fluorescence
XRR	X-ray reflectometry
Z	Thomson scattering
ZFC	Zero field cooled
β	Absorptive dispersion correction
δ	Misfit parameter
δ	Anomalous dispersion correction
$\Delta b'$	Lattice mismatch [Å]

ΔQ	Unidirectional lattice mismatch $[Å^{-1}]$
ΔQ	Separation of the Kiessig Fring maxima $[Å^{-1}]$
$\Delta \mu$	Distance between the Gaussian maxima $[Å^{-1}]$
η	Amount of substance
2θ	Scattering angle [°]
$ heta_i$	Angular position of Kiessig fringes $[^{\circ}]$
$ heta_c$	Angular position of critical angle $[\circ]$
$ heta_W$	Curie-Weiss temperature [K]
λ	Wavelength $[Å]$
μ	Integral particle moment
$\mu_{ m B}$	Bohr magneton = $9.274009994(57)*10^{-24}\mathrm{JT}^{-1}$
ρ	Density $[g/cm^3]$
χ	Susceptibility
χ^2	Goodness of fit
χ_D	Diamagnetic susceptibility
$ ho_D$	Density $[g/cm^3]$
$ ho_e$	Electron density
ω	Diffracted beam direction
References

- [1] T. G. H. James, *Gold Bull.* **1972**, *5*(2), 38–42.
- [2] E. Bloch, Transparent Mirror, **1903**.
- [3] H. Frey, H. R. Khan, Handbook of Thin-Film Technology, Springer Berlin Heidelberg, Berlin, Heidelberg, 2015.
- [4] A. H. Lettington, Carbon **1998**, 36(5-6), 555–560.
- [5] T. A. Otitoju, A. L. Ahmad, B. S. Ooi, J. Ind. Eng. Chem. 2017, 47, 19–40.
- [6] F. Samson, Surf. Coat. Technol. **1996**, 81(1), 79–86.
- [7] J. Azadmanjiri, C. C. Berndt, J. Wang, A. Kapoor, V. K. Srivastava, *RSC Adv.* 2016, 6(111), 109361–109385.
- [8] F. Siewert, J. Buchheim, T. Zeschke, M. Störmer, G. Falkenberg, R. Sankari, J. Synchrotron Radiat. 2014, 21(5), 968–975.
- [9] X. Cheng, L. Zhang, C. Morawe, M. Sanchez Del Rio, J. Synchrotron Radiat.
 2015, 22(2), 317–327.
- [10] B. Tudu, A. Tiwari, Vacuum **2017**, 146, 329–341.
- [11] D. Richardson, K. Srinivasan, S. Katz, M. Wu, Appl. Phys. Lett. 2017, 111(18).
- [12] A. Kingon, *Nature* **1999**, *401*(6754), 658–659.
- [13] Z. Su, M. Yao, M. Li, W. Gao, Q. Li, Q. Feng, X. Yao, J. Mater. Chem. C 2018, 6(21), 5616–5623.
- [14] A. Pearse, T. Schmitt, E. Sahadeo, D. M. Stewart, A. Kozen, K. Gerasopoulos, A. A. Talin, S. B. Lee, G. W. Rubloff, K. E. Gregorczyk, ACS Nano 2018, 12(5), 4286–4294.
- [15] J. H. Choi, Y. M. Kim, Y. W. Park, T. H. Park, J. W. Jeong, H. J. Choi, E. H. Song, J. W. Lee, C. H. Kim, B. K. Ju, *Nanotechnology* **2010**, *21*(47).
- [16] J. Meyer, H. Schmidt, W. Kowalsky, T. Riedl, A. Kahn, App. Phys. Lett. 2010, 96(24), 1–4.

- [17] S. H. Lim, S. W. Seo, H. Lee, H. Chae, S. M. Cho, Korean J. Chem. Eng. 2016, 33(6), 1971–1976.
- [18] Y. Zhang, J. Hao, J. Mater. Chem. C 2013, 1(36), 5607.
- [19] F. M. Koehler, M. Rossier, M. Waelle, E. K. Athanassiou, L. K. Limbach, R. N. Grass, D. Günther, W. J. Stark, *Chem. commun.* 2009, 4862–4864.
- [20] S. D. Bader, *Rev. Mod. Phys.* **2006**, *78*, 1–15.
- [21] A.-H. Lu, E. L. Salabas, F. Schüth, Angew. Chem. Int. Ed 2007, 46, 1222– 1244.
- [22] M. Wankhede, A. Bouras, M. Kaluzova, C. G. Hadjipanayis, Expert Rev Clin Pharmacol. 2012, 5(2), 173–186.
- [23] S. Disch, E. Wetterskog, R. P. Hermann, A. Wiedenmann, U. Vainio, G. Salazar-Alvarez, L. Bergström, T. Brückel, New J. Phys. 2012, 14, 0130205–0130216.
- [24] Eds., J. Li, J. Li, Y. Chu, Crystal Growth Concepts, Machanisms and Applications, nova Science Publisher, New York, 2015, 1–345.
- [25] L. Fister, X. Li, J. McConnell, T. Novet, D. C. Johnson, J. Vac. Sci. Technol. A 1993, 11(6), 3014–3019.
- [26] D. C. Johnson, Curr. Opin. Solid State Mater. Sci. 1998, 3, 159–167.
- [27] R. Westover, R. A. Atkins, M. Falmbigl, J. J. Ditto, D. C. Johnson, J. Solid State Chem. 2016, 236, 173–185.
- [28] M. Esters, M. B. Alemayehu, Z. Jones, N. T. Nguyen, M. D. Anderson, C. Grosse, S. F. Fischer, D. C. Johnson, Angew. Chem. Int. Ed 2015, 127, 1146–1150.
- [29] G. Hautier, C. Fischer, V. Ehrlacher, A. Jain, G. Ceder, *Inorg. Chem.* 2011, 50(17), 656–663.
- [30] W. Sun, S. T. Dacek, S. P. Ong, G. Hautier, A. Jain, W. D. Richards, A. C. Gamst, K. A. Persson, G. Ceder, *Sci. Adv.* **2016**, *2*, 1–8.
- [31] R. Atkins, D. B. Moore, D. C. Johnson, *Chem. Mater.* **2013**, *25*, 1744–1750.

- [32] M. B. Alemayehu, M. Falmbigl, C. Grosse, K. Ta, S. F. Fischer, D. C. Johnson, J. Alloys Compd. 2015, 619, 861–868.
- [33] I. Häusler, R. Atkins, M. Falmbigl, S. P. Rudin, W. Neumann, D. C. Johnson, Z. Kristallogr. 2015, 230(1), 45–54.
- [34] G. A. Wiegers, Prog. Solid St. Chem. 1996, 24(1-2), 1–139.
- [35] J. Wulff, A. Meetsma, S. Van Smaalen, R. J. Haange, J. L. De Boer, G. A. Wiegers, J. Solid State Chem. 1990, 84(1), 118–129.
- [36] A. Meerschaut, Y. Moëlo, L. Cario, A. Lafond, C. Deudon, Mol. Cryst. Liq. Cryst. Sci. Technol., Sect. A 2000, 341(2), 1–8.
- [37] J. Brandt, L. Kipp, M. Skibowski, E. E. Krasovskii, W. Schattke, E. Spiecker,
 C. Dieker, W. Jäger, Surf. Sci. 2003, 532-535, 705–710.
- [38] G. Radovsky, R. Popovitz-Biro, T. Lorenz, J.-O. Joswig, G. Seifert, L. Houben,
 R. E. Dunin-Borkowski, R. Tenne, J. Mater. Chem. C 2016, 4, 89.
- [39] J. Rouxel, A. Meerschaut, G. A. Wiegers, J. Alloys Compd. 1995, 229(1), 144–157.
- [40] C. M. Fang, A. R. H. F. Ettema, C. Haas, G. A. Wiegers, Phys. Rev. B 1995, 52(4), 2336–2347.
- [41] A. R. H. . F. Ettema, C. Haas, J. Phys.: Condens. Matter 1993, 5, 3817–3826.
- [42] E. Kabliman, P. Blaha, K. Schwarz, *Phys. Rev. B* **2010**, *82*(12), 1–8.
- [43] D. Merrill, D. Moore, S. Bauers, M. Falmbigl, D. Johnson, *Materials* 2015, 8(4), 2000–2029.
- [44] C. Heideman, N. Nyugen, J. Hanni, Q. Lin, S. Duncombe, D. C. Johnson,
 P. Zschack, J. Solid State Chem. 2008, 181(7), 1701–1706.
- [45] M. Beekman, S. Disch, S. Rouvimov, D. Kasinathan, K. Koepernik, H. Rosner, P. Zschack, W. S. Neumann, D. C. Johnson, Angew. Chem. Int. Ed 2013, 52(50), 13211–13214.
- [46] M. D. Anderson, Dissertation, University of Oregon, 2011.

- [47] M. Falmbigl, M. Esters, D. C. Johnson, Cryst. Res. Technol. 2017, 52(10), 1700067.
- [48] M. D. Hornbostel, E. J. Hyer, J. Thiel, D. C. Johnson, J. Am. Chem. Soc. 1997, 119(11), 2665–2668.
- [49] M. Beekman, G. Cogburn, C. Heideman, S. Rouvimov, P. Zschack, W. Neumann, D. Johnson, J. Electron. Mater. 2012, 41(6), 1476–1480.
- [50] D. R. Merrill, D. R. Sutherland, J. J. Ditto, D. B. Moore, M. Falmbigl, D. L. Medlin, D. C. Johnson, *Nanoscale* **2016**, *8*(28), 13646–13651.
- [51] R. D. Westover, G. Mitchson, J. J. Ditto, D. C. Johnson, Eur. J. Inorg. Chem. 2016, 2016(8), 1225–1231.
- [52] M. Falmbigl, Z. Hay, J. Ditto, G. Mitchson, D. C. Johnson, J. Mater. Chem. C 2015, 3(47), 12308–12315.
- [53] R. D. Westover, G. Mitchson, O. K. Hite, K. Hill, D. C. Johnson, J. Electron. Mater. 2016, 45(10), 4898–4902.
- [54] S. R. Wood, D. R. Merrill, G. Mitchson, A. C. Lygo, S. R. Bauers, D. M. Hamann, D. R. Sutherland, J. Ditto, D. C. Johnson, *Chem. Mater.* 2017, 29, 773–779.
- [55] G. Mitchson, S. R. Bauers, P. Schädlich, J. J. Ditto, D. C. Johnson, Eur. J. Inorg. Chem. 2016, 950–957.
- [56] I. Okońska-Kozlowska, J. Kopyczok, H. D. Lutz, T. Stingl, Acta Cryst. C 1993, 49, 1448–1449.
- [57] J. S. Bettinger, R. V. Chopdekar, M. Liberati, J. R. Neulinger, M. Chshiev,
 Y. Takamura, L. M. B. Alldredge, E. Arenholz, Y. U. Idzerda, A. M. Stacy,
 W. H. Butler, Y. Suzuki, J. Magn. Magn. Mater. 2007, 318, 65–73.
- [58] M. Esters, A. Liebig, J. J. Ditto, M. Falmbigl, M. Albrecht, D. C. Johnson, J. Alloys Compd. 2016, 671, 220–225.
- [59] M. D. Anderson, J. O. Thompson, D. C. Johnson, Chem. Mater. 2013, 25, 3996–4002.

- [60] C. Zhang, Y. Yan, Y. Sheng Zhao, J. Yao, Annu. Rep. Prog. Chem., Sect. C: Phys. Chem. 2013, 109, 211–239.
- [61] M. L. Rao, M. Shamsuzzoha, A. Gupta, J. Cryst. Growth 2007, 306(2), 321– 325.
- [62] N. Daneu, A. Rečnik, T. Yamazaki, T. Dolenec, Phys. Chem. Miner. 2007, 34(4), 233–247.
- [63] M. Noh, J. Thiel, D. C. Johnson, *Science* **1995**, *270*(5239), 1181–1184.
- [64] C. Pang, R. Yang, A. Singh, H. Chen, M. K. Bowman, N. Bao, L. Shen, A. Gupta, RSC Adv. 2017, 7, 31173–31179.
- [65] S. Q. Wang, MRS Bull. **1994**, 19(8), 30–40.
- [66] J. DuMond, J. P. Youtz, J. Appl. Phys. **1940**, 11(5), 357–365.
- [67] G. S. Chen, S. T. Chen, J. Appl. Phys. **2000**, 87(12), 8473.
- [68] M. A. Nicolet, *Thin Solid Films* **1978**, *52*(3), 415–443.
- [69] D. Appy, M. Wallingford, D. Jing, R. Ott, M. C. Tringides, G. Richter, P. A. Thiel, J. Vac. Sci. Technol. A 2017, 35(6), 061401.
- [70] A. Babitsyna, T. Emel'yanova, T. Koneshova, M. Chernitsyna, V. Kalinnikov, *Russ. J. Inorg. Chem.* 1980, 25, 603–604. ASM Alloy Phase Diagrams Database.
- [71] F. Hulliger, Struct. Bonding **1968**, 4, 83–216.
- [72] G. Z. Magda, J. Petõ, G. Dobrik, C. Hwang, L. P. Biró, L. Tapasztó, Sci. Rep. 2015, 5, 3–7.
- [73] M. Kertesz, R. Hoffmann, J. Am. Chem. Soc. **1984**, 106(12), 3453–3460.
- [74] W. Choi, N. Choudhary, G. H. Han, J. Park, D. Akinwande, Y. H. Lee, *Mater. Today* 2017, 20(3), 116–130.
- [75] D. Voiry, A. Mohite, M. Chhowalla, Chem. Soc. Rev. 2015, 44(9), 2702–2712.
- [76] M. Chhowalla, H. S. Shin, G. Eda, L.-J. Li, K. P. Loh, H. Zhang, Nat. Chem. 2013, 5(4), 263–275.

- [77] H. Katzke, P. Tolédano, W. Depmeier, *Phys. Rev. B* **2004**, *69*(13), 1–8.
- [78] R. E. Atkins, Dissertation, University of Oregon, 2013.
- [79] M. B. Alemayehu, M. Falmbigl, K. Ta, D. C. Johnson, Chem. Mater. 2015, 27(6), 2158–2164.
- [80] J. R. Lu, E. M. Lee, R. K. Thomas, Acta Cryst. 1996, 52, 11–41.
- [81] T. Brückel, D. Richter, G. Roth, A. Wischnewski, R. Zorn, *Neutron scattering*, Forschungszentrum Jülich, 2015.
- [82] Mario Birkholz, P. F. Fewster, C. Genzel, Thin Film Analysis by X-Ray Scattering, Wiley-VCH, 2006.
- [83] H. Kiessig, Ann. Phys. **1933**, 5(10), 769–788.
- [84] T. M. Phung, J. M. Jensen, D. C. Johnson, J. J. Donovan, B. G. McBurnett, X-Ray Spectrom. 2008, 37, 608–617.
- [85] T. M. Phung, D. C. Johnson, G. A. Antonelli, J. Appl. Phys. 2006, 100, 063317– 1–6.
- [86] H. Zabel, Appl. Phys. A. **1994**, 58, 159–168.
- [87] C. E. Pfluger, Anal. Chem **1972**, 44(5), 563–572.
- [88] R. A. Cowley, T. W. Ryan, J. Phys. D. 1987, 20(1), 61–66.
- [89] P. F. Fewster, Rep. Prog. Phys. 1996, 59, 1339–1407.
- [90] T. Chatterji, Neutron Scattering from Magnetic Material, Elsevier Science, 2006.
- [91] S. J. Blundell, J. A. C. Bland, *Phys. Rev. B* **1992**, 46(6), 3391–3400.
- [92] J. F. Ankner, G. P. Felcher, J. Magn. Magn. Mater. 1999, 200, 741–754.
- [93] Q. Liang, J. Liu, Z. Cheng, Y. Li, L. Chen, R. Zhang, J. Zhang, Y. Han, J. Mater. Chem. A 2016, 4(1), 223–232.
- [94] D. R. Merrill, D. B. Moore, M. N. Coffey, A. W. Jansons, M. Falmbigl, D. C. Johnson, Semicond. Sci. Technol. 2014, 29(6), 064004.

- [95] G. Mitchson, M. Falmbigl, J. Ditto, D. C. Johnson, *Inorg. Chem.* 2015, 54 (21), 10309–10315.
- [96] C. L. Heideman, R. Rostek, M. D. Anderson, A. a. Herzing, I. M. Anderson, D. C. Johnson, J. Electron. Mater. 2010, 39(9), 1476–1481.
- [97] M. M. Smeller, C. L. Heideman, Q. Lin, M. Beekman, M. D. Anderson, P. Zschack, I. M. Anderson, D. C. Johnson, Z. anorg. allg. Chem. 2012, 638(15), 2632–2639.
- [98] A. C. Lygo, D. M. Hamann, D. B. Moore, D. R. Merrill, J. Ditto, M. Esters, J. Orlowicz, S. R. Wood, D. C. Johnson, J. Am. Chem. Soc. 2018, 140(9), 3385–3393.
- [99] M. Falmbigl, M. B. Alemayehu, D. R. Merrill, M. Beekman, D. C. Johnson, Cryst. Res. Technol. 2015.
- [100] G. A. Wiegers, A. Meetsma, R. J. Haange, J. Wulff, J. L. de Boer, S. Kuypers, G. Van Tendeloo, J. Van Landuyt, S. Amelinckx, A. Meersehaut, P. Rabu, J. Rouxel, *Solid State Commun.* **1989**, 70(4), 409–413.
- [101] I. Häusler, R. Atkins, M. Falmbigl, S. P. Rudin, W. Neumann, D. C. Johnson, Z. Kristallogr. 2015, 230(1), 45–54.
- [102] D. M. Hamann, D. R. Merrill, S. R. Bauers, G. Mitchson, J. Ditto, S. P. Rudin,
 D. C. Johnson, *Inorg. Chem.* 2017, 56(6), 3499–3505.
- [103] R. Atkins, M. Dolgos, A. Fiedler, C. Grosse, S. F. Fischer, S. P. Rudin, D. C. Johnson, Chem. Mater. Mater. 2014, 26, 2862–2872.
- [104] O. K. Hite, M. Falmbigl, M. B. Alemayehu, M. Esters, S. R. Wood, D. C. Johnson, *Chem. Mater.* 2017, 29(13), 5646–5653.
- [105] D. B. Moore, M. Beekman, S. Disch, P. Zschack, I. Häusler, W. Neumann, D. C. Johnson, Chem. Mater. 2013, 25, 2404–249.
- [106] C. L. Heideman, S. Tepfer, Q. Lin, R. Rostek, P. Zschack, M. D. Anderson, I. M. Anderson, D. C. Johnson, J. Am. Chem. Soc. 2013, 135(30), 11055–11062.
- [107] M. D. Anderson, C. L. Heideman, Q. Lin, M. Smeller, R. Kokenyesi, A. a. Herzing, I. M. Anderson, D. a. Keszler, P. Zschack, D. C. Johnson, Angew. Chem. Int. Ed 2013, 125, 2036–2039.

- [108] M. Falmbigl, A. Fiedler, R. E. Atkins, S. F. Fischer, D. C. Johnson, *Nano Lett.* 2015, 15, 943–948.
- [109] D. M. Hamann, A. C. Lygo, M. Esters, D. R. Merrill, J. Ditto, D. R. Sutherland,
 S. R. Bauers, D. C. Johnson, ACS Nano 2018, 12(2), 1285–1295.
- [110] S. P. Rudin, D. C. Johnson, *Phys. Rev. B* **2015**, *91*(14), 144203.
- [111] E. von Horschek, W. Klemm, Z. anorg. allg. Chem. 1939, 242, 49–62.
- [112] C. Riekel, J. Solid State Chem. 1976, 17(4), 389–392.
- [113] I. S. Braude, A. A. Mamalui, O. N. Onishko, J. Alloys Compd. 2009, 486(1-2), 859–863.
- [114] M. Bremholm, Y. S. Hor, R. J. Cava, Solid State Sci. 2011, 13(1), 38–41.
- [115] M. Falmbigl, D. Putzky, J. Ditto, M. Esters, S. R. Bauers, F. Ronning, D. C. Johnson, ACS Nano 2015, 9(8), 8440–8448.
- [116] T. Chattopadhyay, J. Pannetier, H. G. Von Schnering, J. Phys. Chem. Solids 1986, 47(9), 879–885.
- M. B. Alemayehu, M. Falmbigl, K. Ta, C. Grosse, R. D. Westover, S. R. Bauers, S. F. Fischer, D. C. Johnson, *Chem. Mater.* 2015, 27, 867–875.
- [118] D. B. Moore, M. Beekman, S. Disch, D. C. Johnson, Angew. Chem. Int. Ed 2014, 126(22), 5778–5781.
- [119] I. V. Golosovsky, M. Tovar, U. Hoffman, I. Mirebeau, F. Fauth, D. a. Kurdyukov, Y. a. Kumzerov, *JETP Letters* 2006, 83(7), 298–301.
- [120] M. Esters, Dissertation, University of Oregon, 2017.
- [121] A. Le Bail, H. Duroy, J. Fourquet, Mater. Res. Bull. 1988, 23(3), 447–452.
- [122] G. Wiegers, *Physica* B+C **1980**, 99(1-4), 151–165.
- [123] G. C. Tewari, M. Karppinen, A. K. Rastogi, J. Solid State Chem. 2013, 198, 108–113.
- [124] L. M. Kulikov, A. A. Semjonov-Kobzar, M. M. Antonova, A. A. Chechovsky, L. G. Akselrud, R. V. Skolozdra, D. Fruchart, J. L. Soubeyroux, J. Alloys Compd. 1996, 244 (96), 11–15.

- [125] J. V.-v. D. Berg, R. Sherwood, J. Phys. Chem. Solids 1971, 32, 167–173.
- [126] N. S. Gunning, T. Dankwort, M. Falmbigl, U. Ross, G. Mitchson, D. M. Hamann, A. Lotnyk, L. Kienle, D. C. Johnson, *Chem. Mater.* 2017, 29(19), 8292– 8298.
- [127] G. E. Lloyd, *Mineralogical Magazine* **1987**, *51*, 3–19.
- [128] C. Grosse, M. B. Alemayehu, M. Falmbigl, A. Mogilatenko, O. Chiatti, D. C. Johnson, S. F. Fischer, Sci. Rep. 2016, 6, 33457.
- [129] Z. Liu, Z. Fei, C. Xu, Y. Jiang, X.-L. Ma, H.-M. Cheng, W. Ren, Nanoscale 2017, 9, 7501–7507.
- [130] S. Susarla, J. A. Hachtel, X. Yang, A. Kutana, A. Apte, Z. Jin, R. Vajtai, J. C. Idrobo, J. Lou, B. I. Yakobson, C. S. Tiwary, Adv. Mater. 2018, 1804218, 1–6.
- [131] S. Singh, N. Khare, Appl. Surf. Sci. 2016, 364, 783–788.
- [132] S. Kattel, G. Wang, J. Chem. Phys. **2014**, 141(12).
- [133] P. Strasser, S. Koh, T. Anniyev, J. Greeley, K. More, C. Yu, Z. Liu, S. Kaya, D. Nordlund, H. Ogasawara, M. F. Toney, A. Nilsson, *Nat. Chem.* 2010, 2(6), 454–460.
- [134] H. Huang, H. Jia, Z. Liu, P. Gao, J. Zhao, Z. Luo, J. Yang, J. Zeng, Angew. Chem. Int. Ed 2017, 3594–3598.
- [135] A. Mayence, M. Wéry, D. T. Tran, E. Wetterskog, P. Svedlindh, C.-W. Tai,
 L. Bergström, *Nanoscale* 2016, *8*, 14171–14177.
- [136] N. Pathak, S. K. Gupta, C. L. Prajapat, S. K. Sharma, P. S. Ghosh, B. Kanrar,
 P. K. Pujari, R. M. Kadam, *Phys. Chem. Chem. Phys.* 2017, 19(19), 11975–11989.
- [137] L. Dubau, J. Nelayah, S. Moldovan, O. Ersen, P. Bordet, J. Drnec, T. Asset, R. Chattot, F. Maillard, ACS Catalysis 2016, 6(7), 4673–4684.
- [138] X. Huang, W. Yang, R. Harder, Y. Sun, M. Lu, Y. S. Chu, I. K. Robinson,
 H. K. Mao, *Nano Letters* 2015, 15(11), 7644–7649.
- [139] S. K C, C. Zhang, S. Hong, R. M. Wallace, K. Cho, 2D Materials 2015, 2(3), 035019.

- [140] C. Cepeda-Jiménez, J. Beltrán, A. Hernando, M. García, F. Ynduráin, A. Zhilyaev, M. Pérez-Prado, Acta Mater. 2017, 123, 206–213.
- [141] D. Srivastava, G. C. Tewari, M. Karppinen, J. Phys.: Condens. Matter 2014, 26(50), 505501.
- [142] C. F. van Bruggen, R. J. Haange, G. A. Wiegers, D. K. G. de Boer, *Physica B+C* 1980, 99(1-4), 166–172.
- [143] D. C. Freitas, M. Núñez, P. Strobel, A. Sulpice, R. Weht, A. A. Aligia, M. Núñez-Regueiro, Phys. Rev. B 2013, 87(1), 1–9.
- [144] R. Atkins, J. Wilson, P. Zschack, C. Grosse, W. Neumann, D. C. Johnson, *Chem. Mater.* 2012, 24 (23), 4594–4599.
- [145] S. R. Wood, D. R. Merrill, M. Falmbigl, D. B. Moore, J. Ditto, M. Esters, D. C. Johnson, *Chem. Mater.* 2015, 27(17), 6067–6076.
- [146] C. A. F. Vaz, J. A. C. Bland, G. Lauhoff, *Rep. Prog. Phys.* **2008**, *71*(5), 056501.
- [147] S. M. Clarke, D. E. Freedman, *Inorg. Chem.* **2015**, *54*(6), 2765–2771.
- [148] Y. Koh, S. Cho, J. Lee, L.-X. Yang, Y. Zhang, C. He, F. Chen, D.-L. Feng, M. Arita, K. Shimada, H. Namatame, M. Taniguchi, C. Kim, Jpn. J. Appl. Phys., Part 1 2013, 52(10S), 10MC15.
- [149] G. C. Tewari, T. S. Tripathi, A. K. Rastogi, *eprint arXiv:1109.1071* **2011**, 1–9.
- [150] M. Beekman, G. Rodriguez, R. Atkins, J. Kunert, D. B. Moore, D. C. Johnson, J. Appl. Phys. 2015, 117(18).
- [151] L. Zhang, J. Fan, X. Zhu, W. Ning, Z. Qu, M. Ge, L. Pi, Y. Zhang, Appl. Phys. A 2013, 113(1), 201–206.
- [152] P. S. Behera, P. A. Bhobe, A. K. Nigam, in DAE Solid State Physics Symposium 2015, 130009–1–3.
- [153] K. Ramasamy, H. Sims, S. Keshavarz, N. Naghibolashrafi, A. Gupta, J. Mater. Chem. C 2016, 4(16), 3628–3639.
- [154] V. N. Berzhansky, N. A. Drokin, V. I. Ivanov, V. P. Kononov, I. S. Edelman, S. A. Havrichkov, V. K. Chernov, A. G. Shishkov, A. M. Pirogova, *Thin Solid Films* 1990, 190, 199–215.

- [155] F. K. Lotgering, R. P. Stapele, Solid State Commun. 1967, 5, 143–146.
- [156] I. Nakatani, H. Nose, K. Masumoto, J. Phys. Chem. Solids 1978, 39, 743–749.
- [157] M. Robbins, H. Lehmann, J. White, J. Phys. Chem. Solids 1967, 28(6), 897– 902.
- [158] T. Kanomata, I. Hideaki, J. Phys. Soc. Jpn. 1970, 29(2), 332–335.
- [159] L. Zhang, L. Ling, J. Fan, R. Li, S. Tan, Y. Zhang, J. Appl. Phys. 2011, 109(11), 113911.
- [160] Y.-H. Wang, Dissertation, University of Alabama, 2010.
- [161] Y.-H. A. Wang, N. Bao, L. Shen, P. Padhan, A. Gupta, J. Am. Chem. Soc. 2007, 129(41), 12408–12409.
- [162] A. I. Pankrats, A. M. Vorotynov, V. I. Tugarinov, S. M. Zharkov, D. A. Velikanov, G. M. Abramova, G. M. Zeer, K. Ramasamy, A. Gupta, J. Appl. Phys. 2014, 116(5), 054302.
- [163] J. B. Goodenough, Solid State Commun. 1967, 5(8), 577–580.
- [164] C. Colominas, *Phys. Rev.* **1967**, *153*(2), 558–560.
- [165] H. Yokoyama, R. Watanabe, J. Phys. Soc. Jpn. 1967, 23, 450.
- [166] A. Kimura, J. Matsuno, J. Okabayashi, A. Fujimori, T. Shishidou, E. Kulatov, T. Kanomata, *Phys. Rev. B* 2001, 63(22), 2244201–2244207.
- [167] Y. H. Wang, A. Gupta, M. Chshiev, W. H. Butler, App. Phys. Lett. 2008, 92(6), 2–5.
- [168] M. Liberati, J. R. Neulinger, R. V. Chopdekar, J. S. Bettinger, E. Arenholz, W. H. Butler, A. M. Stacy, Y. I. Idzerda, Y. Suzuki, J. Appl. Phys. 2008, 103(7), 2–5.
- [169] T. Saha-Dasgupta, M. De Raychaudhury, D. D. Sarma, Phys. Rev. B 2007, 76(5), 054441.
- [170] S. Bordács, I. Kézsmárki, K. Ohgushi, Y. Tokura, New J. Phys. 2010, 12.
- [171] M. Winterberger, Y. Allain, Solid State Commun. 1987, 64 (11), 1343–1346.

- [172] G. C. Tewari, T. S. Tripathi, H. Yamauchi, M. Karppinen, Mater. Chem. Phys. 2014, 145(1-2), 156–161.
- [173] G. C. Tewari, M. Karppinen, A. K. Rastogi, J. Solid State Chem. 2013, 198, 108–113.
- [174] C. M. Fang, C. F. van Bruggen, R. A. de Groot, G. A. Wiegers, C. Haas, J. Phys.: Condens. Matter 1997, 9(46), 10173–10184.
- [175] J. Sugiyama, H. Nozaki, I. Umegaki, T. Uyama, K. Miwa, J. H. Brewer, S. Kobayashi, C. Michioka, H. Ueda, K. Yoshimura, *Phys. Rev. B* 2016, 94(1), 1–5.
- [176] D. Srivastava, G. C. Tewari, M. Karppinen, R. M. Nieminen, J. Phys.: Condens. Matter 2013, 25(10), 105504.
- [177] A. Gagor, D. Gnida, A. Pietraszko, Mater. Chem. Phys. 2014, 146(3), 283– 288.
- [178] P. Bongers, C. Van Bruggen, J. Koopstra, W. Omloo, G. Wiegers, F. Jellinek, J. Phys. Chem. Solids 1968, 29(6), 977–984.
- [179] H. Y. Lv, W. J. Lu, D. F. Shao, Y. Liu, Y. P. Sun, Phys. Rev. B 2015, 92(21), 1–8.
- [180] A. Zameshin, I. A. Makhotkin, S. N. Yakunin, R. W. E. van de Kruijs, A. E. Yakshin, F. Bijkerk, J. Appl. Cryst. 2016, 49, 1300–1307.
- [181] O. Balmes, R. van Rijn, D. Wermeille, A. Resta, L. Petit, H. Isern, T. Dufrane, R. Felici, *Catal. Today* 2009, 145(3-4), 220–226.
- [182] J. Drnec, T. Zhou, S. Pintea, W. Onderwaater, E. Vlieg, G. Renaud, R. Felici, J. Appl. Cryst. 2014, 47(1), 365–377.
- [183] S. Roobol, W. Onderwaater, J. Drnec, R. Felici, J. Frenken, J. Appl. Cryst. 2015, 48(4), 1–6.
- [184] S. Mattauch, A. Koutsioubas, S. Pütter, J. large-scale research facilities 2015, 8(1), 1–4.
- [185] M. Schaffer, B. Schaffer, Q. Ramasse, Ultramicroscopy 2012, 114, 62–71.
- [186] R. M. Langford, M. Rogers, *Micron* **2008**, *39*, 1325–1330.

- [187] C. A. Schneider, W. S. Rasband, K. W. Eliceiri, Nat. Methods 2012, 9(7), 671–675.
- [188] H. M. Rietveld, J. Appl. Cryst. 1969, 2, 65–71.
- [189] A. Larson, R. Von Dreele, General Structure Analysis System (GSAS), 2000.
- [190] B. H. Toby, J. Appl. Cryst. 2001, 34(2), 210–213.

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